

High Performance Visible & Infrared Sensors for Exoplanet Astronomy

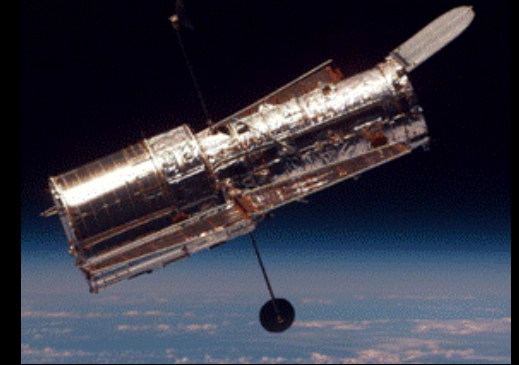
James W. Beletic
Teledyne Imaging Sensors

19 August 2010



Teledyne

Providing the best images
of the Universe



Credits and sincere thanks for information provided by the following organizations



e2v

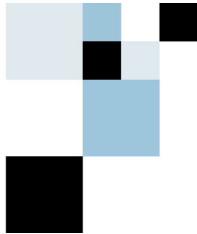
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Paul Jordan



MIT Lincoln Laboratory

Barry Burke
Vyshnavi Suntharalingham



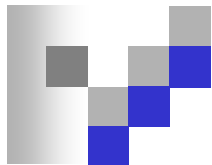
Fairchild Imaging

Paul Vu



**Semiconductor
Technology Associates**

Dick Bredthauer



Sarnoff

James Janesick

Disclaimer

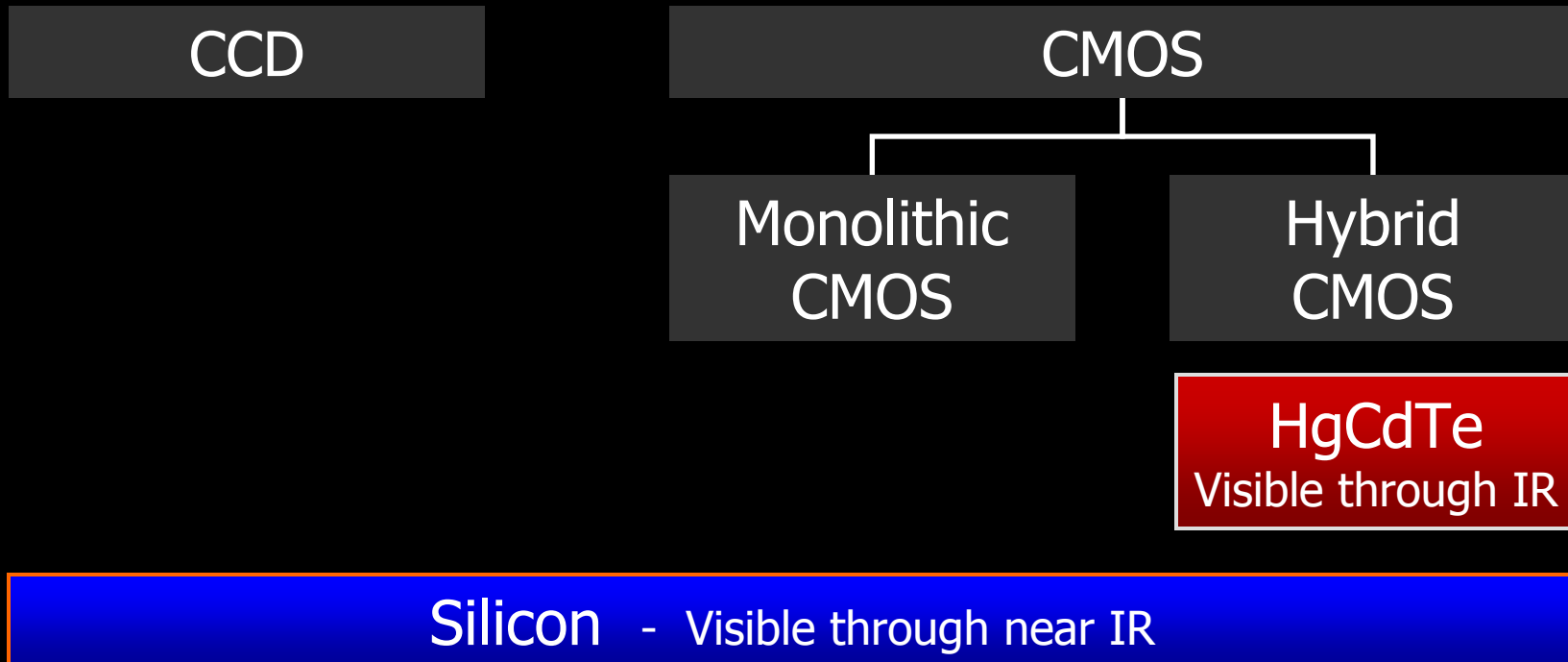
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The Ideal Detector for High Resolution Spectroscopy

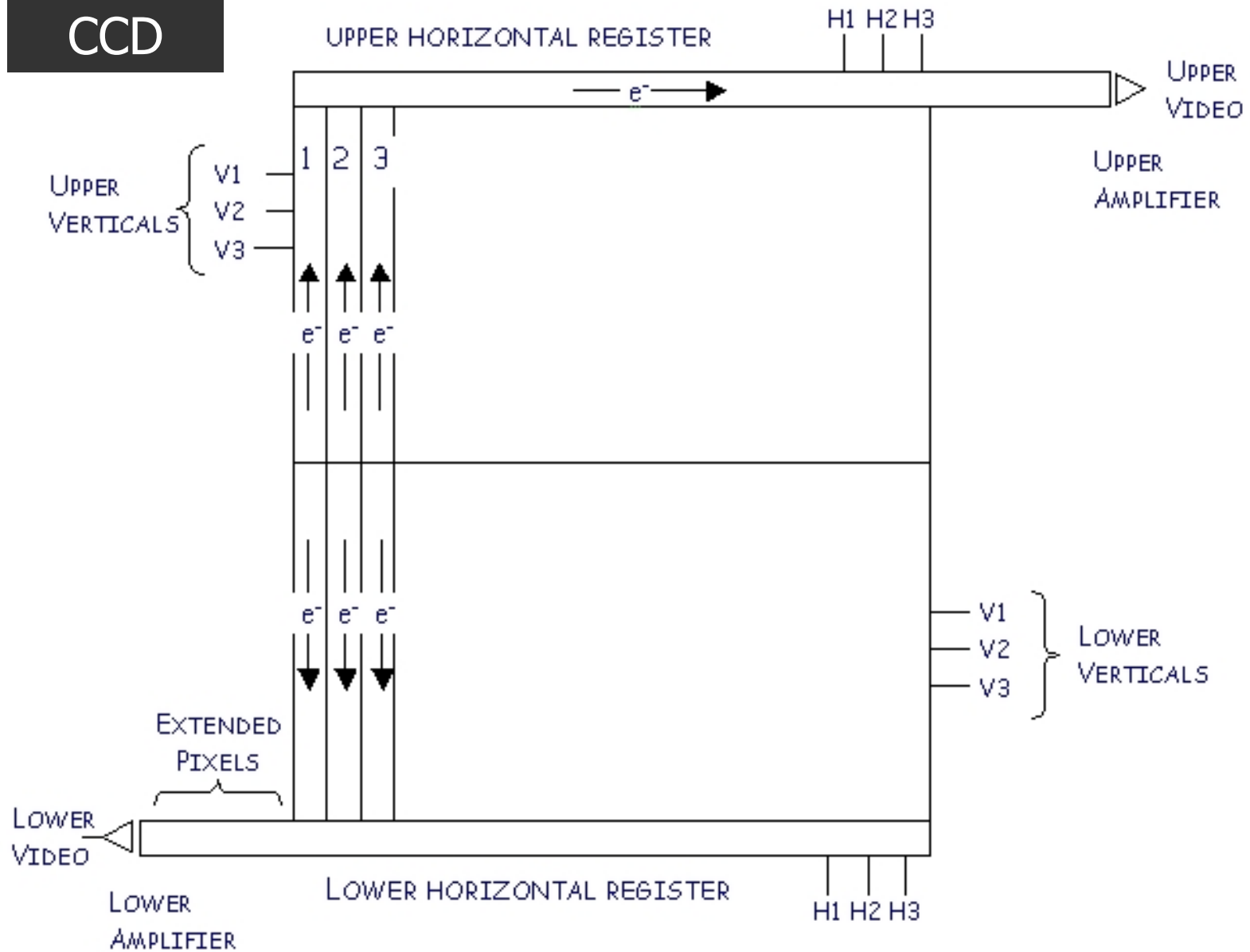
- Detect 100% of photons
 - Each photon detected as a delta function
 - Large number of pixels
 - All pixels of equal size
 - Record charge where detected (i.e. no blurring within detector)
 - No noise other than photon noise
 - Time tag for each photon
 - Measure photon wavelength
 - Measure photon polarization
- ✓ Up to 98% quantum efficiency
 - ✓ One electron for each photon
 - ✓ 2K×2K, 2K×4K, 4K×4K, 10K×10K
Gigapixel mosaics possible
 - ✓ Mostly true (watch for stitch boundaries)
 - ✗ Charge diffusion, charge transfer inefficiency (CTI), electrical crosstalk
 - ✗ Dark current, readout noise
 - ✗ No – framing detectors
 - ✗ No – defined by filter
 - ✗ No – defined by filter

Plus numerous other “features”: poorly operating pixels (cosmetics), hot pixels, charge traps, persistence (latency), etc.

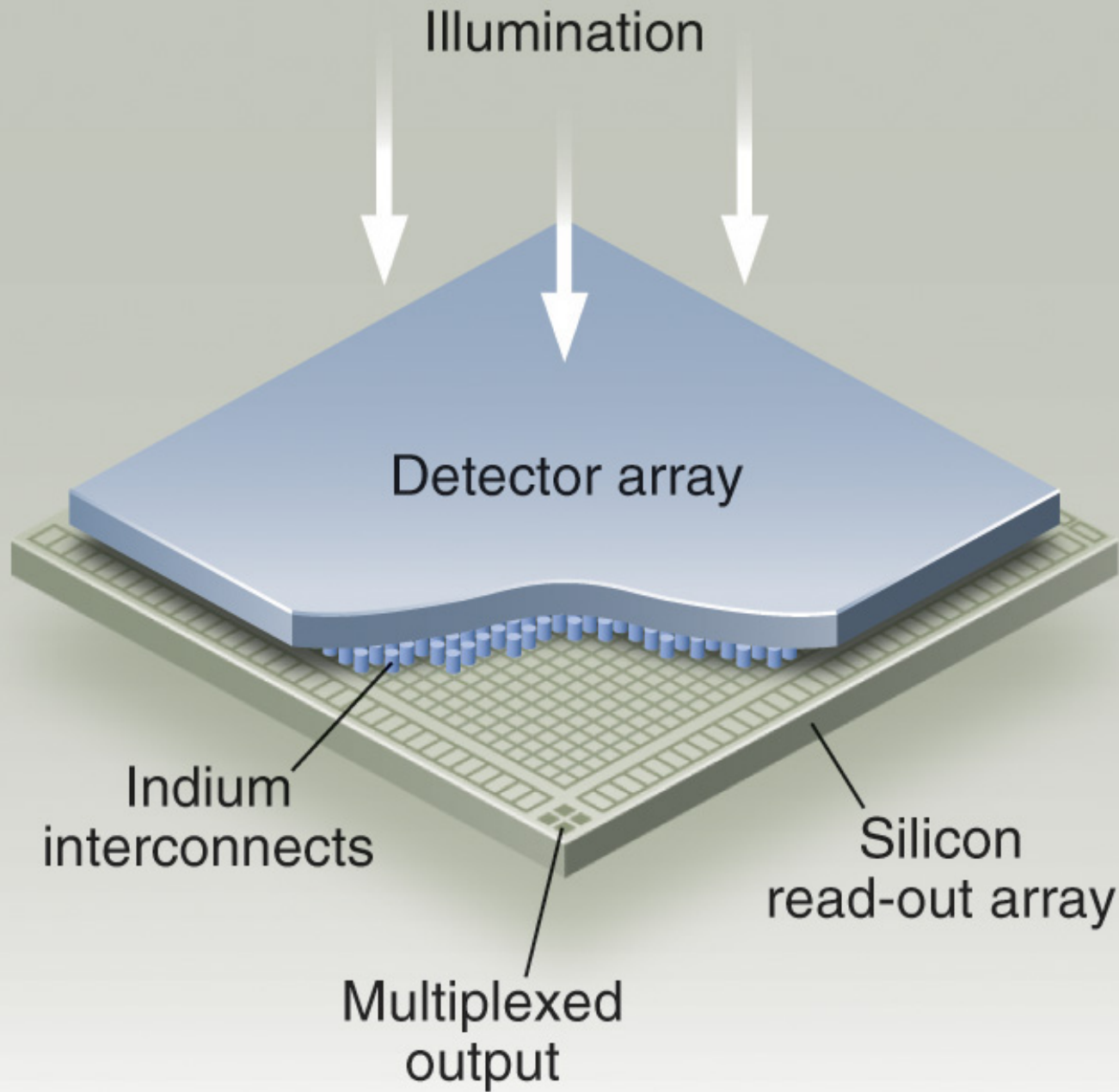
Basic Types of Imaging Sensors

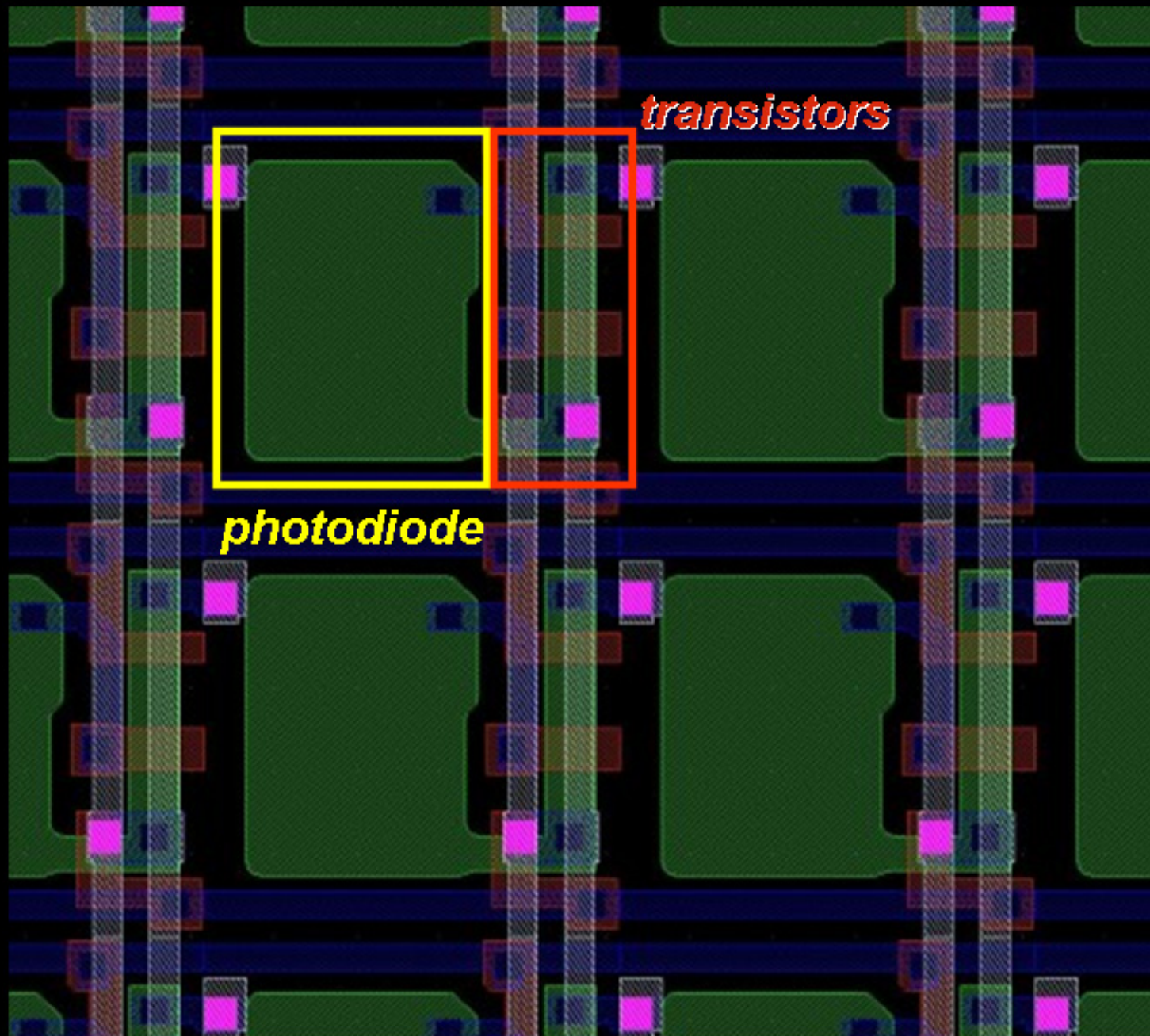


CCD

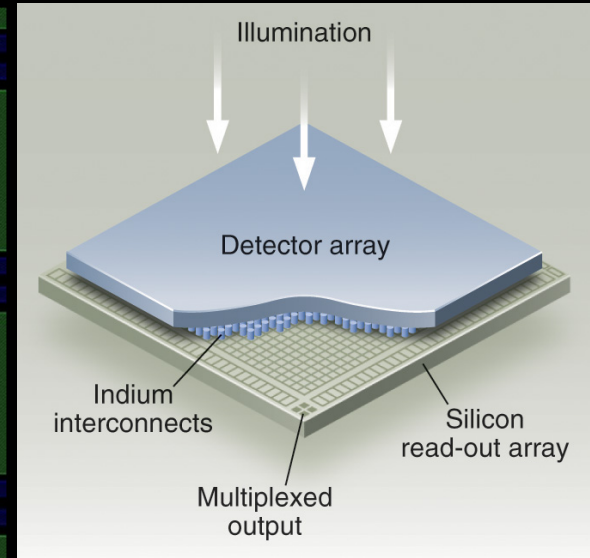
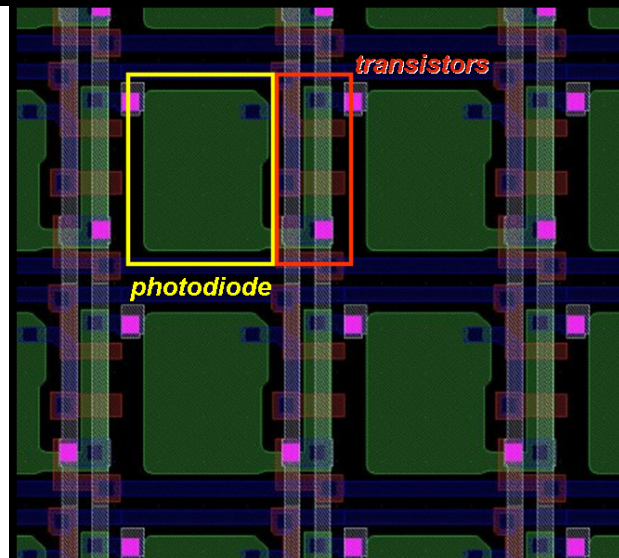
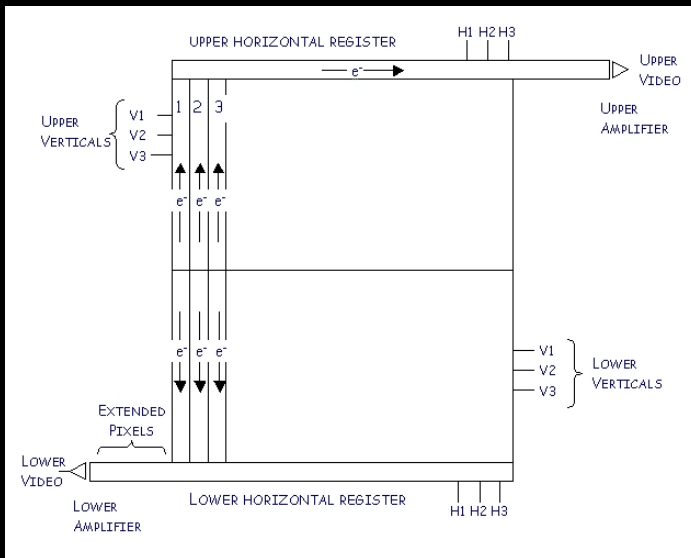


Hybrid CMOS





Monolithic
CMOS



CCD

Monolithic CMOS

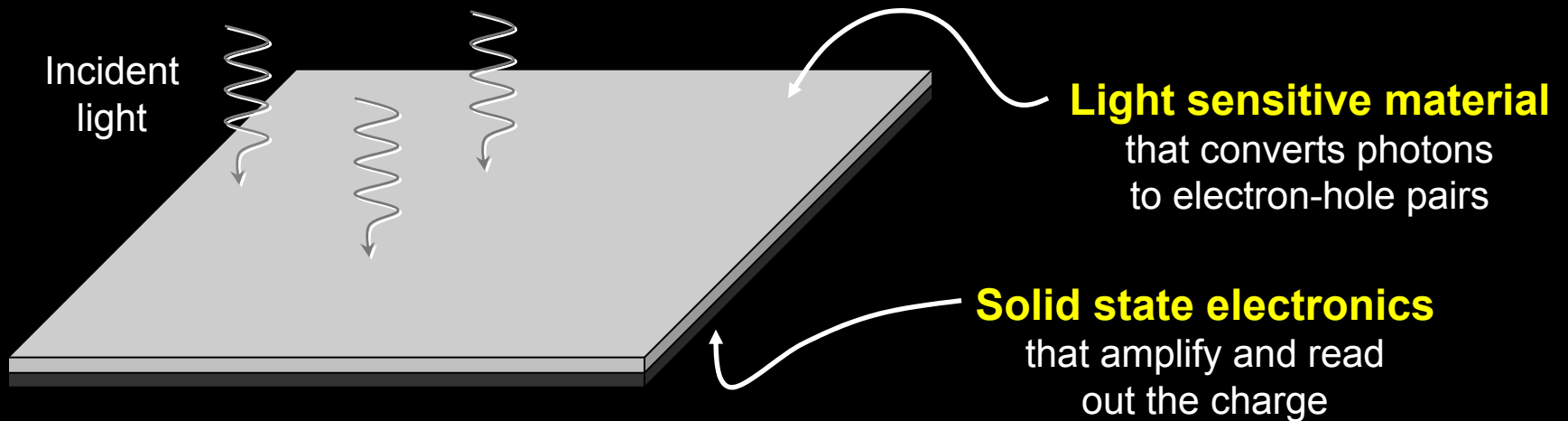
Hybrid CMOS

HgCdTe
Visible through IR

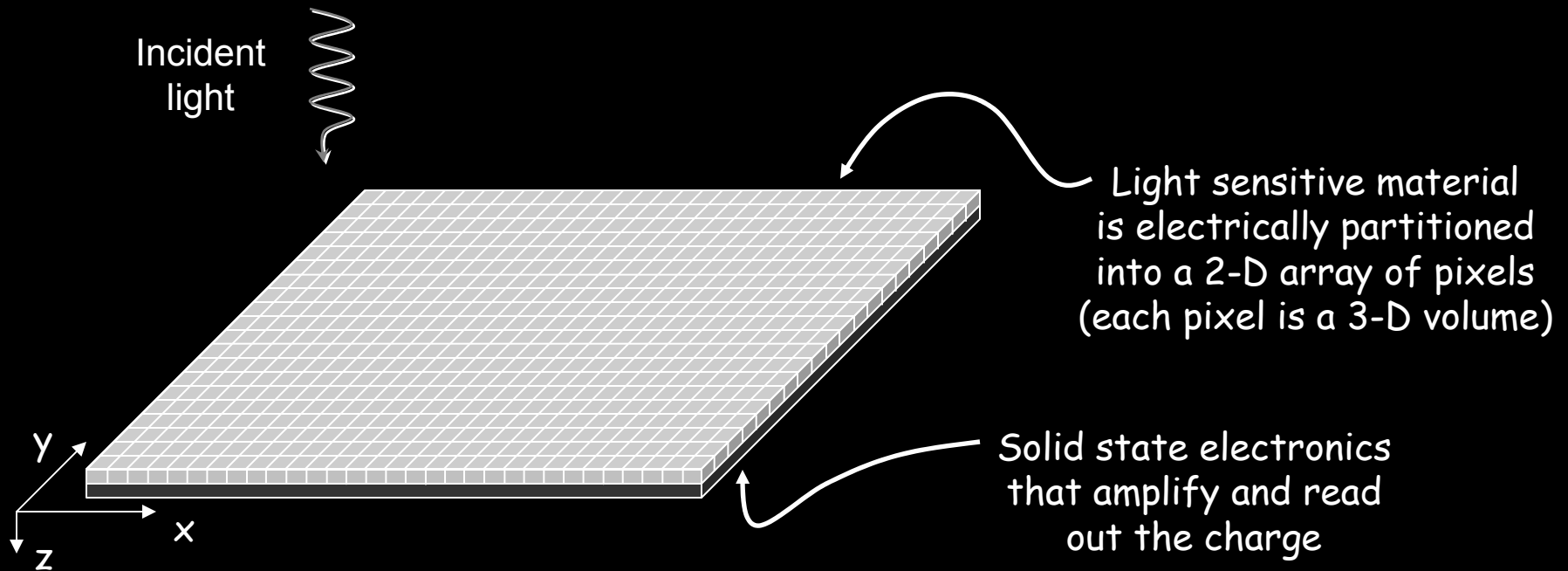
Silicon - Visible through near IR

Two main parts of an imaging detector

Detector material & Solid state electronics

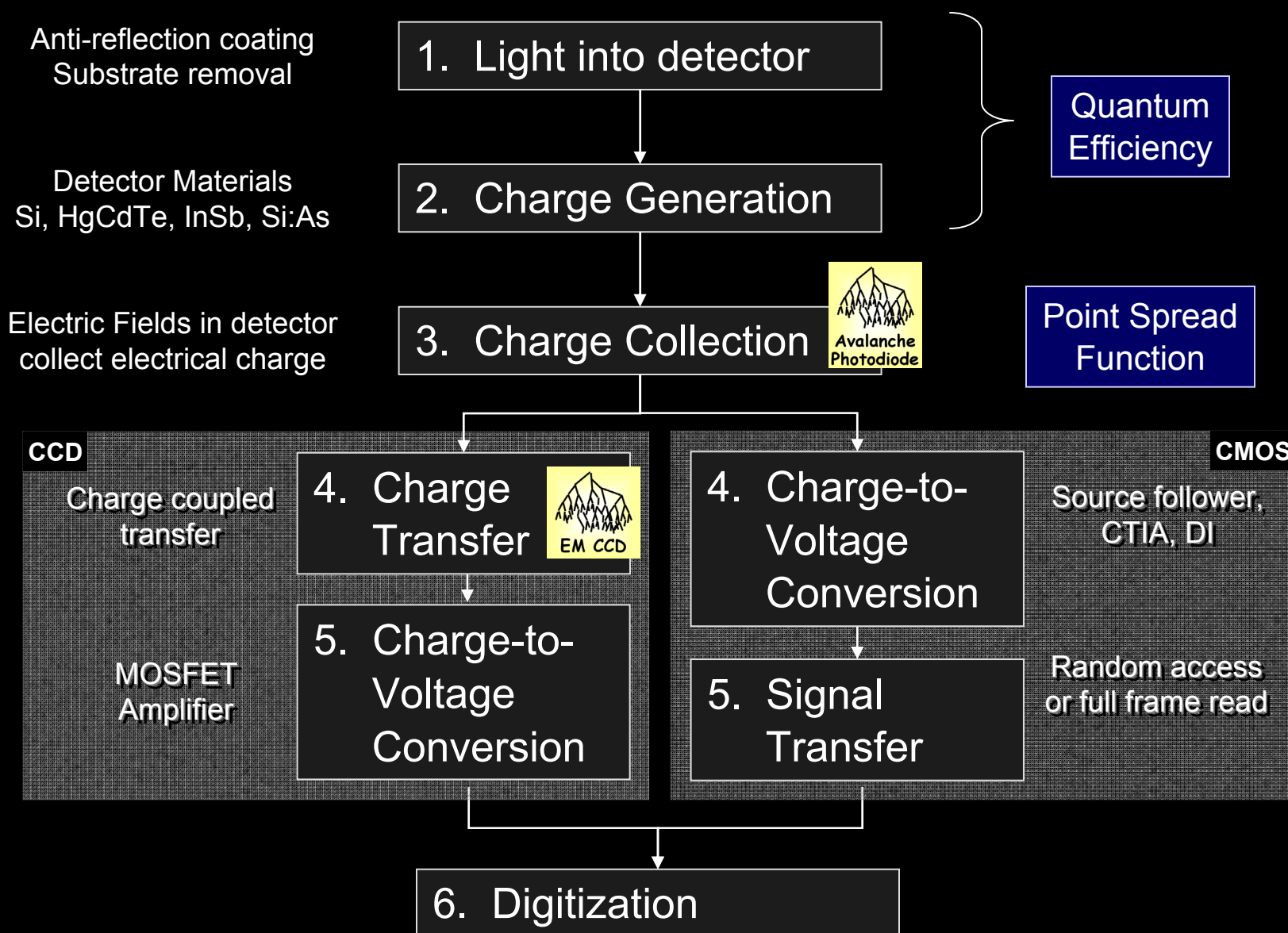


Charge Collection

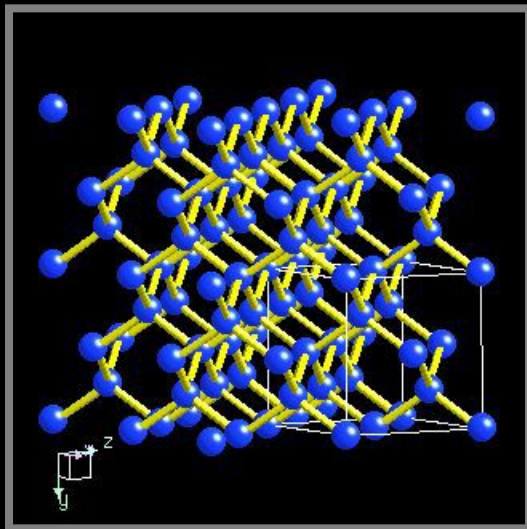
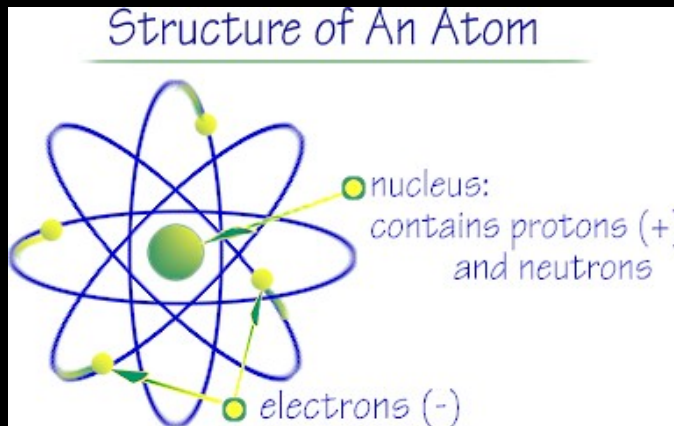


- Intensity image is generated by collecting photocharge generated in 3-D volume into 2-D array of pixels.
- Optical and IR focal plane arrays both collect charges via electric fields.
- In the z-direction, optical and IR use a p-n junction to “sweep” charge toward pixel collection nodes.

6 steps of optical / IR photon detection



Crystals are excellent detectors of light



Silicon crystal lattice

- Simple model of atom
 - Protons (+) and neutrons in the nucleus with electrons orbiting
- Electrons are trapped in the crystal lattice
 - by electric field of protons
- Light energy can free an electron from the grip of the protons, allowing the electron to roam about the crystal
 - creates an “electron-hole” pair.
- The photocharge can be collected and amplified, so that light is detected
- The light energy required to free an electron depends on the material.

Periodic Table

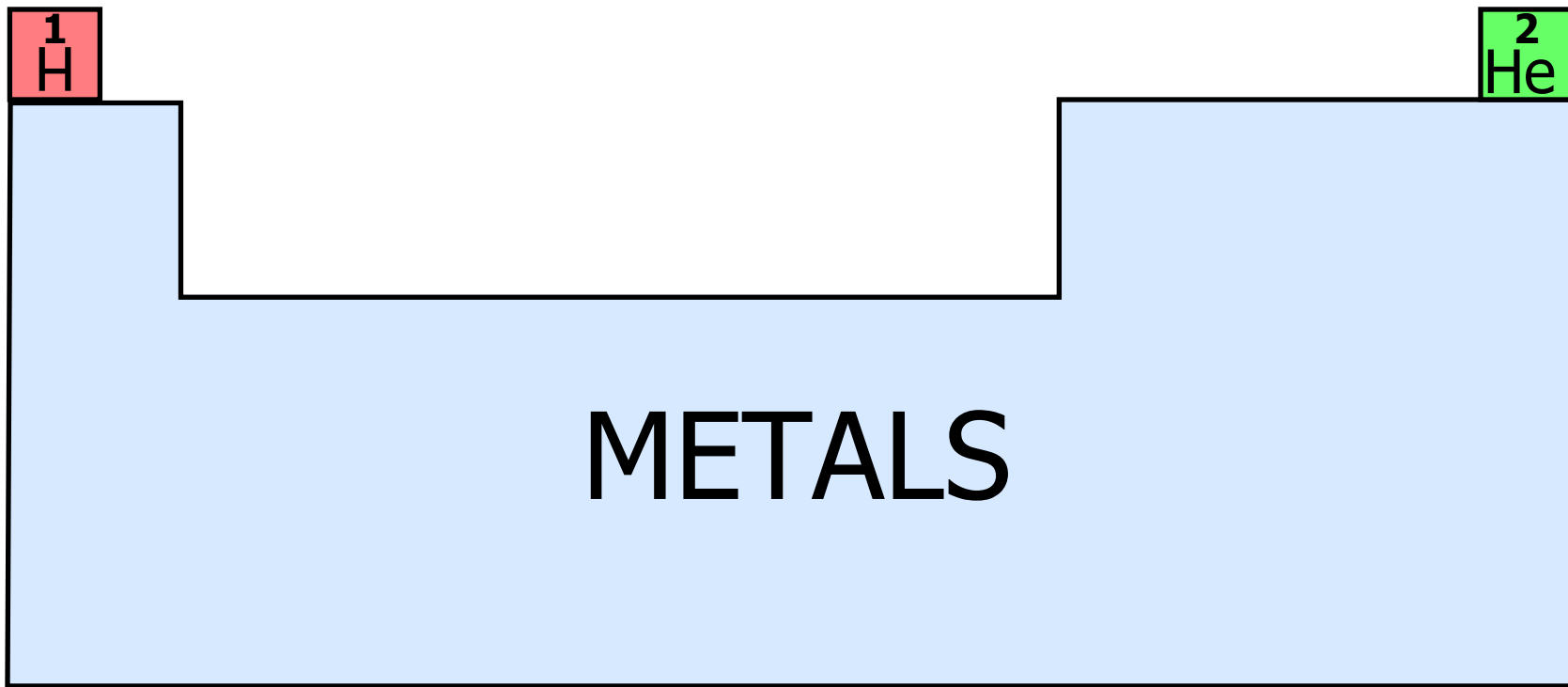
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19 K Potassium 39.1	20 Ca Calcium 40.2	21 Sc Scandium 45.0	22 Ti Titanium 47.9	23 V Vanadium 50.9	24 Cr Chromium 52.0	25 Mn Manganese 54.9	26 Fe Iron 55.9	27 Co Cobalt 58.9	28 Ni Nickel 58.7	29 Cu Copper 63.5	30 Zn Zinc 65.4	31 Ga Gallium 69.7	32 Ge Germanium 72.6	33 As Arsenic 74.9	34 Se Selenium 79.0	35 Br Bromine 79.9	36 Kr Krypton 83.8
37 Rb Rubidium 85.5	38 Sr Strontium 87.6	39 Y Yttrium 88.9	40 Zr Zirconium 91.2	41 Nb Niobium 92.9	42 Mo Molybdenum 95.9	43 Tc Technetium 99	44 Ru Ruthenium 101.0	45 Rh Rhodium 102.9	46 Pd Palladium 106.4	47 Ag Silver 107.9	48 Cd Cadmium 112.4	49 In Indium 114.8	50 Sn Tin 118.7	51 Sb Antimony 121.8	52 Te Tellurium 127.6	53 I Iodine 126.9	54 Xe Xenon 131.3
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Types of Elements Key:

- Alkali metals
- Alkaline earth metals
- Transition metals
- Lanthanides
- Actinides
- Poor metals
- Semi-metals
- Non-metals
- Noble gases

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89 Ac Actinium 132.9	90 Th Thorium 232.0	91 Pa Protactinium 231.0	92 U Uranium 238.0	93 Np Neptunium 237.0	94 Pu Plutonium 242.0	95 Am Americium 243.0	96 Cm Curium 247.0	97 Bk Berkelium 247.0	98 Cf Californium 251.0	99 Es Einsteinium 254.0	100 Fm Fermium 253.0	101 Md Mendelevium 258.0	102 No Nobelium 254.0	103 Lr Lawrencium 257.0

The Astronomer's Periodic Table



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Detector Families

Si - IV semiconductor
HgCdTe - II-VI semiconductor
InGaAs & InSb - III-V semiconductors

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	Alkaline earth metals
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	Lanthanides
	Actinides
	Post metals
	Semi-metals
	Non-metals
	Noble gases

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Photon Detection

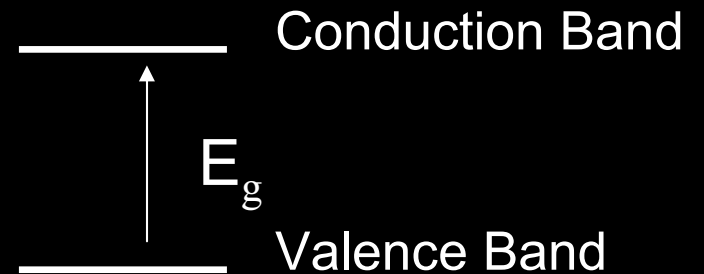
For an electron to be excited from the conduction band to the valence band

$$h\nu > E_g$$

h = Planck constant (6.6310^{-34} Joule•sec)

ν = frequency of light (cycles/sec) = λ/c

E_g = energy gap of material (electron-volts)

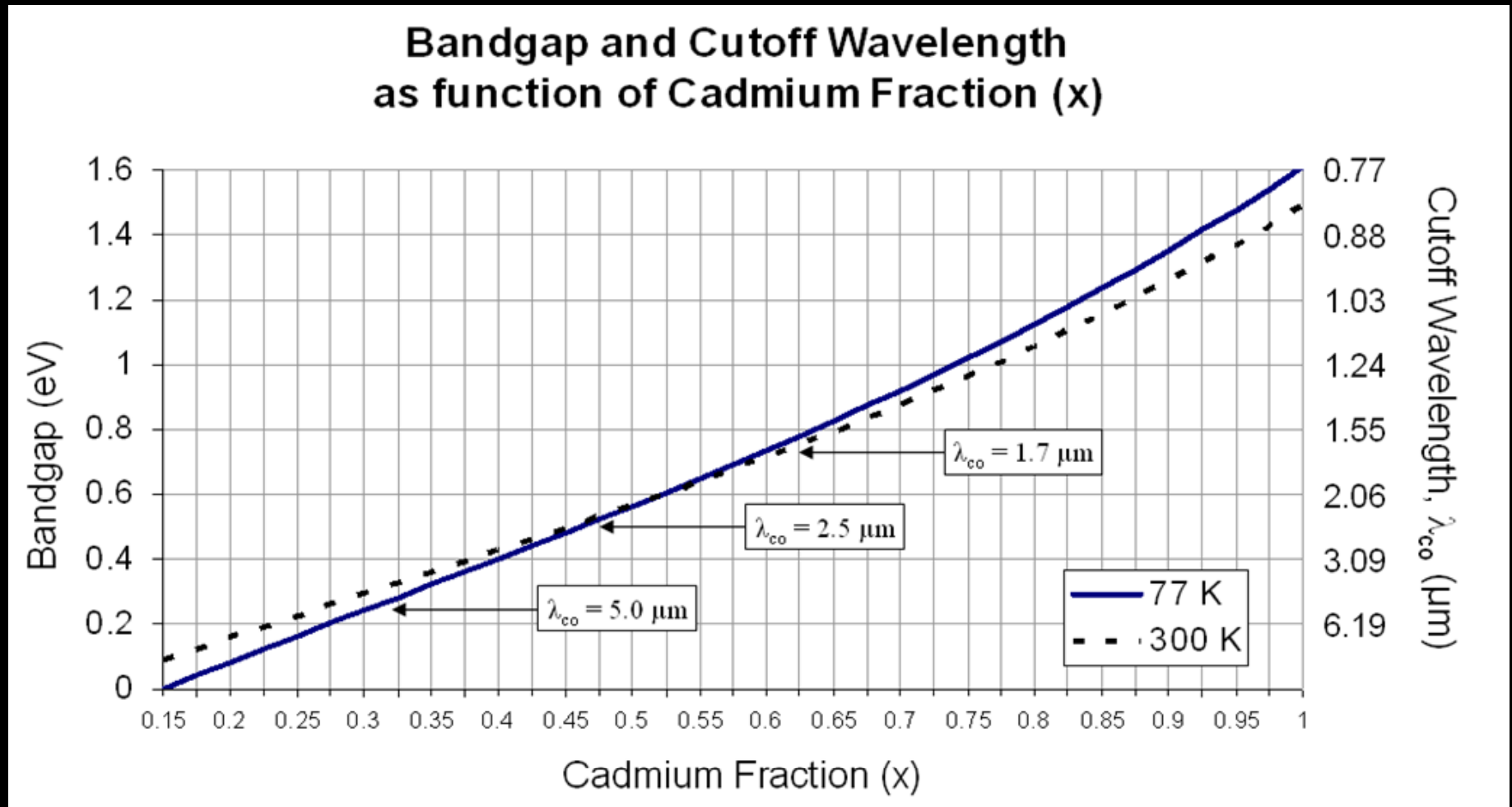


$$\lambda_c = 1.238 / E_g \text{ (eV)}$$

Material Name	Symbol	E_g (eV)	λ_c (μm)
Silicon	Si	1.12	1.1
Indium Antimonide	InSb	0.23	5.5
Mer-Cad-Tel	HgCdTe	1.00 – 0.07	1.24 – 18

Tunable Wavelength: Valuable property of HgCdTe

$\text{Hg}_{1-x}\text{Cd}_x\text{Te}$ Modify ratio of Mercury and Cadmium to “tune” the bandgap energy



$$E_g = -0.302 + 1.93x - 0.81x^2 + 0.832x^3 + 5.35 \times 10^{-4} T(1 - 2x)$$

G. L. Hansen, J. L. Schmidt, T. N. Casselman, J. Appl. Phys. 53(10), 1982, p. 7099

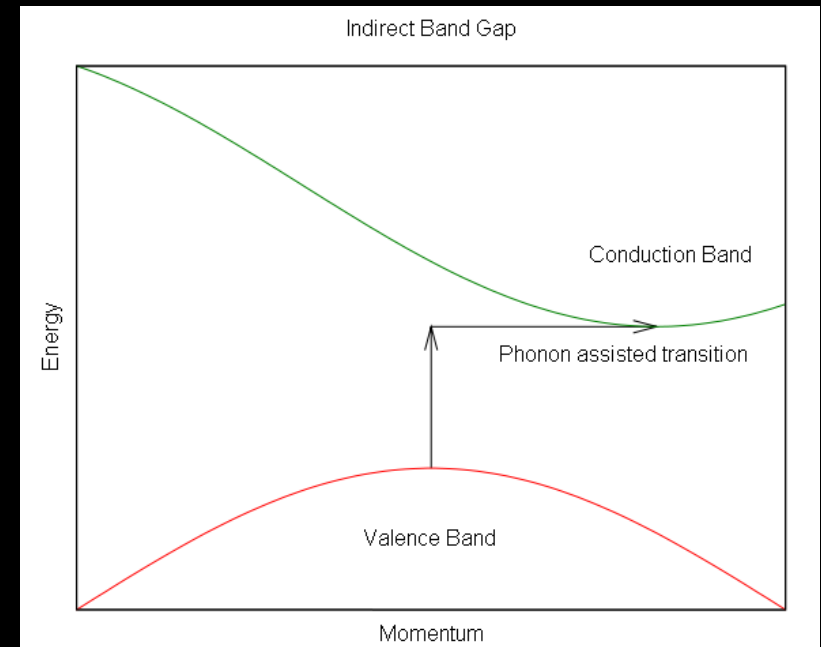
Absorption Depth

The depth of detector material that absorbs 63.2% of the radiation
($1-1/e$) of the energy is absorbed

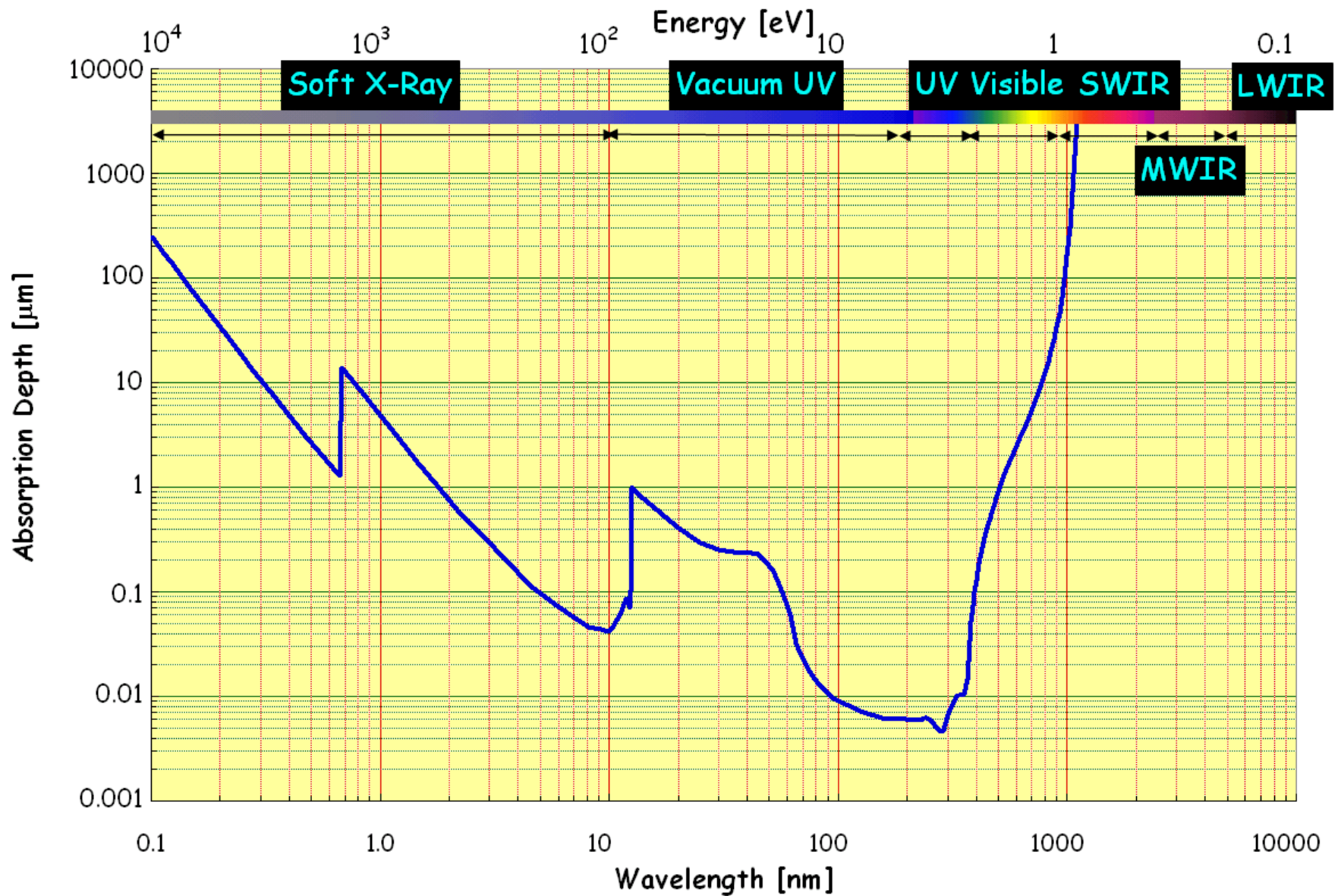
1	absorption depth(s)	63.2% of light absorbed
2		86.5%
3		95.0%
4		98.2%

For high QE, thickness of detector material should be ≥ 3 absorption depths

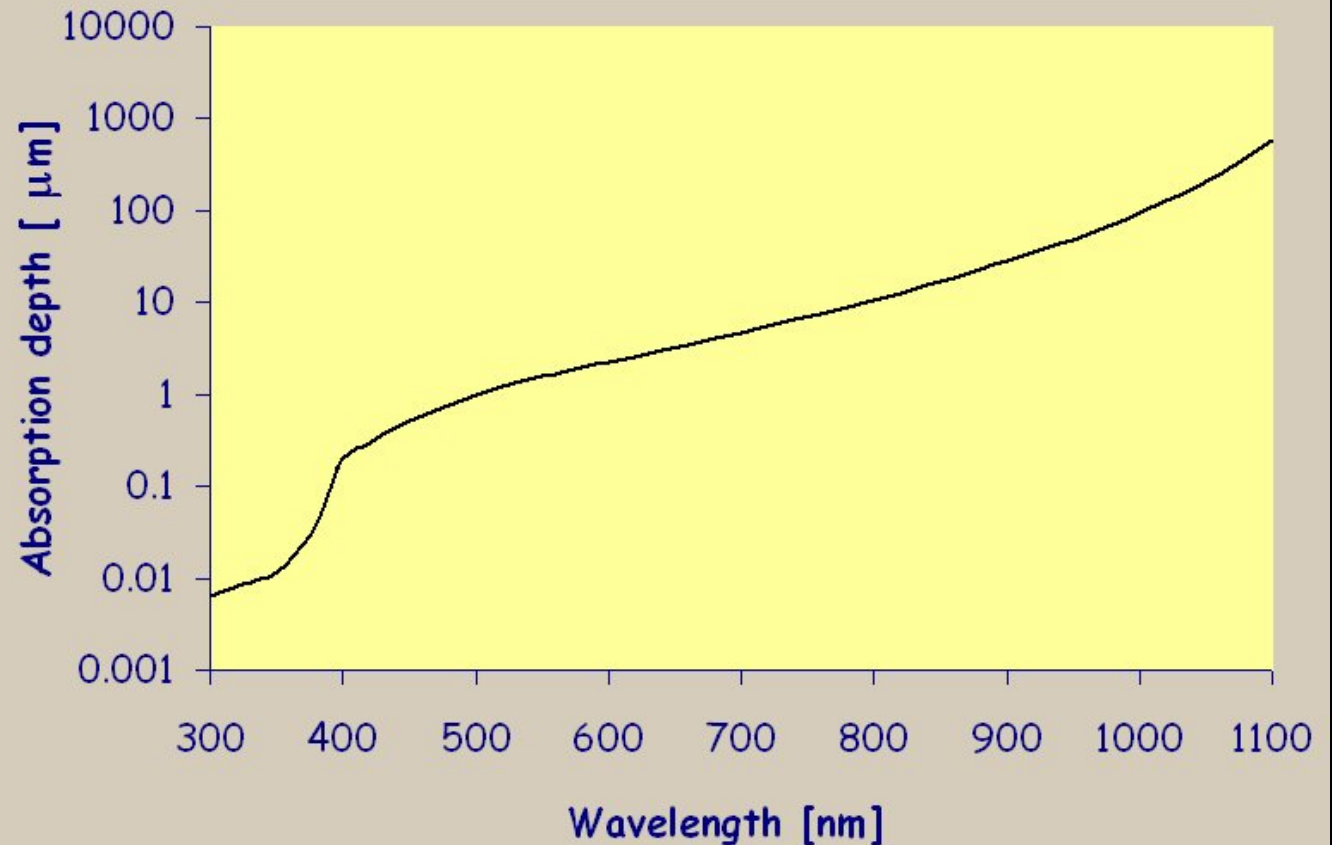
Silicon is an indirect bandgap material and is a poor absorber of light as the photon energy approaches the bandgap energy. For an indirect bandgap material, both the laws of conservation of energy and momentum must be observed. To excite an electron from the valence band to the conduction band, silicon must simultaneously absorb a photon and a phonon that compensates for the missing momentum vector.



Absorption Depth of Light in Silicon

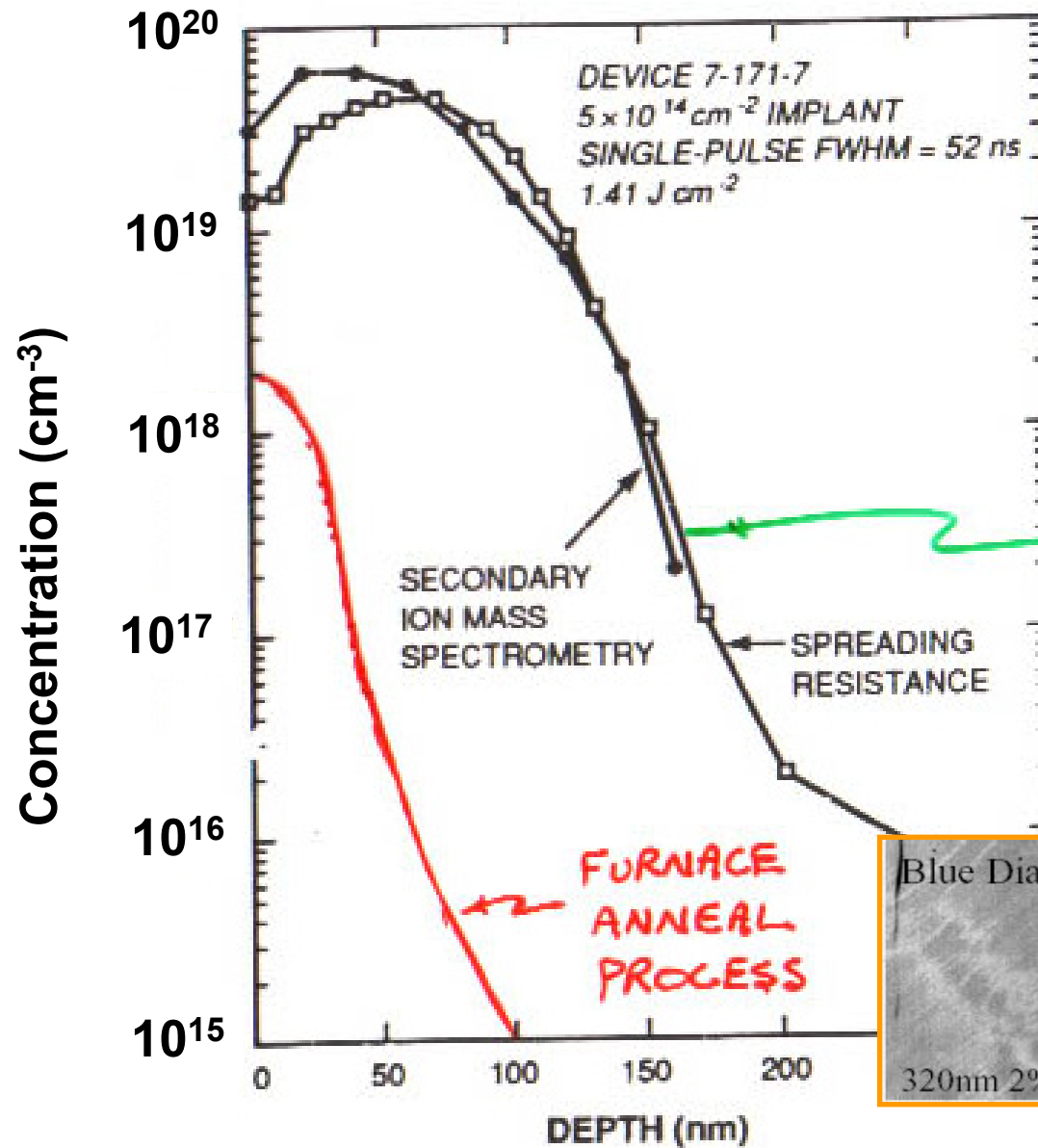


Absorption Depth of Silicon



- For high QE in the near infrared, need very thick (up to 300 microns) silicon detector layer.
- For high QE in the ultraviolet, need to be able to capture photocharge created within 10 nm of the surface where light enters the detector.
- In addition, the index of refraction of silicon varies over wavelength – a challenge for anti-reflection coatings.

Boron Implant / Laser Anneal

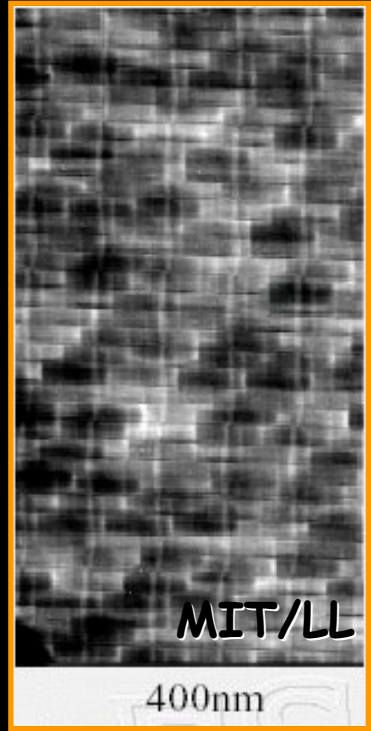
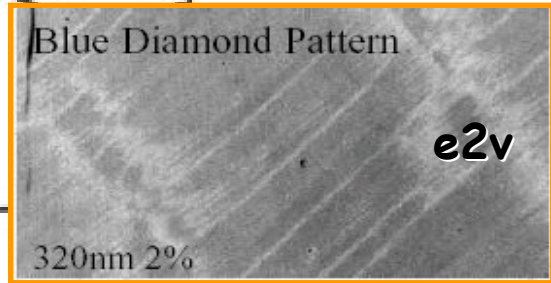


Number of electrons in outer shell

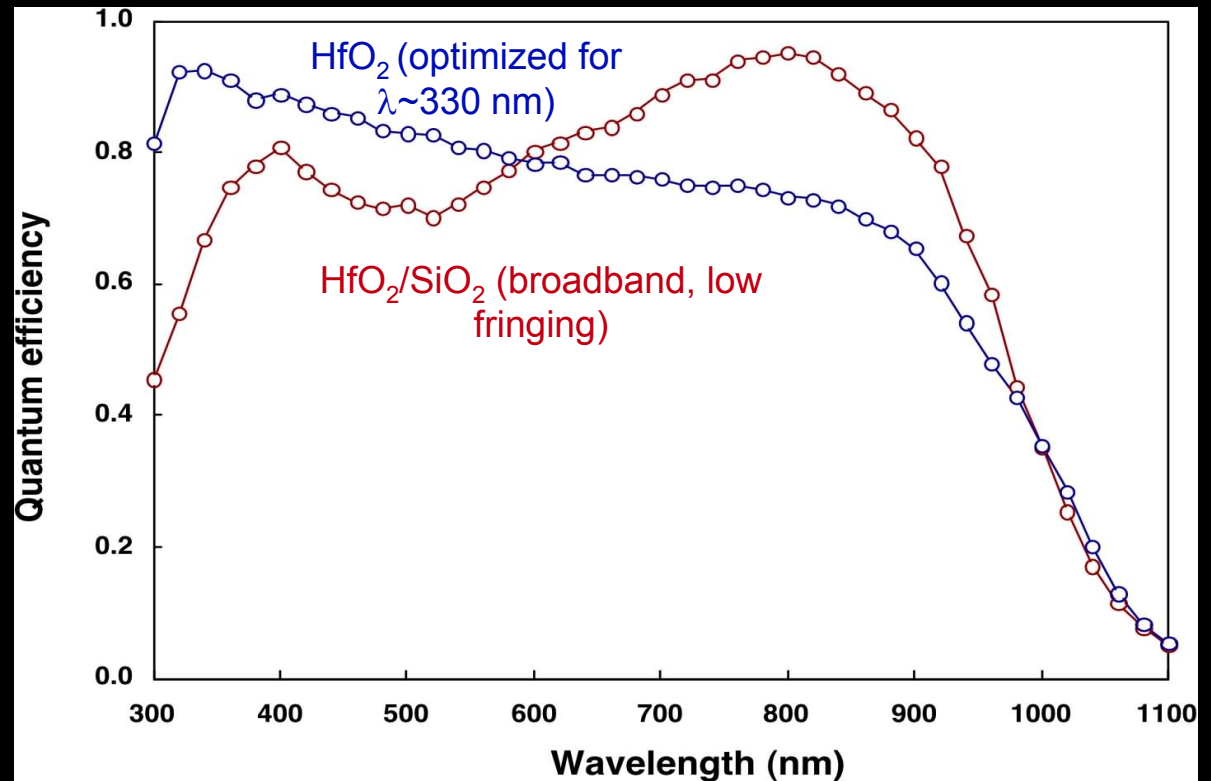
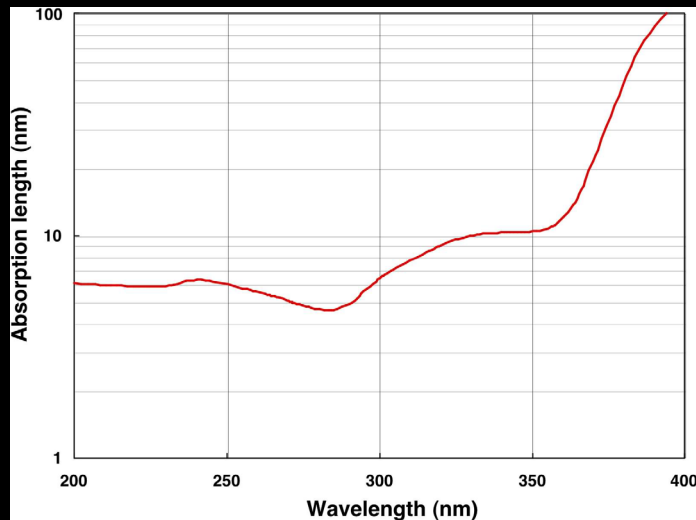
	3	4	5	
5	B Boron 10.8	C Carbon 12.0	N Nitrogen 14.0	O Oxygen 16.0
13	Al Aluminum 27.0	Si Silicon 28.1	P Phosphorus 31.0	S Sulfur 32.1
30	Zn Zinc 65.4	Ga Gallium 69.7	Ge Germanium 72.6	As Arsenic 74.9
48		Se Selenium 79.0		

LASER ANNEAL PROCESS

FURNACE ANNEAL PROCESS



Molecular Beam Epitaxy growth of very thin (~5 nm) thick backside Si layer with boron



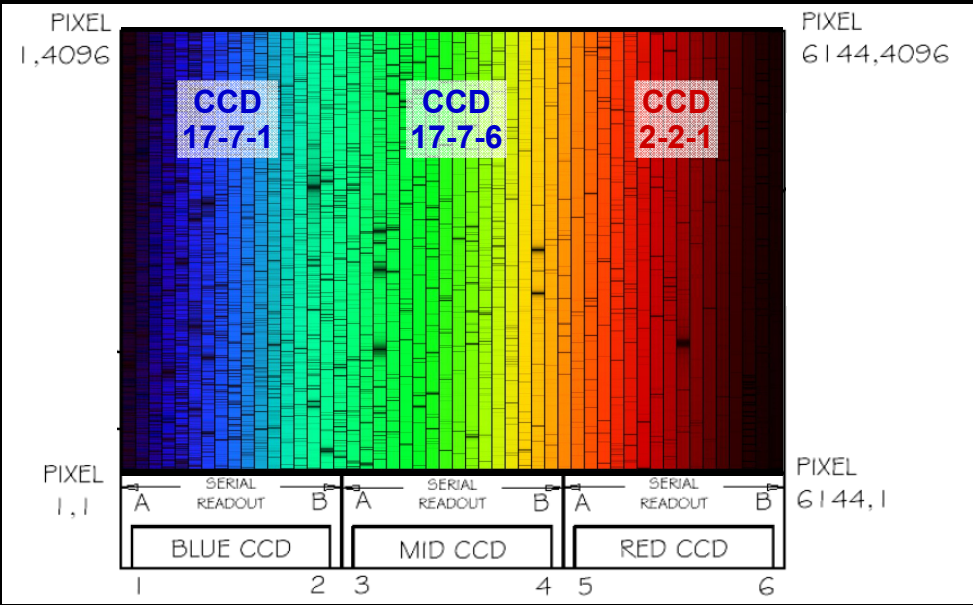
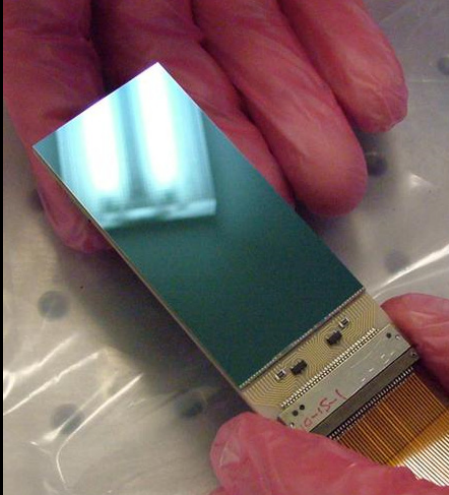
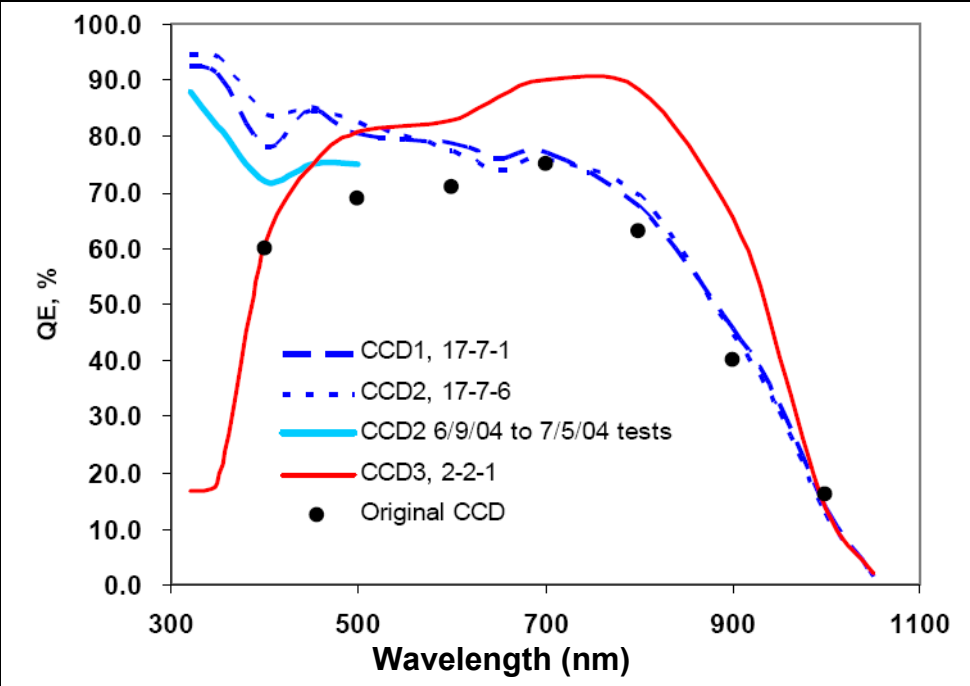
- UV (<400 nm) is challenging
 - Shallow penetration depth of radiation (<10 nm at λ=200-350 nm)
 - Requires extremely thin, doped surface layer

MBE processed
Device thickness = 45μm, T = 20°C

Plots from Barry Burke, MIT/LL

Jet Propulsion Laboratory (JPL) has similar process which they call "delta doping"

HIRES CCDs

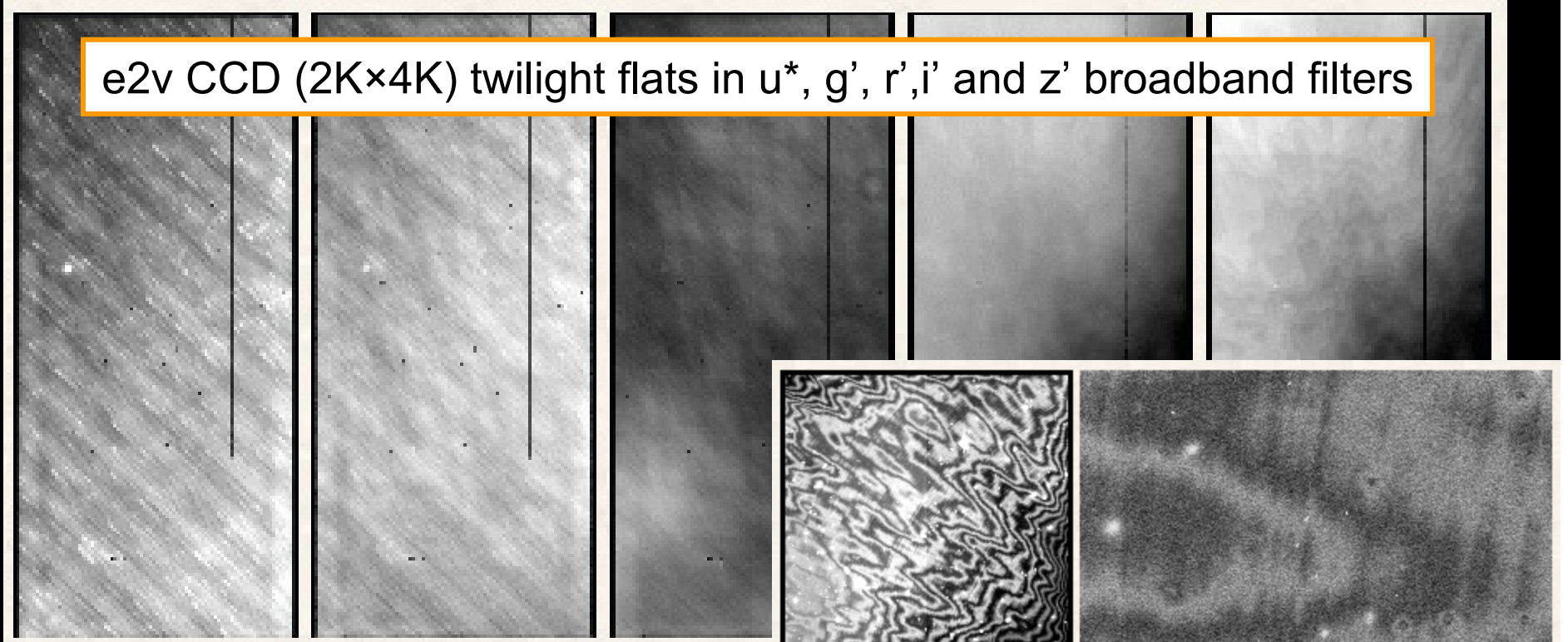


- ### MIT Lincoln Laboratory 2Kx4K CCDs
- Two CCDs with U. Arizona chemisorption backside process for high blue/UV QE
 - The "red" CCD has boron implant & laser anneal

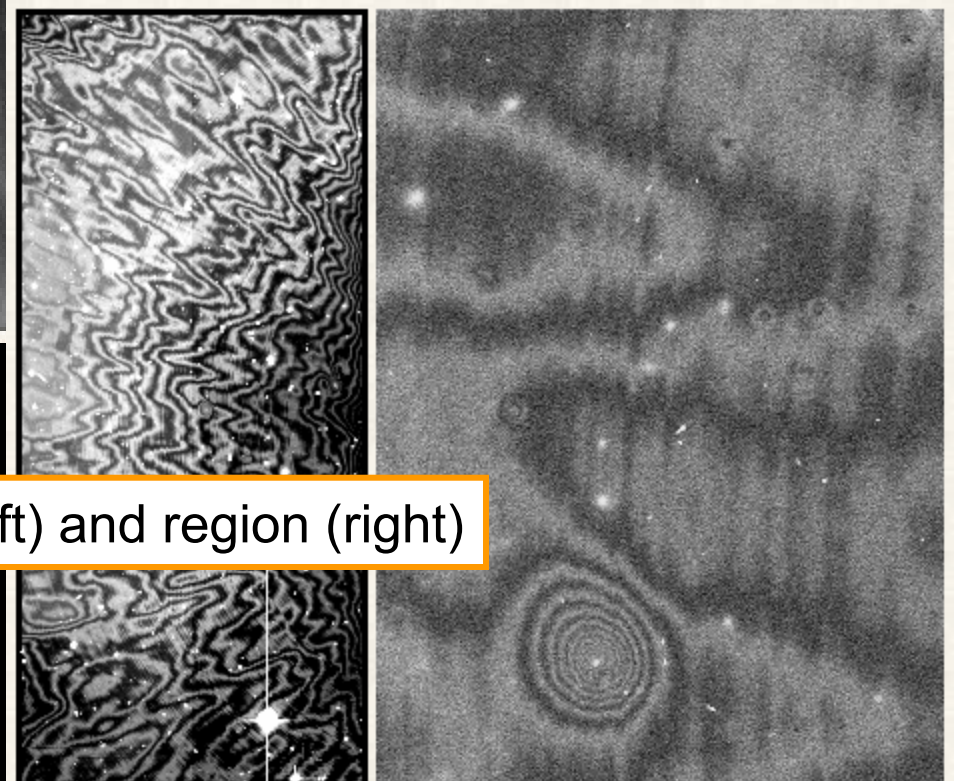
QE variations

Boron implant / laser anneal (blue end), and fringing (red)

e2v CCD (2K×4K) twilight flats in u*, g', r', i' and z' broadband filters



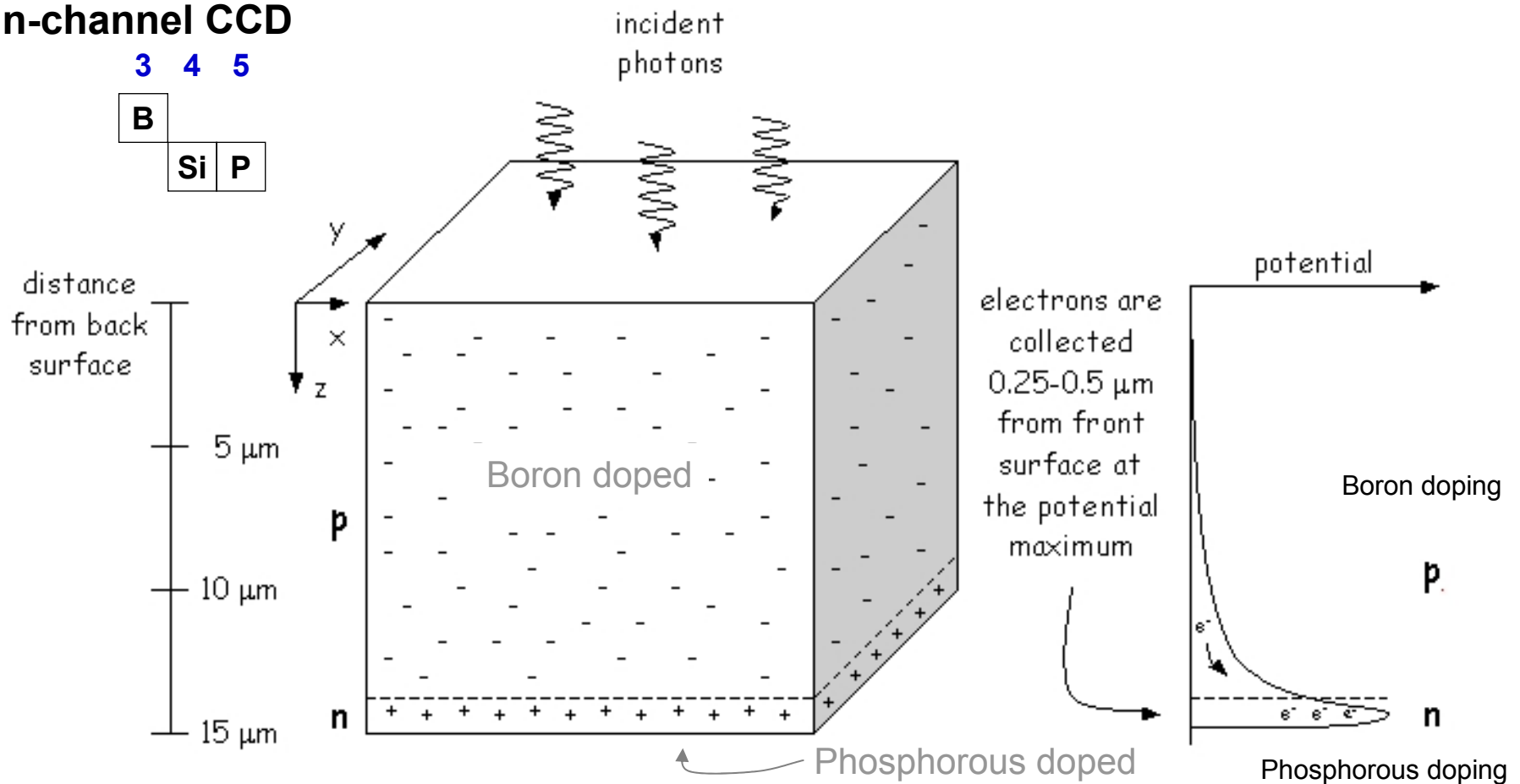
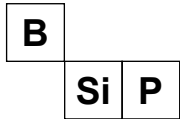
Fringes in the i' band: full CCD (left) and region (right)



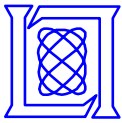
Photovoltaic Detector Potential Well

n-channel CCD

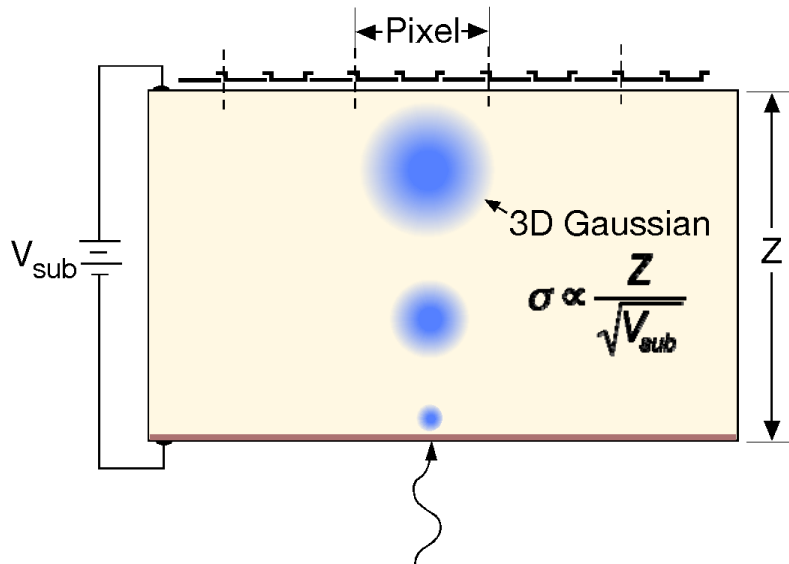
3 4 5



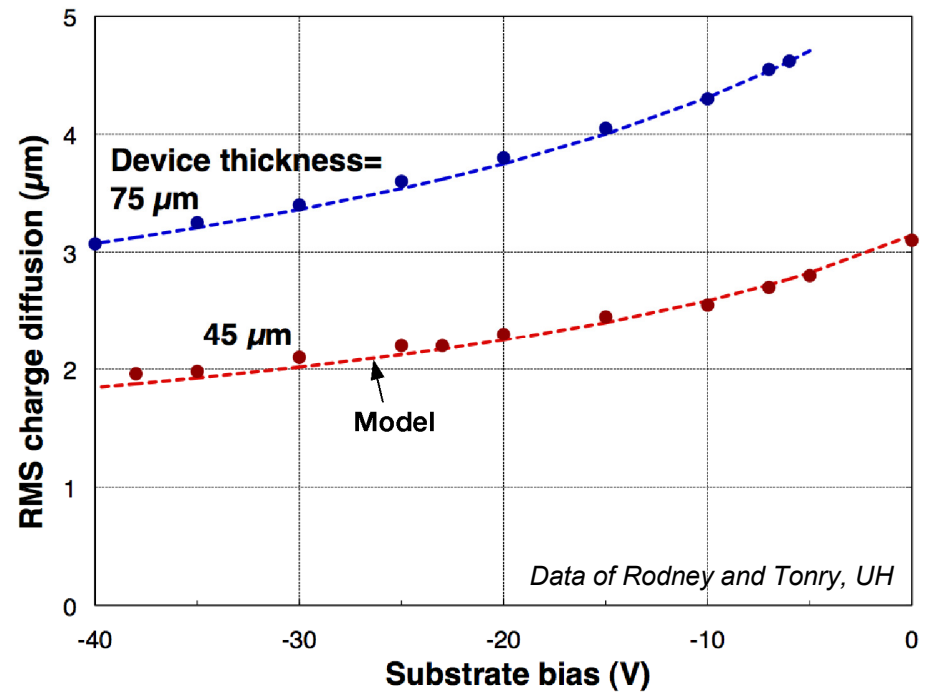
Silicon, HgCdTe and InSb are photovoltaic detectors. All use a pn-junction to generate E-field in the z-direction of each pixel. This electric field separates the electron-hole pairs generated by a photon.



Tradeoff: High Near-IR QE vs. Imager Resolution



Thermal diffusion of photoelectrons reduces resolution



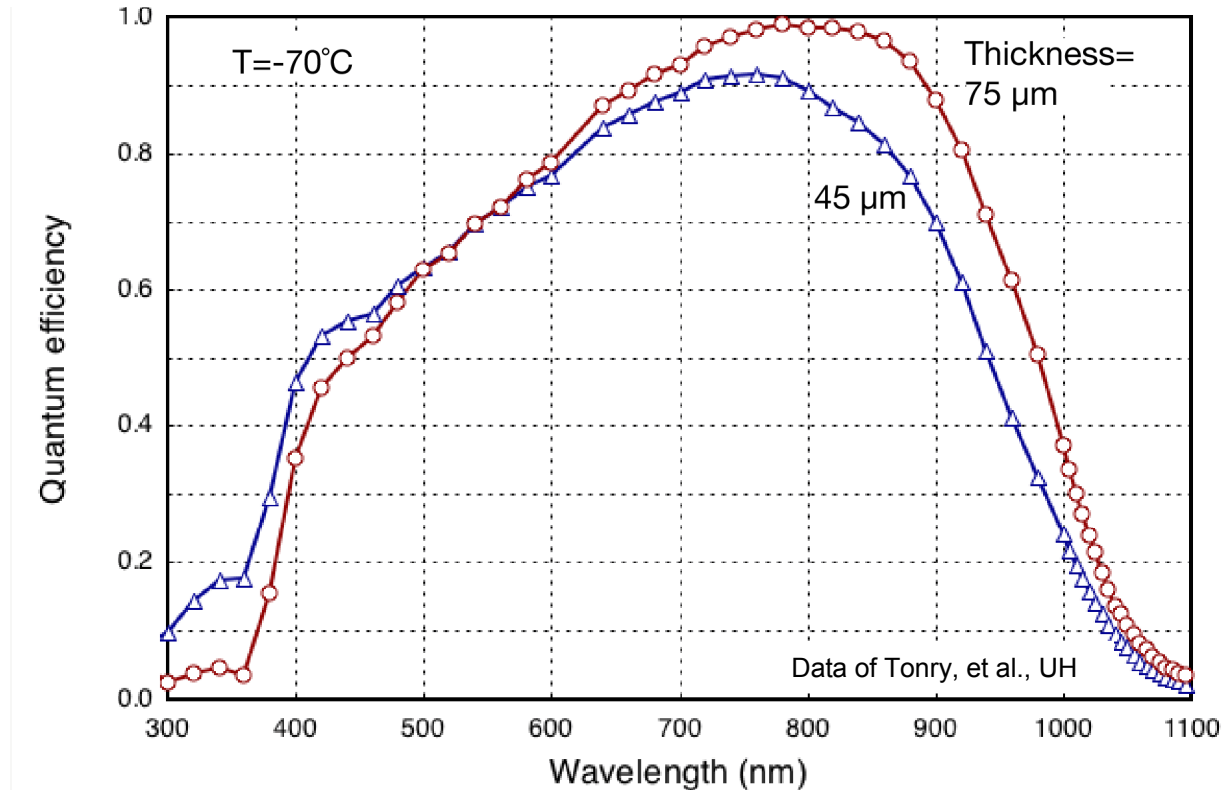
Substrate bias helps counteract effects of thermal diffusion

High resolution in thick imagers => bias across sensor



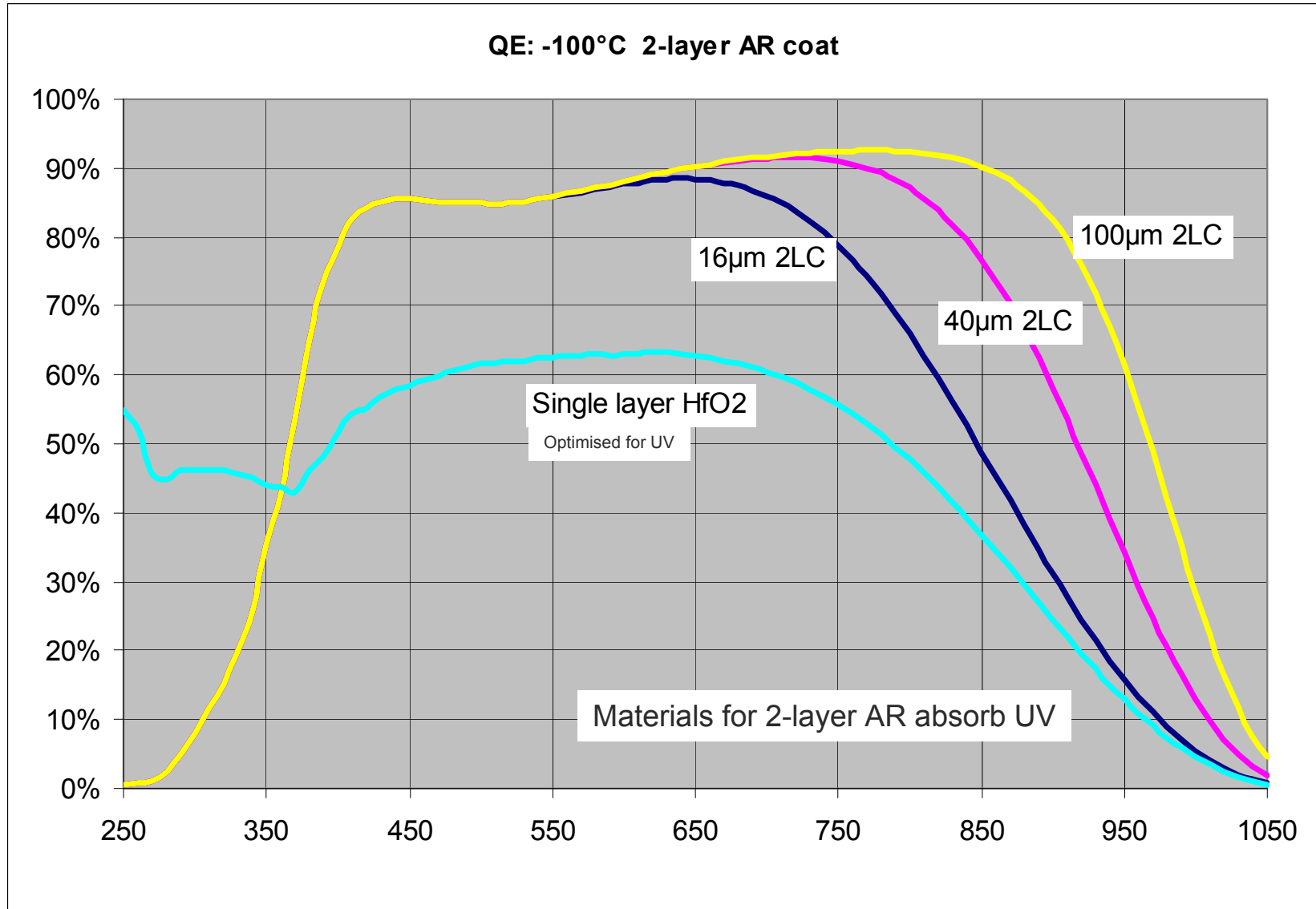
Quantum Efficiency

- **Thicker devices: higher near-infrared quantum efficiency**



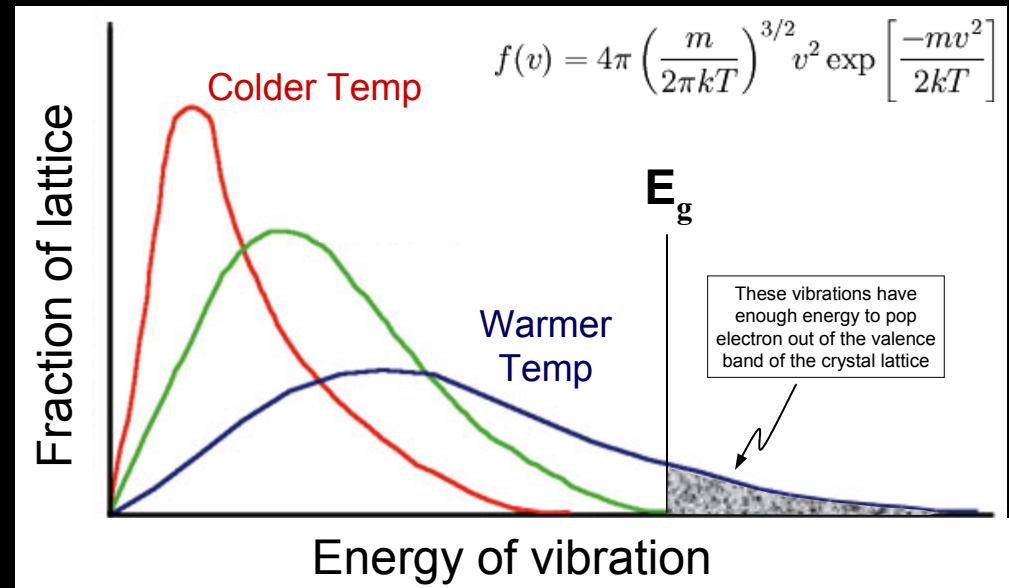
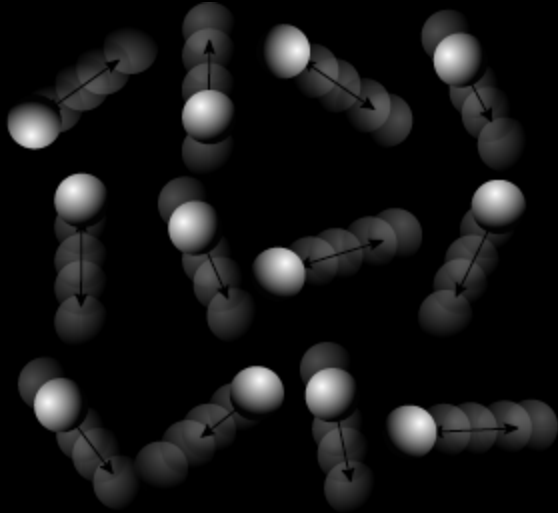
Available CCD performance

e2v



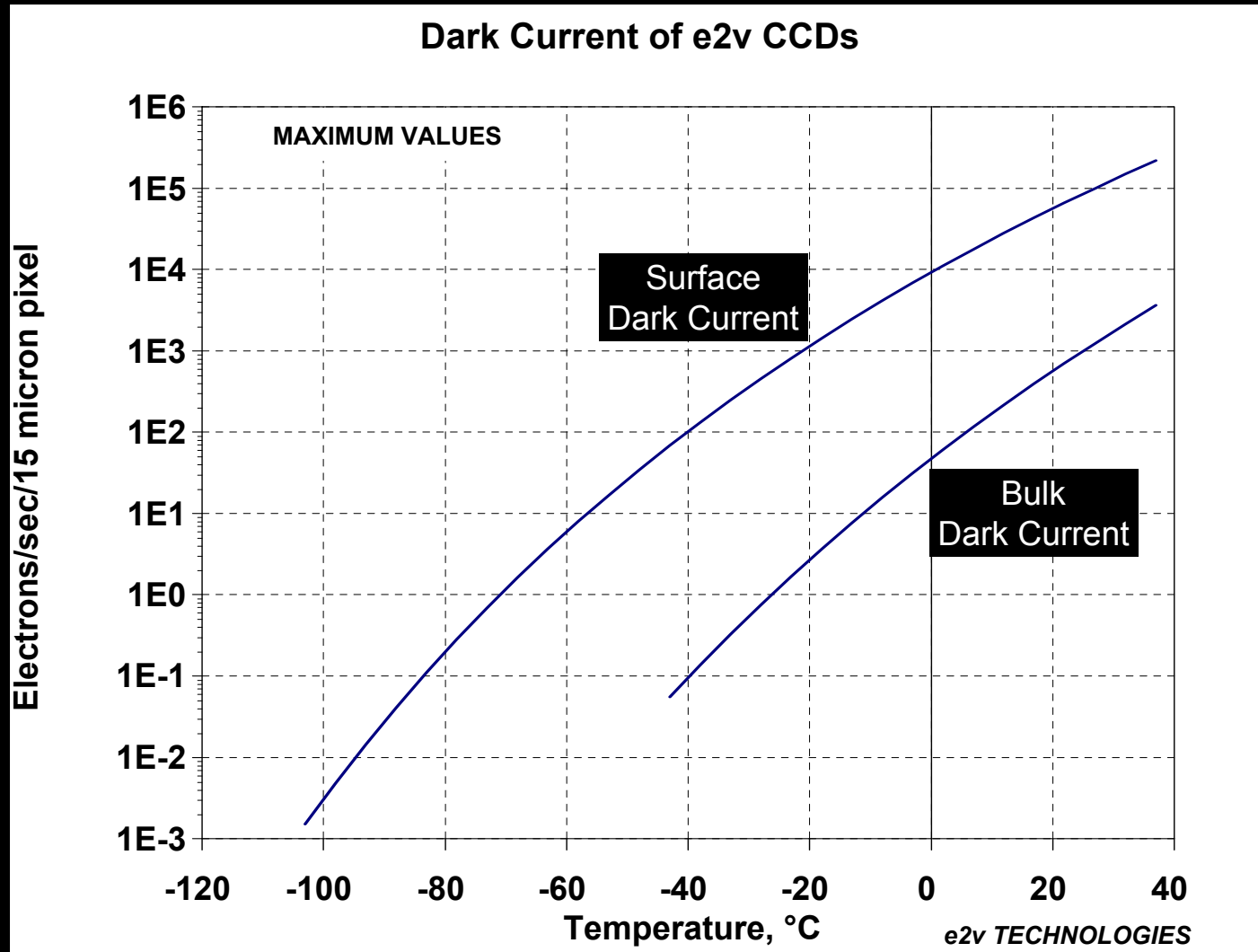
Dark Current

Undesirable byproduct of light detecting materials



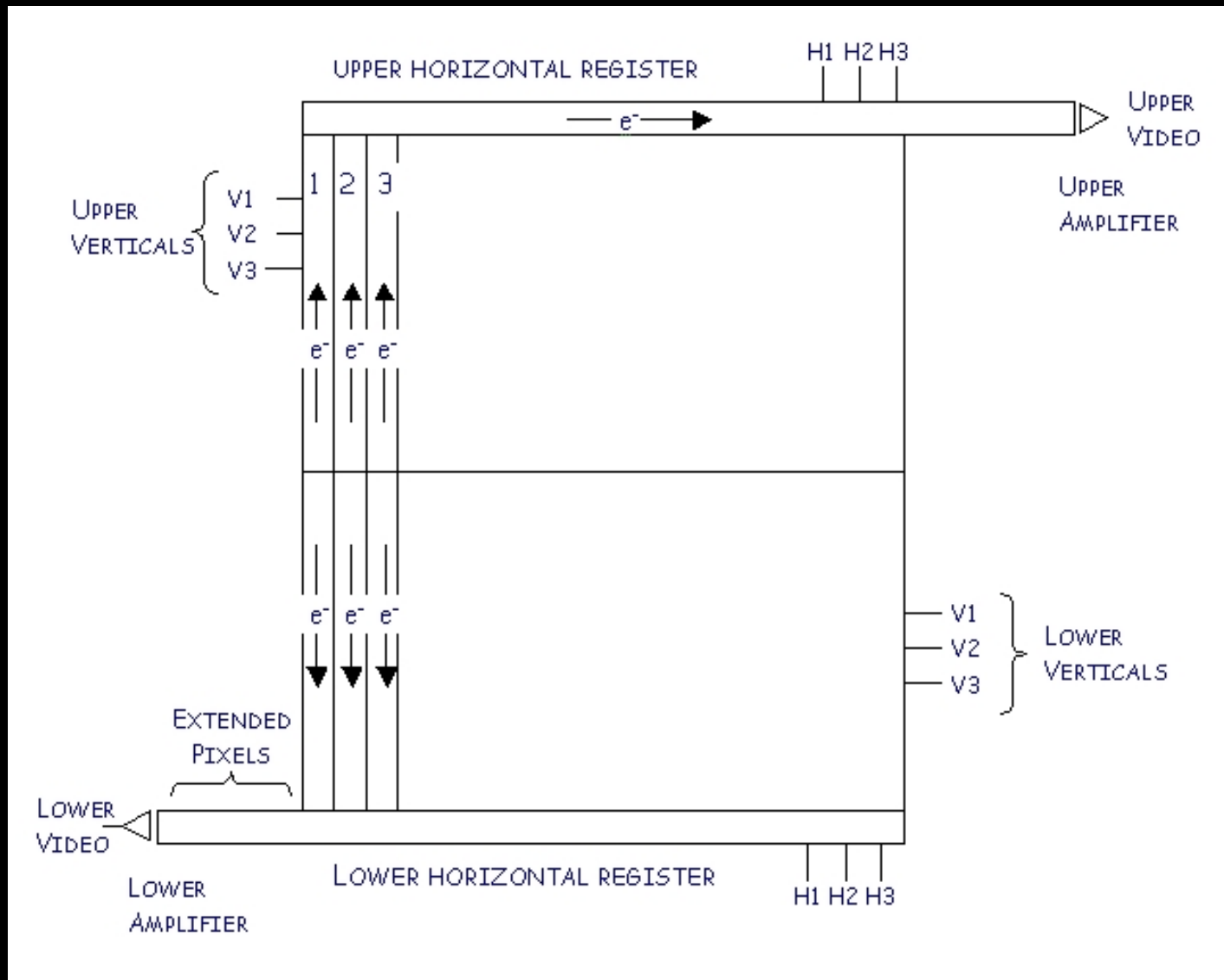
- The vibration of particles (includes crystal lattice phonons, electrons and holes) has energies described by the Maxwell-Boltzmann distribution. Above absolute zero, some vibration energies may be larger than the bandgap energy, and will cause electron transitions from valence to conduction band.
- Need to cool detectors to limit the flow of electrons due to temperature, i.e. the **dark current** that exists in the absence of light.
- The smaller the bandgap, the colder the required temperature to limit dark current below other noise sources (e.g. readout noise)

Dark Current of Silicon-based Detectors

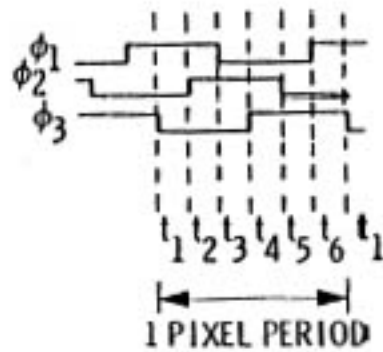


In silicon, dark current usually dominated by surface defects

CCD Architecture

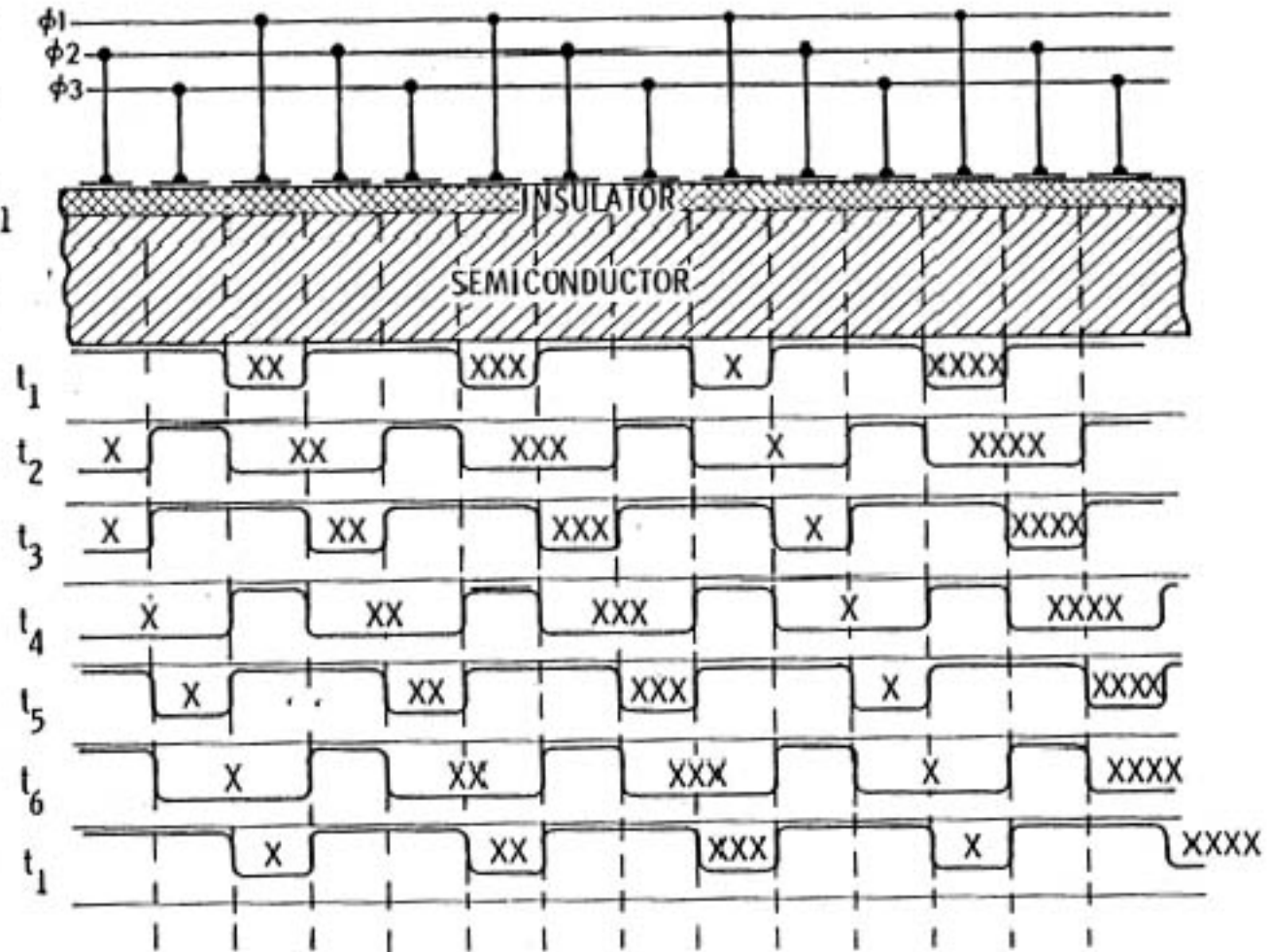


CCD Timing

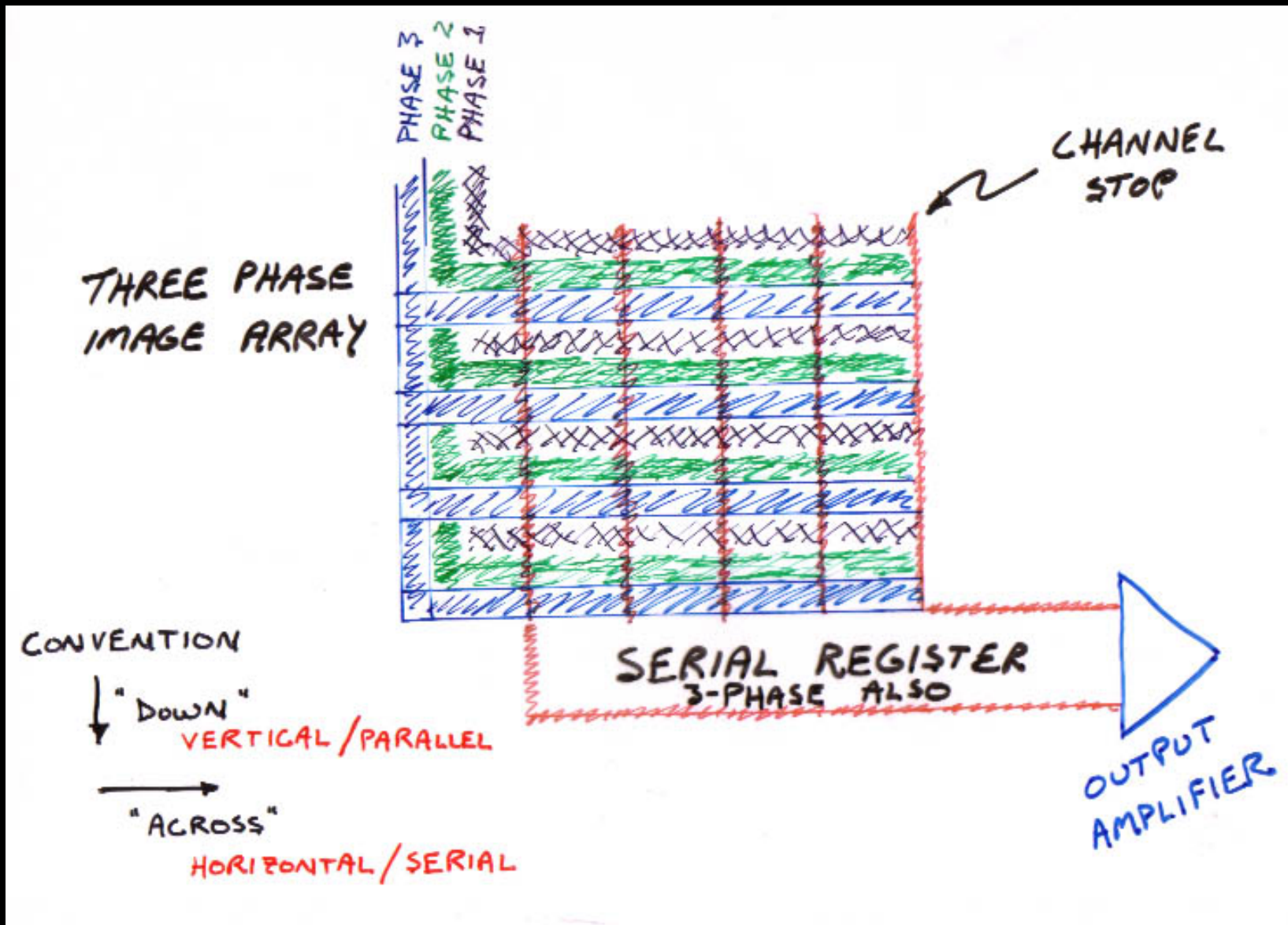


Movement of charge is "coupled"

Charge
Coupled
Device



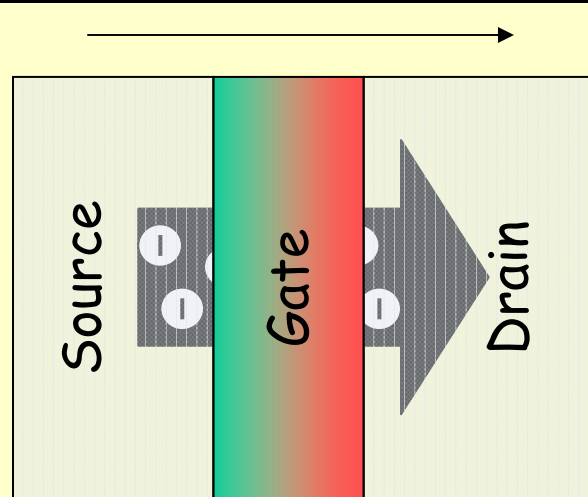
CCD – 3 Phase Serial Register



MOSFET Principles

MOSFET = metal oxide semiconductor field effect transistor

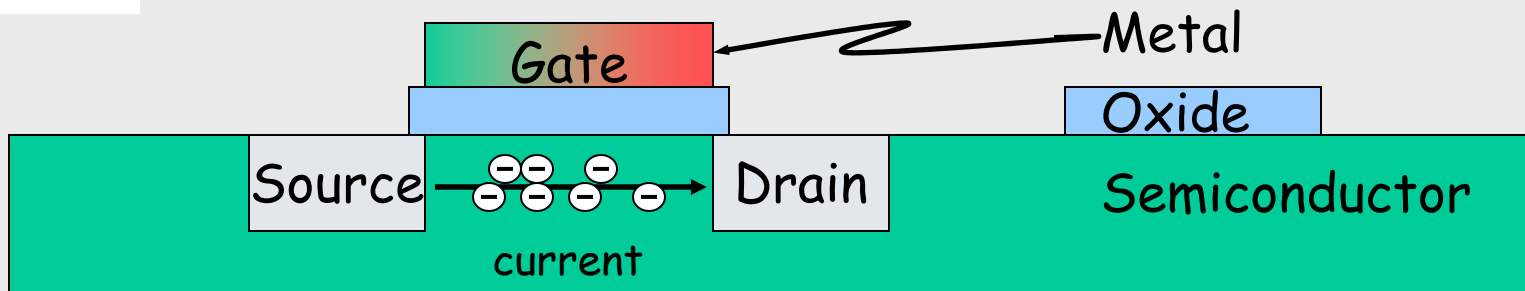
Top view



Turn on the MOSFET and current flows from source to drain

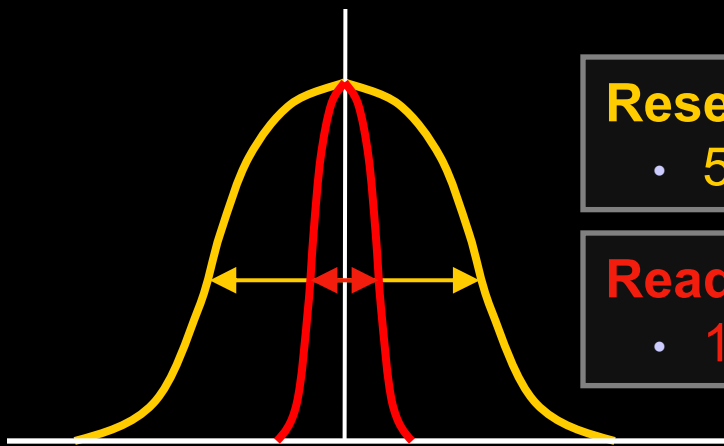
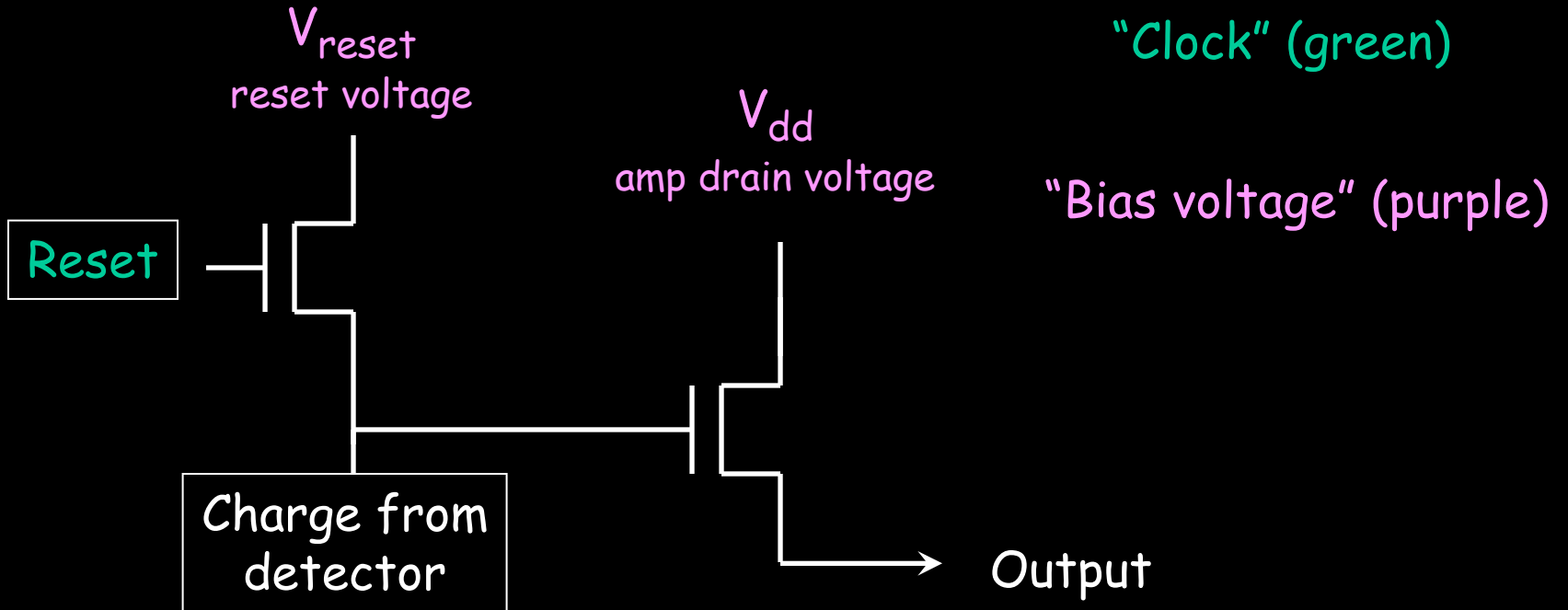
Add charge to gate & the current flow changes since the effect of the field of the charge will reduce the current

Side view



Fluctuations in current flow produce “readout noise”
Fluctuations in reset level on gate produces “reset noise”

MOSFET Amplifier Noise



Reset Noise

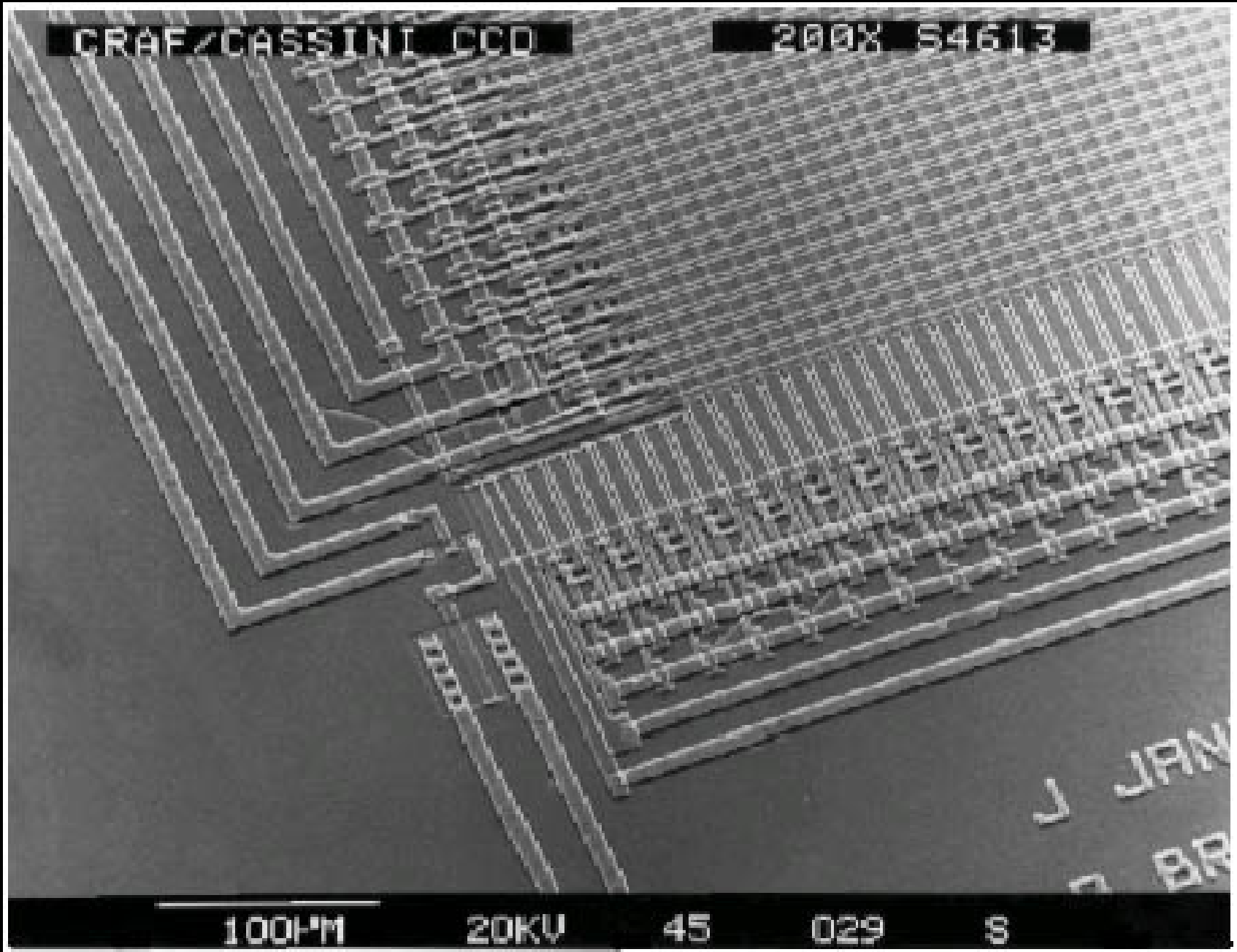
- 50 to 100 e- rms

Read Noise

- 1.5 to 10 e- rms

Correlated Double Sample (CDS)

- Reset
- Read
- Put charge on gate
- Read



CRAF/CASSINI CCD

200X S4613

100 micron diameter human hair

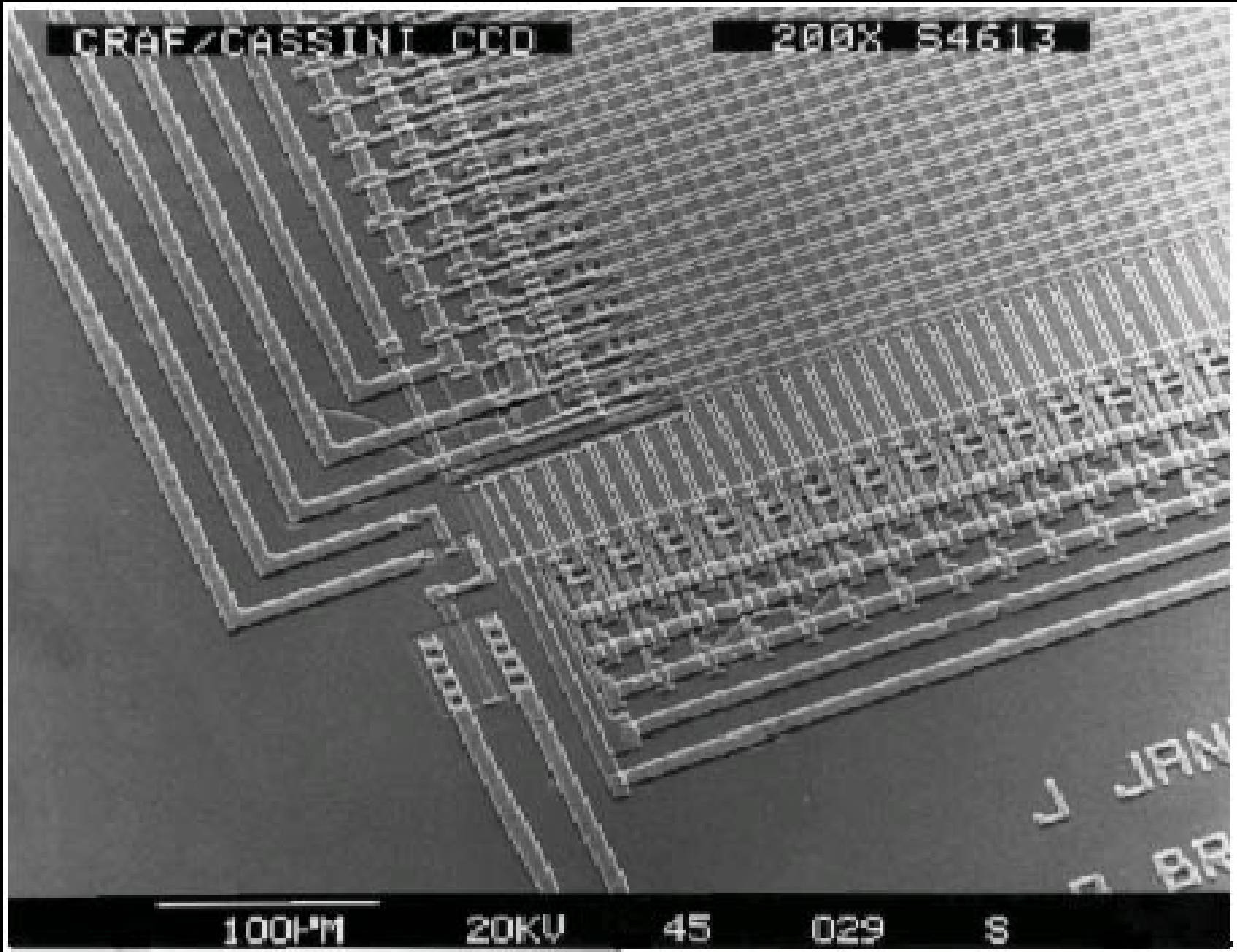
100µm

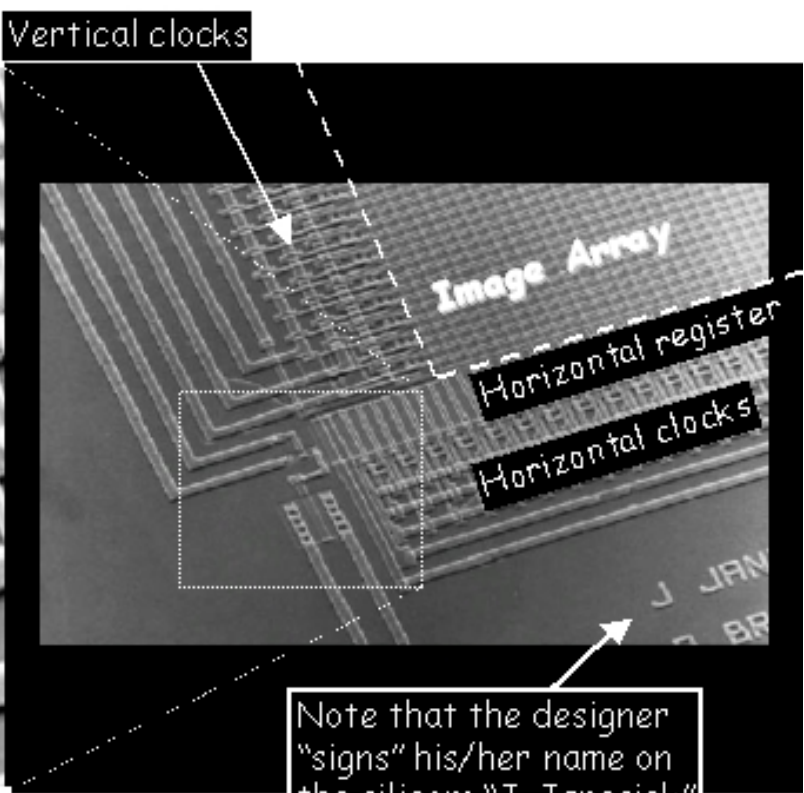
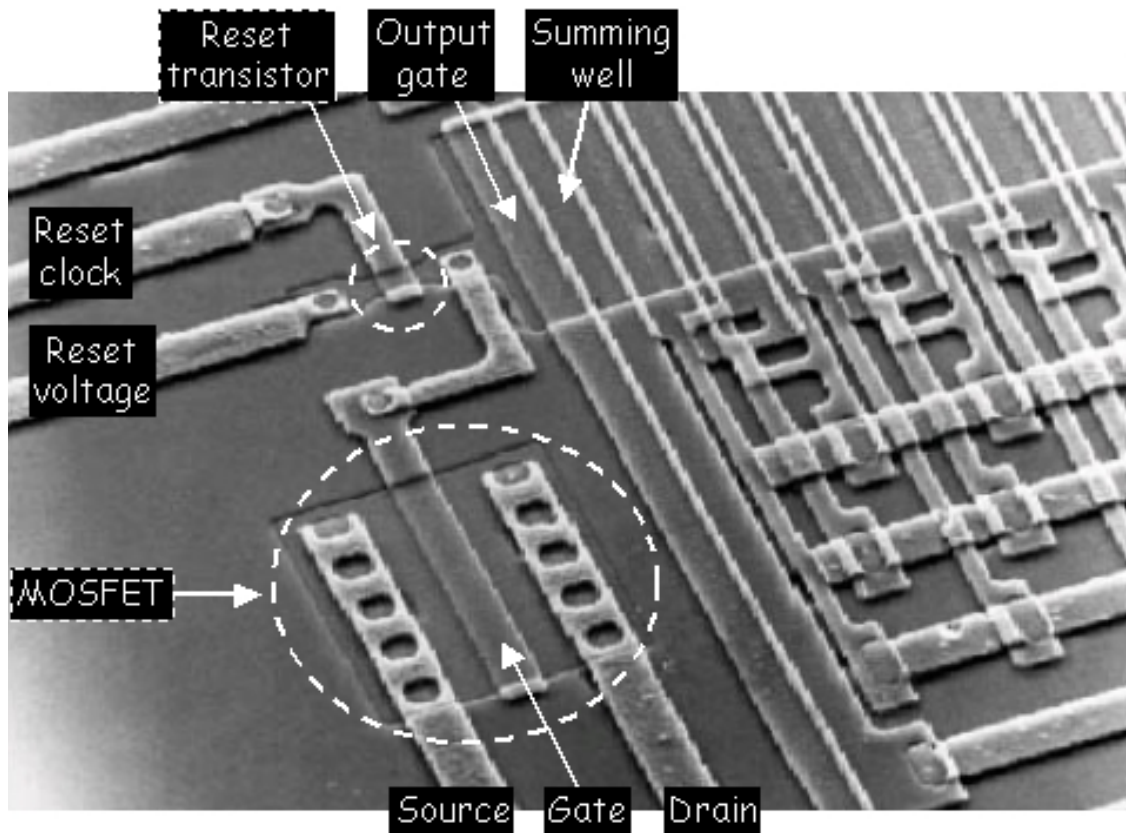
20KV

45

029

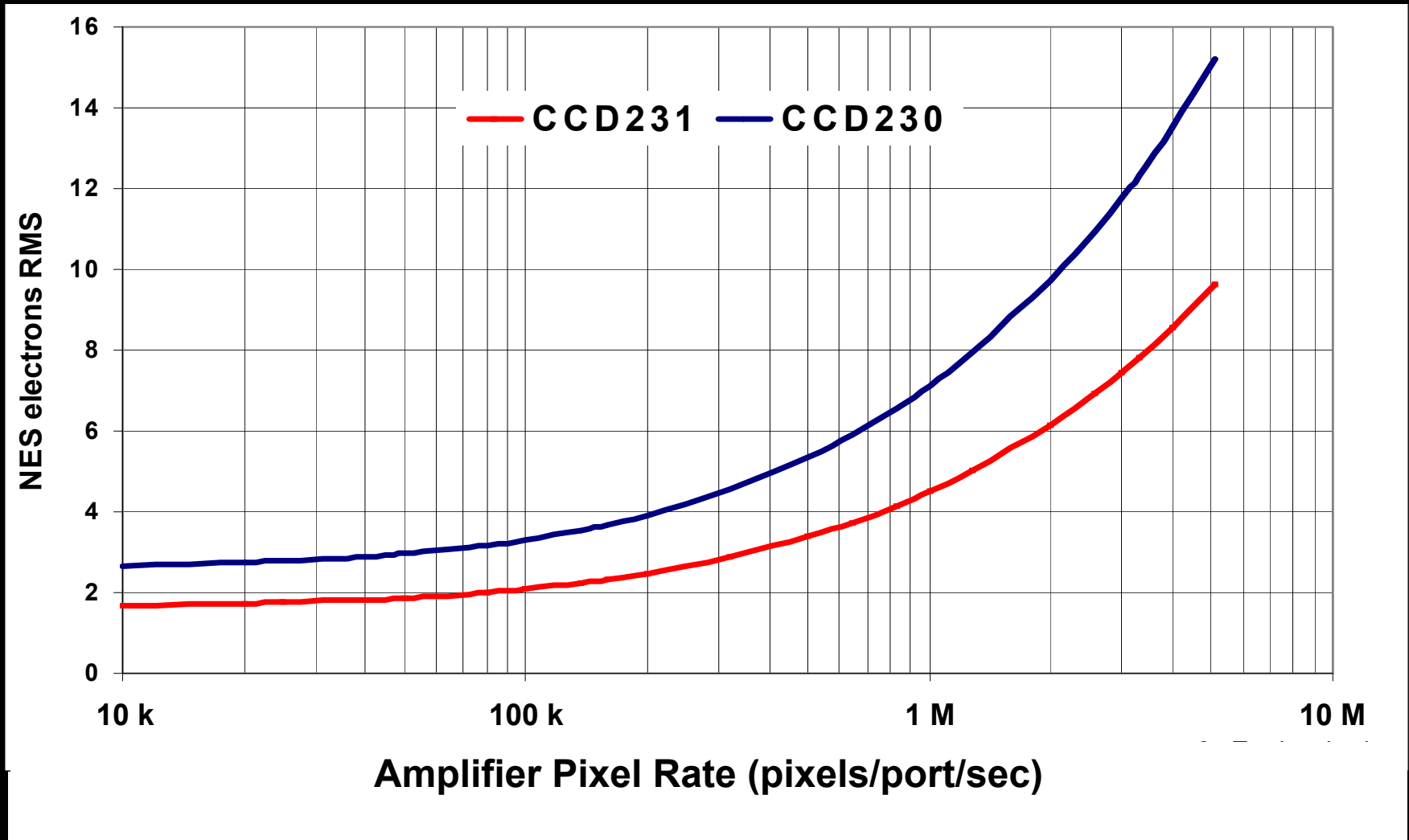
S



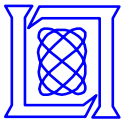


Note that the designer "signs" his/her name on the silicon: "J. Janesick" & "D. Bredthauer"

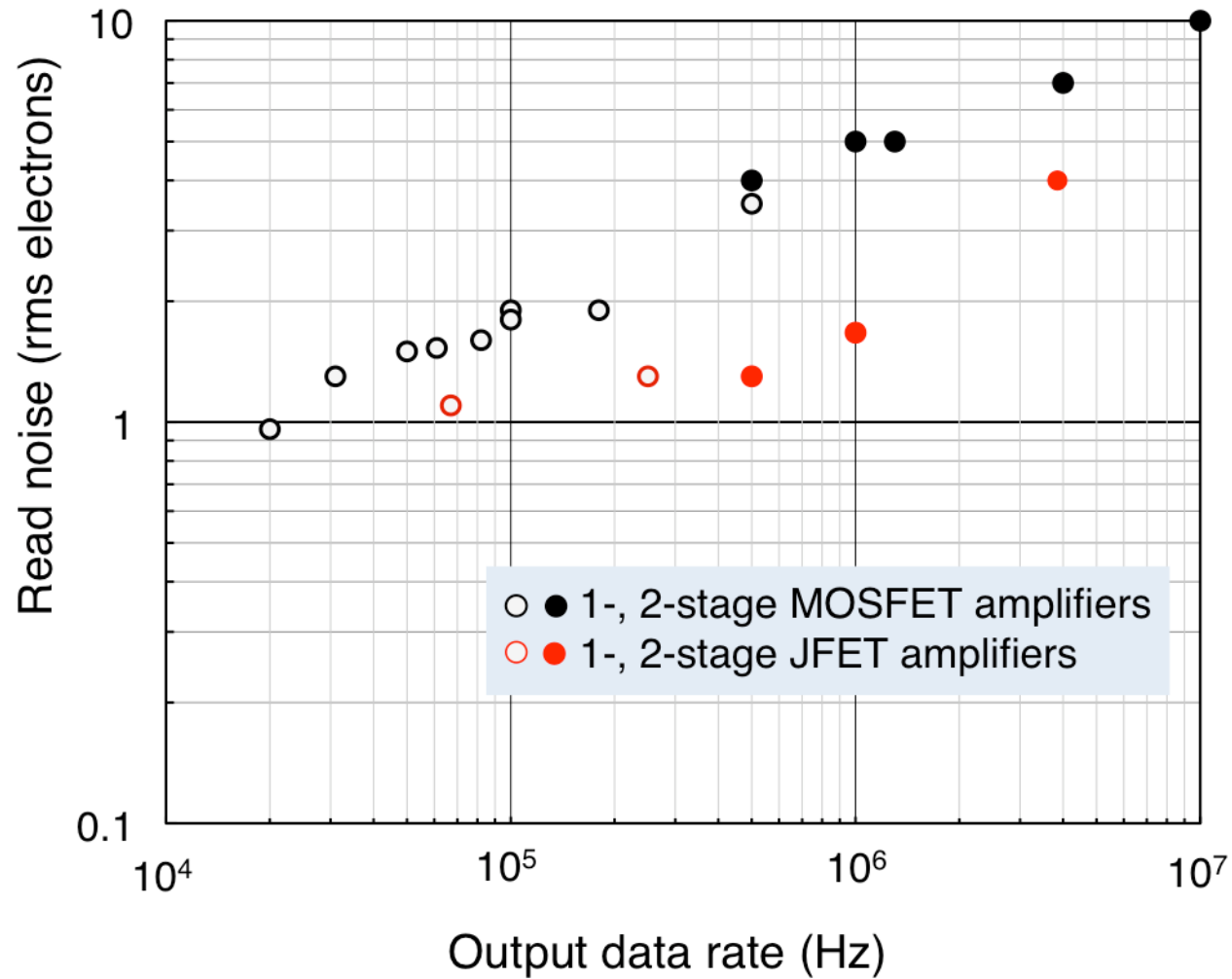
Typical CCD Readout Noise (single CDS)



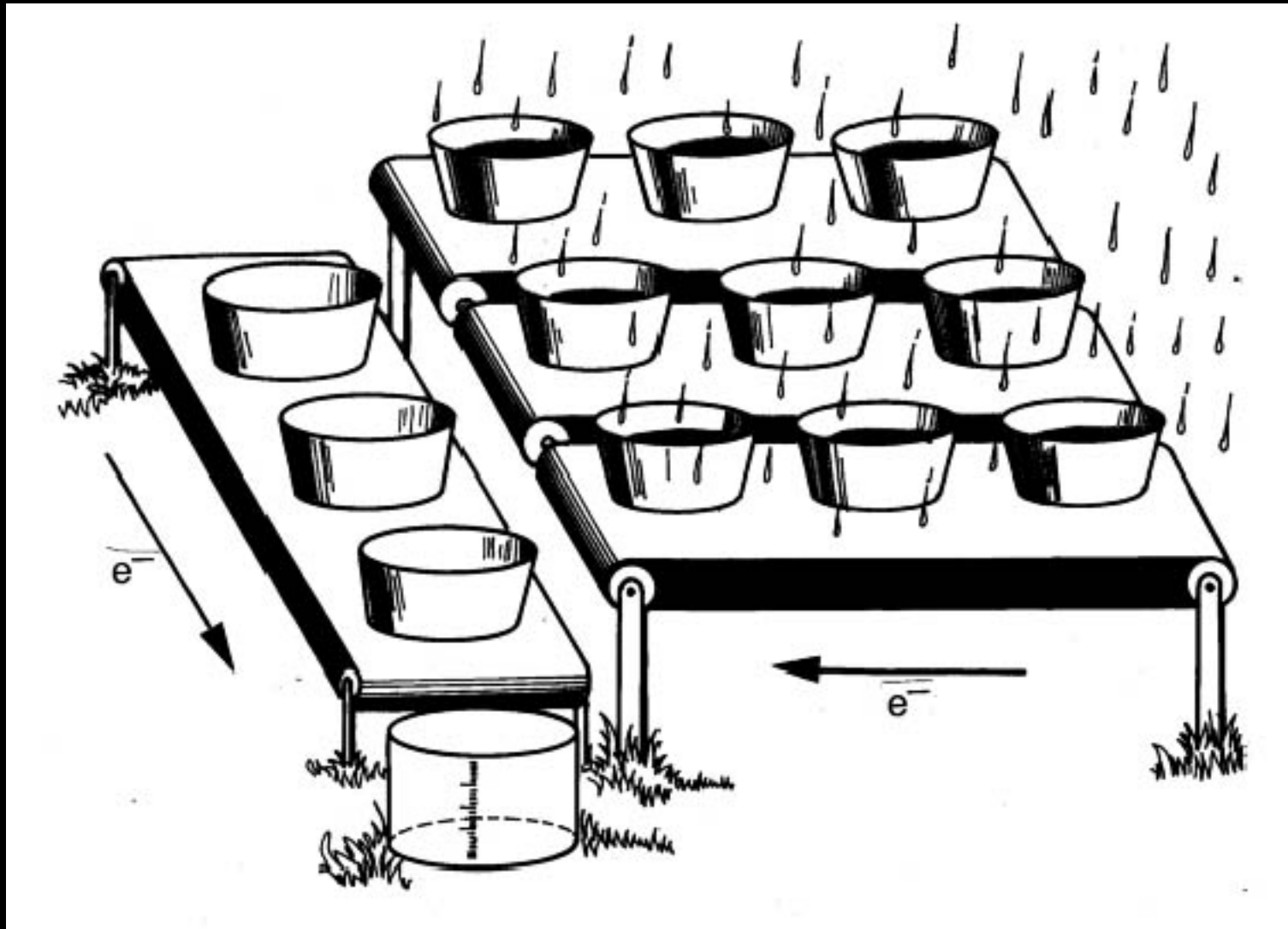
e2v technologies



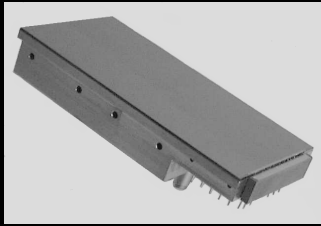
CCD Noise as function of amplifier & data rate



CCD Rain bucket analogy

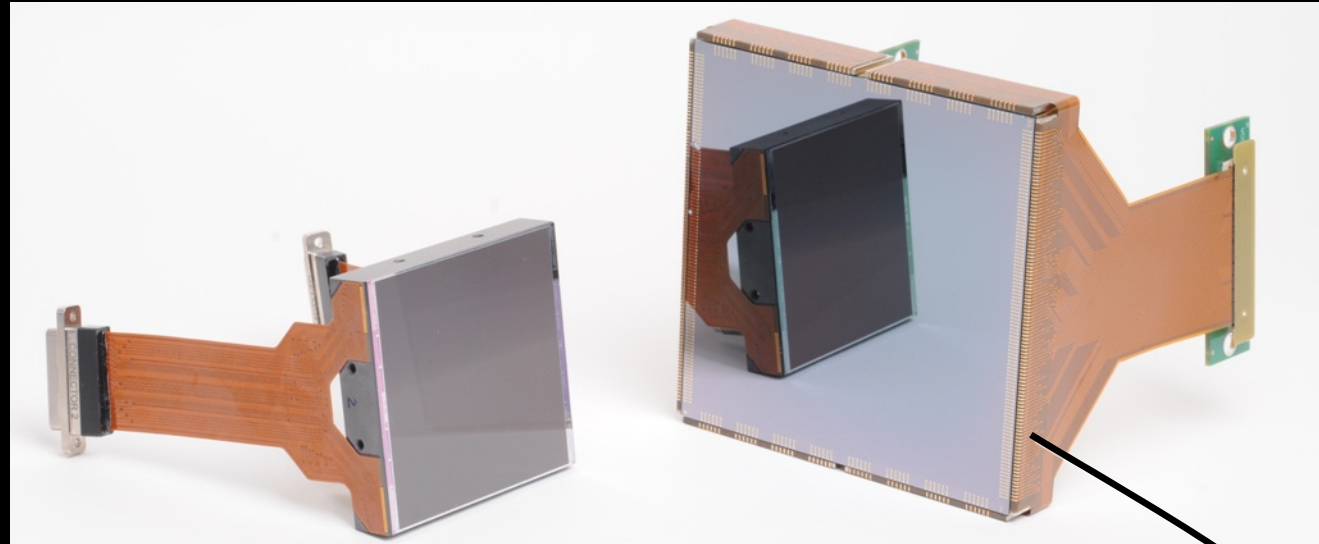


World's Largest Monolithic CCDs



e2v

8.4 million pixels
2048×4096, 15 μm
18.9 cm^2

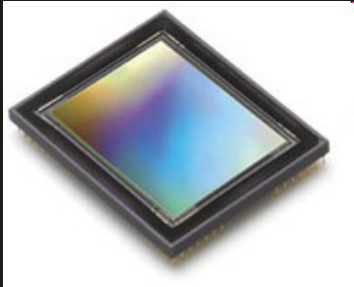


e2v

16.8 million pixels
4096×4096, 15 μm
37.7 cm^2

STA

111.5 million pixels
10,240×10,240, 9 μm
90.3 cm^2

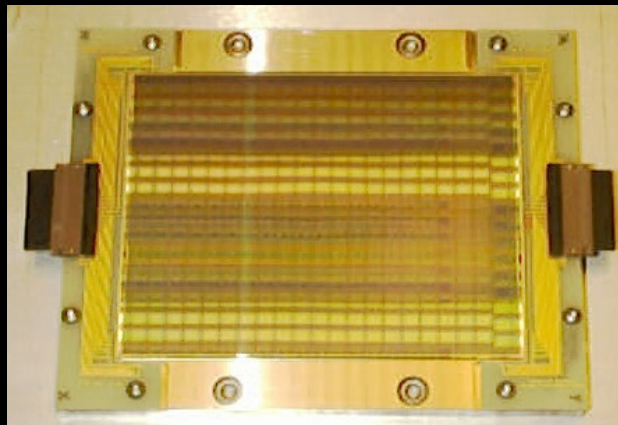


Dalsa

48 million pixels
6000×8000, 6 μm
17.3 cm^2

Philips

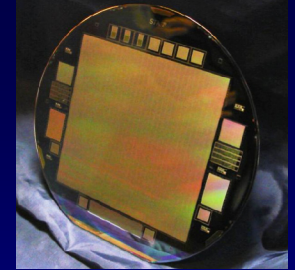
66.1 million pixels
7168×9216, 12 μm
95.1 cm^2



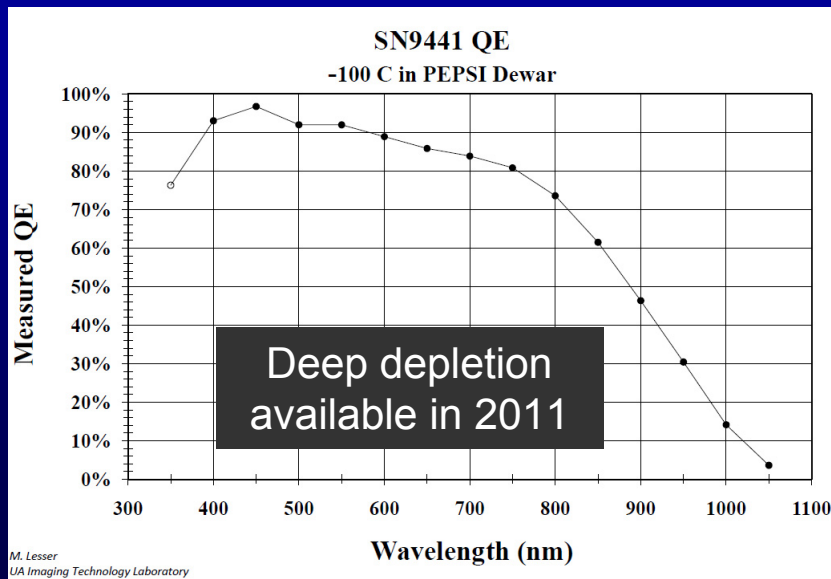
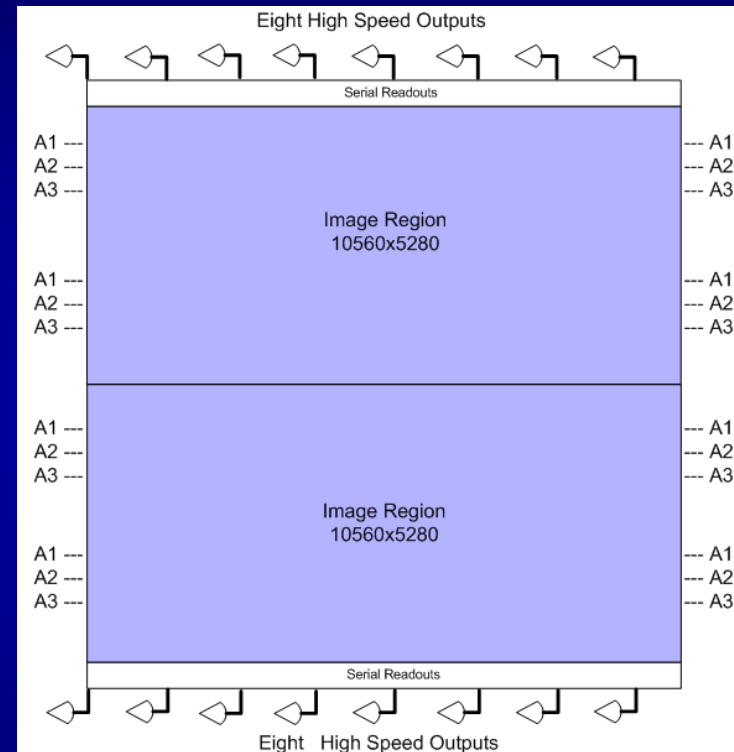
445 Mpixel mosaic



STA1600B 111 Mega pixel imager



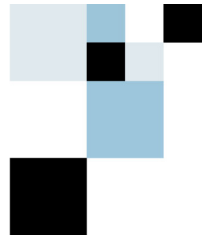
- Full 6-inch wafer imager
- 10,560 × 10,560 pixels
- 9 micron pixel
- 111.5 Megapixels per frame
- 16 dual stage high speed outputs
- Backside thinned available
- Acquisition speeds up to 1 frame/sec



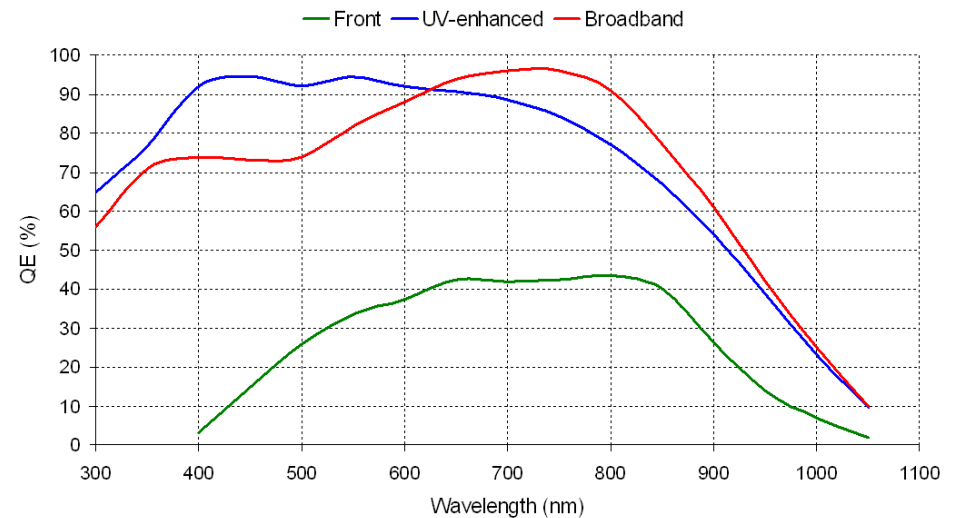
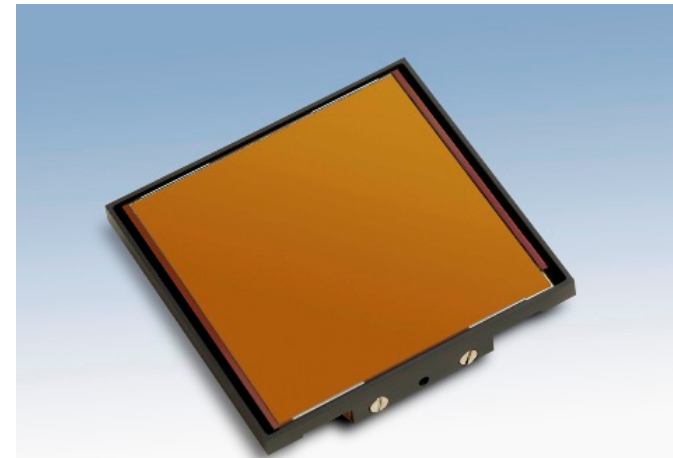
- 7.0-9.0 electrons noise @ 1.0 MHz
- 5.0 electrons @ 100 kHz
- Full well > 80,000 electrons non-MPP

CCD486 6-cm 4k x 4k

Fairchild
Imaging

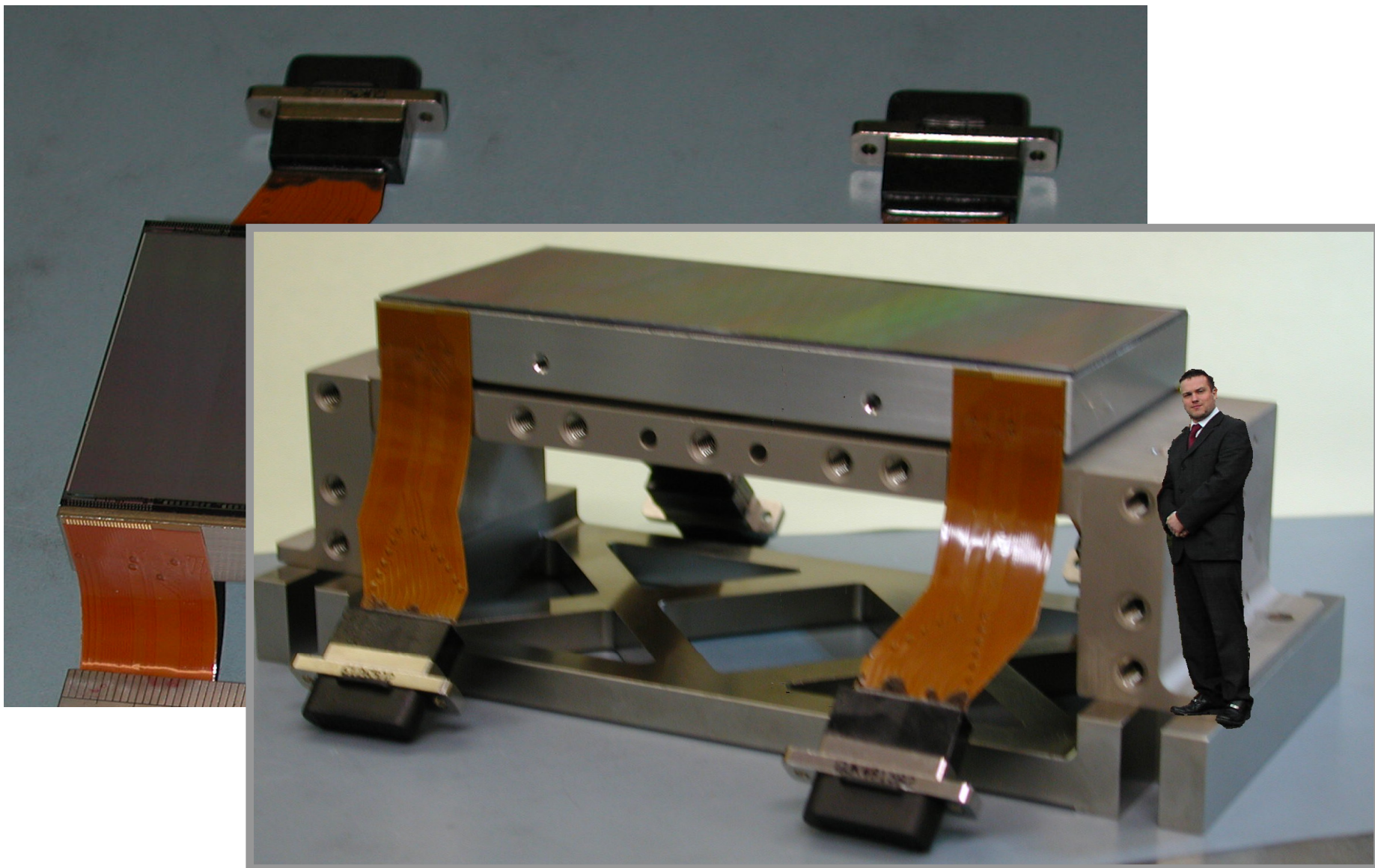


- 4096(H) x 4097(V) full frame CCD
- 15 μm x 15 μm pixels
- 61.44 mm x 61.44 mm image area
- 100% fill factor
- Front or back-illuminated
- Multi-Pinned Phase (MPP) mode
- Readout noise less than 4 e⁻ at 50kHz
- 86 dB dynamic range
- 4 output ports
- 3-phase buried channel architecture
- 800 ke- summing well supports on-chip binning
- Volume production



3K×8K Spectrograph CCD

e2v



Stability of HARPS due in part to mechanical stability of the CCD cryostat – it doesn't move

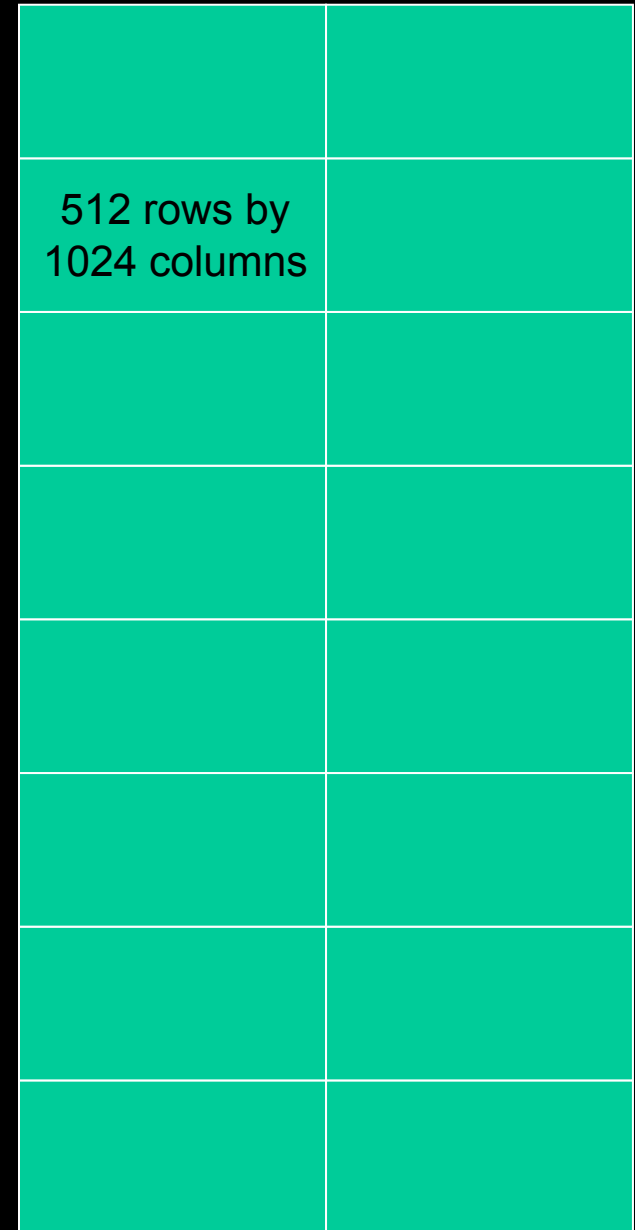
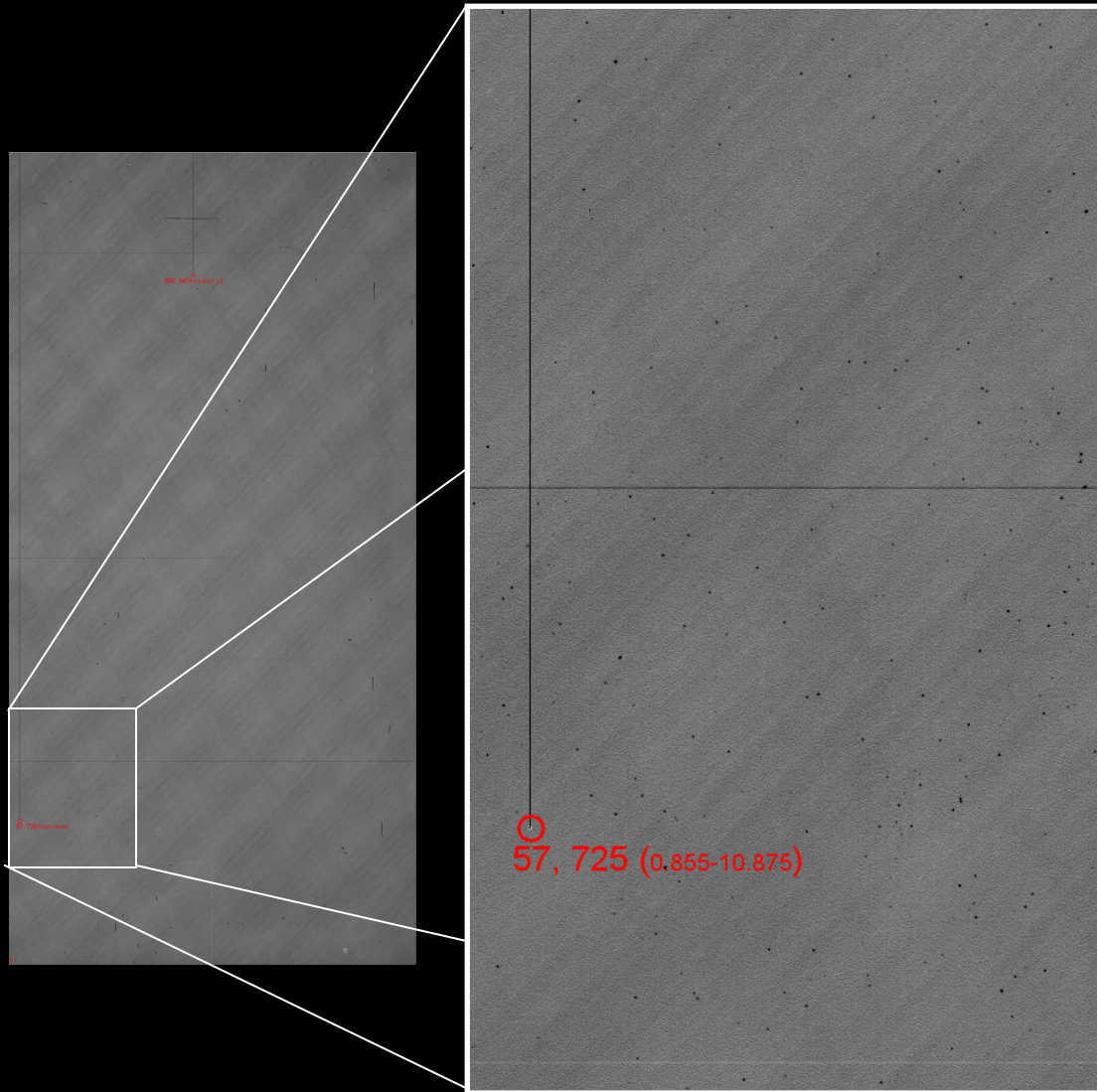
HARPS

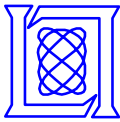


Continuous flow cryostat

e2v has provided me with new information to state that they now have a new stepper for stitching with 100 nm precision, and this stitch issue should no longer be an effect.

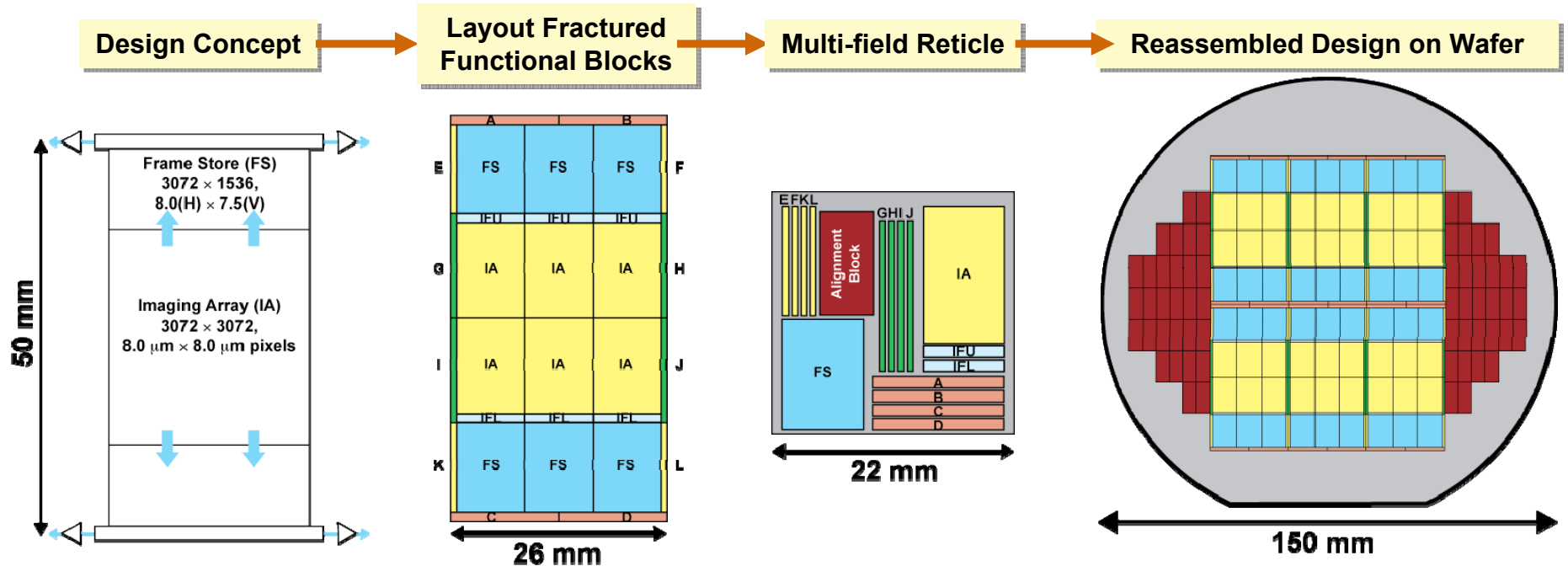
HARPS CCD stitch boundary effect

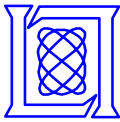




Large-Format, Modular CCD Imagers

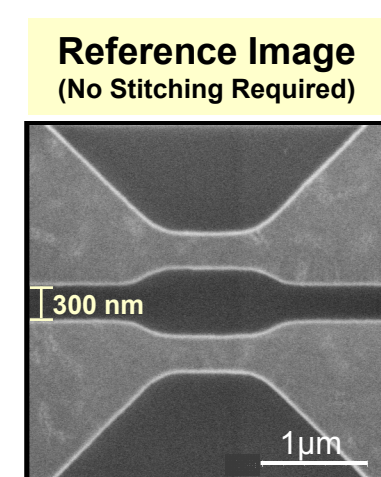
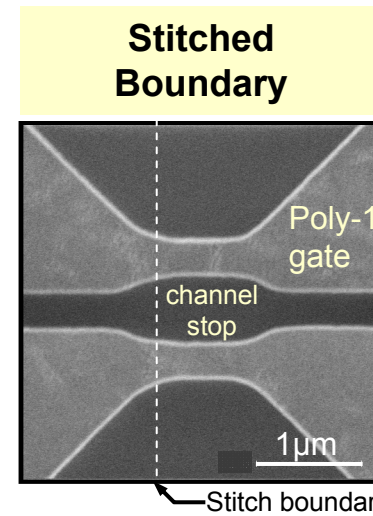
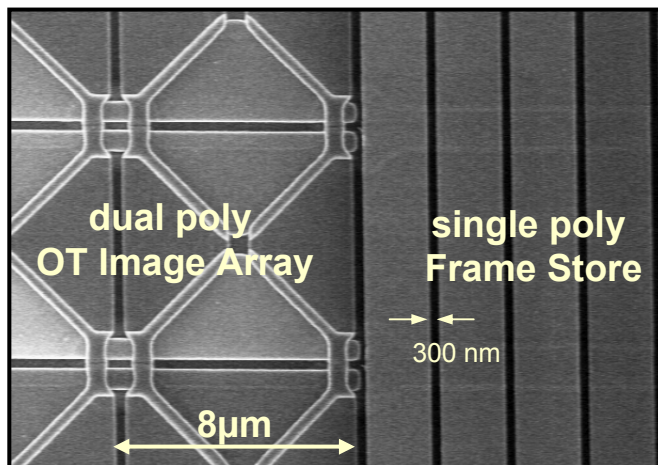
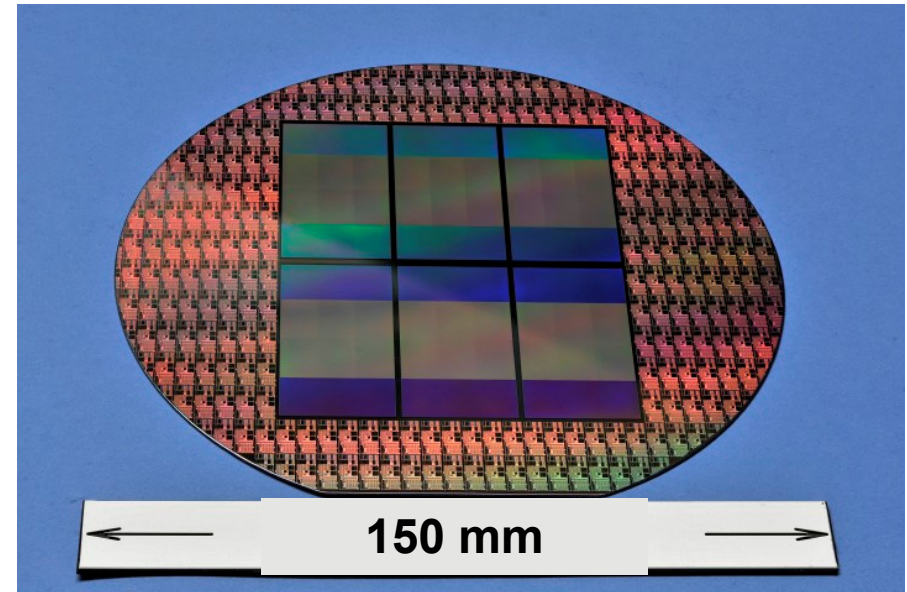
- Example: 3K x 3K OTCCD image sensor with $8\mu\text{m} \times 8\mu\text{m}$ pixels
- Pixels with submicron dimensions require high-resolution (248-nm) patterning
 - Lithography field size is smaller than device size
- Design is fractured into functional blocks onto a multi-field reticle and precisely stitched back together on wafer

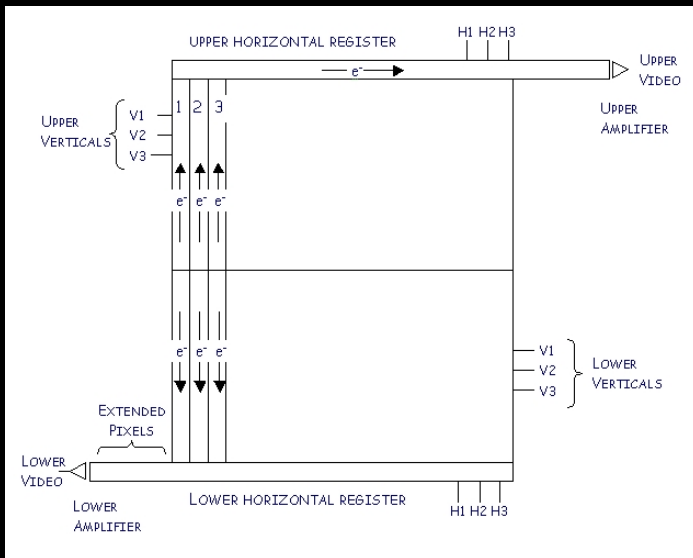




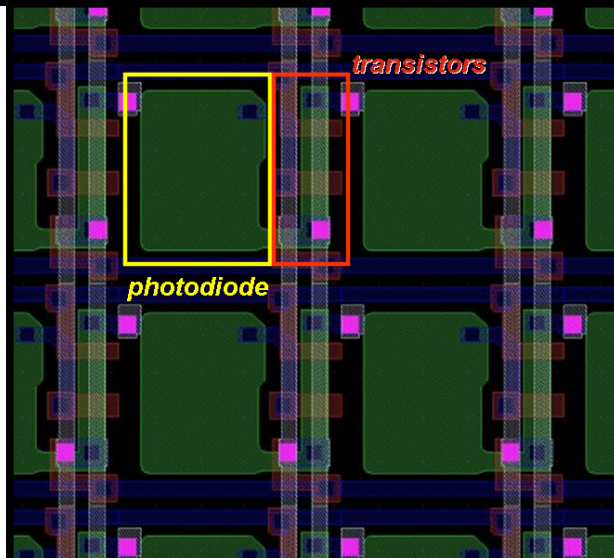
Completed 3K x 3K OTCCD Devices

- Large-area devices (26 mm x 50 mm) fabricated with low-voltage CCD technology
- Stitching methods achieve 35nm (3σ) precision with 8- μ m pixel active devices
- Device test results expected in Nov 2010
- Process technology will be migrated to 200-mm substrates

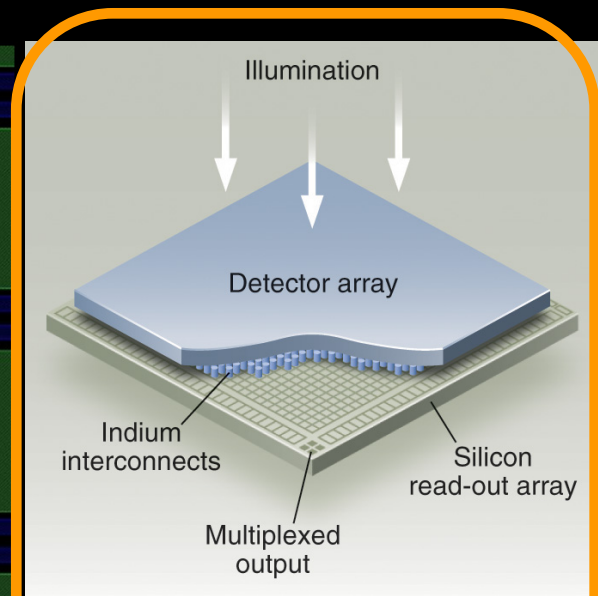




CCD



Monolithic CMOS

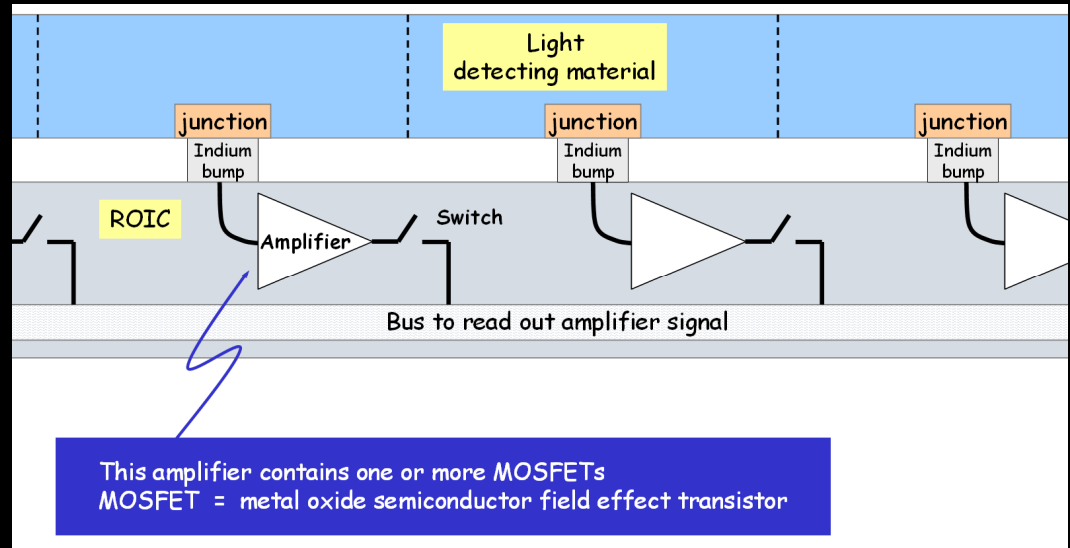
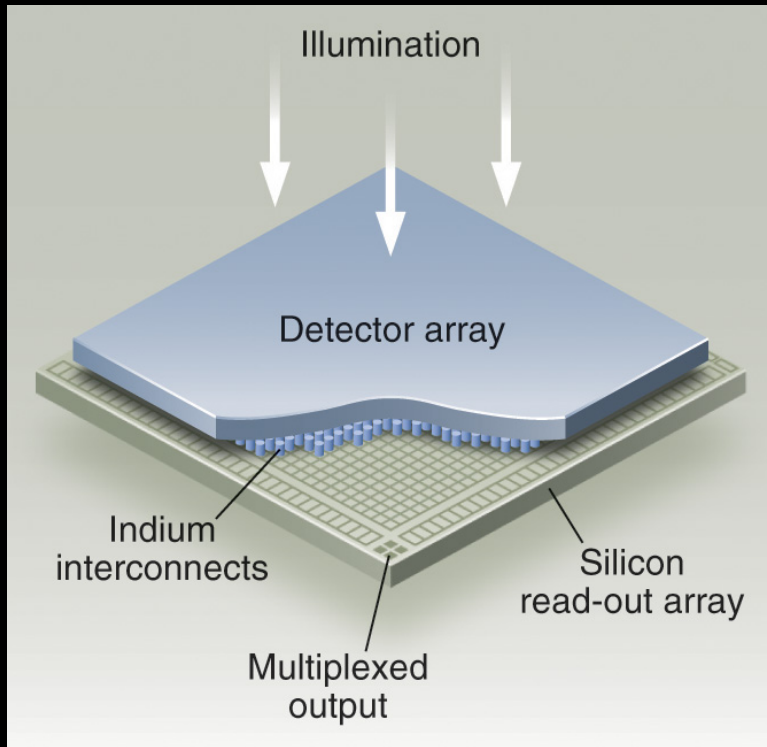


Hybrid CMOS

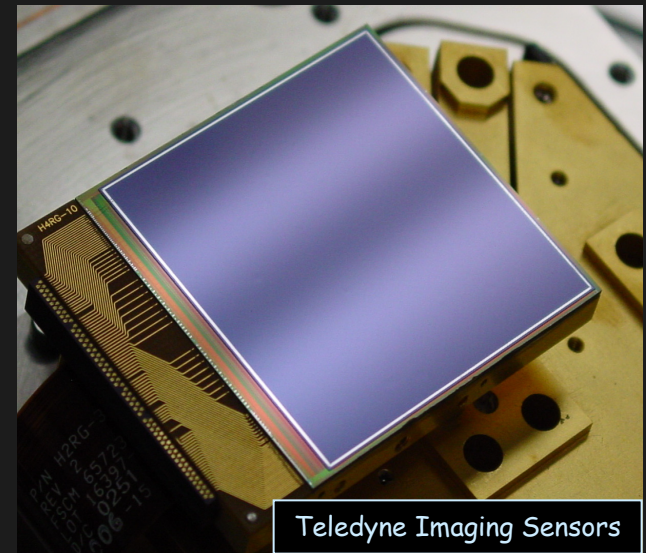
HgCdTe
Visible through IR

Silicon - Visible through near IR

Hybrid Imager Architecture

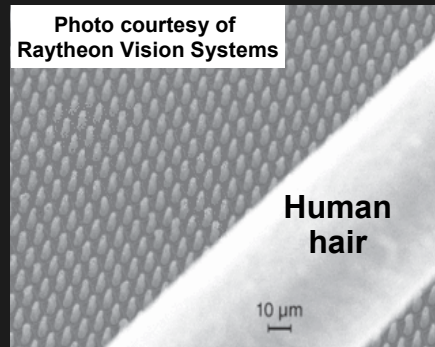


H4RG-10
4096x4096 pixels
10 micron pixel pitch
HyViSI silicon PIN



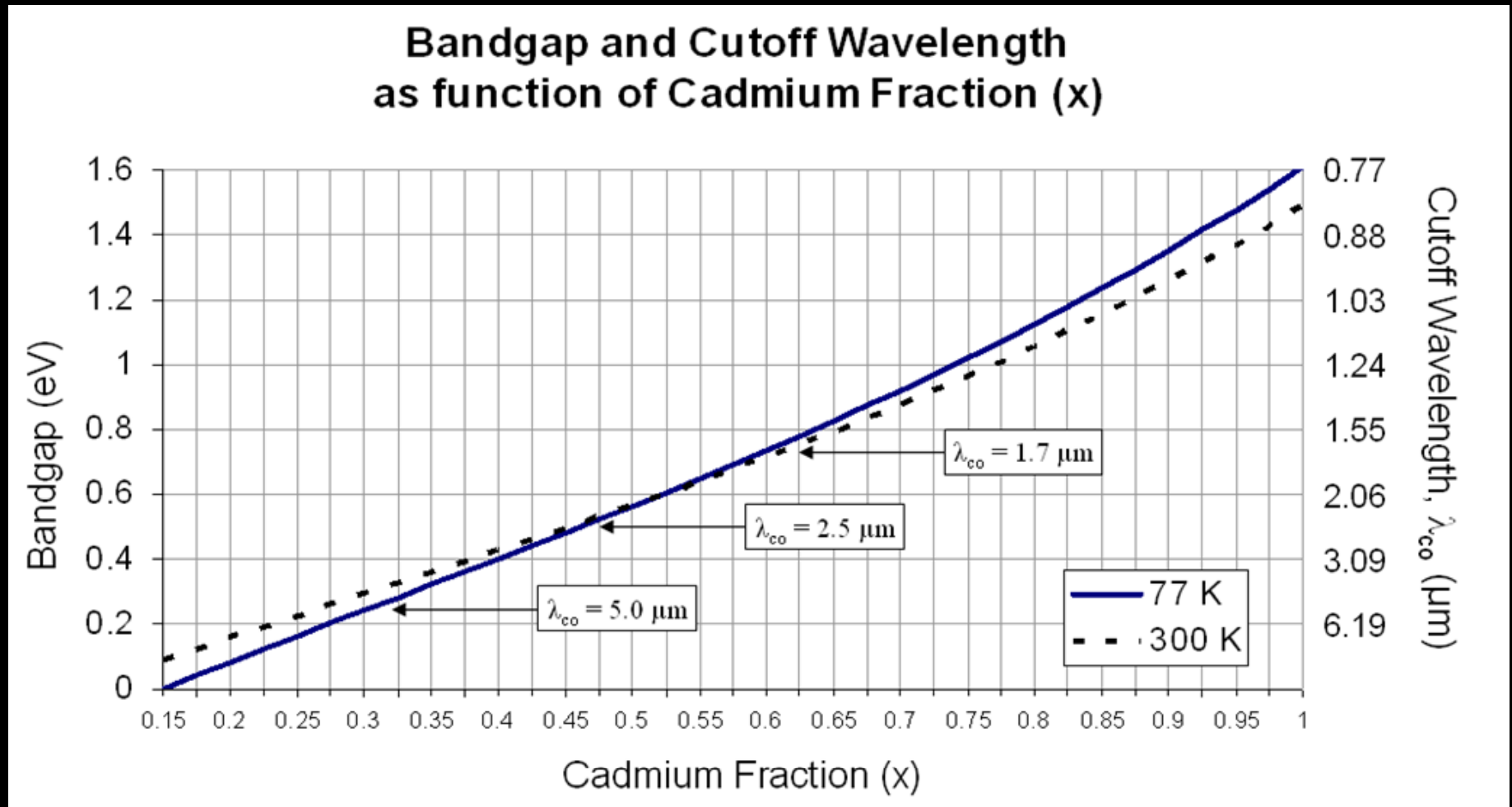
Mature interconnect technique:

- Over 16,000,000 indium bumps per Sensor Chip Assembly (SCA) demonstrated
- >99.9% interconnect yield



Tunable Wavelength: Valuable property of HgCdTe

$\text{Hg}_{1-x}\text{Cd}_x\text{Te}$ Modify ratio of Mercury and Cadmium to “tune” the bandgap energy



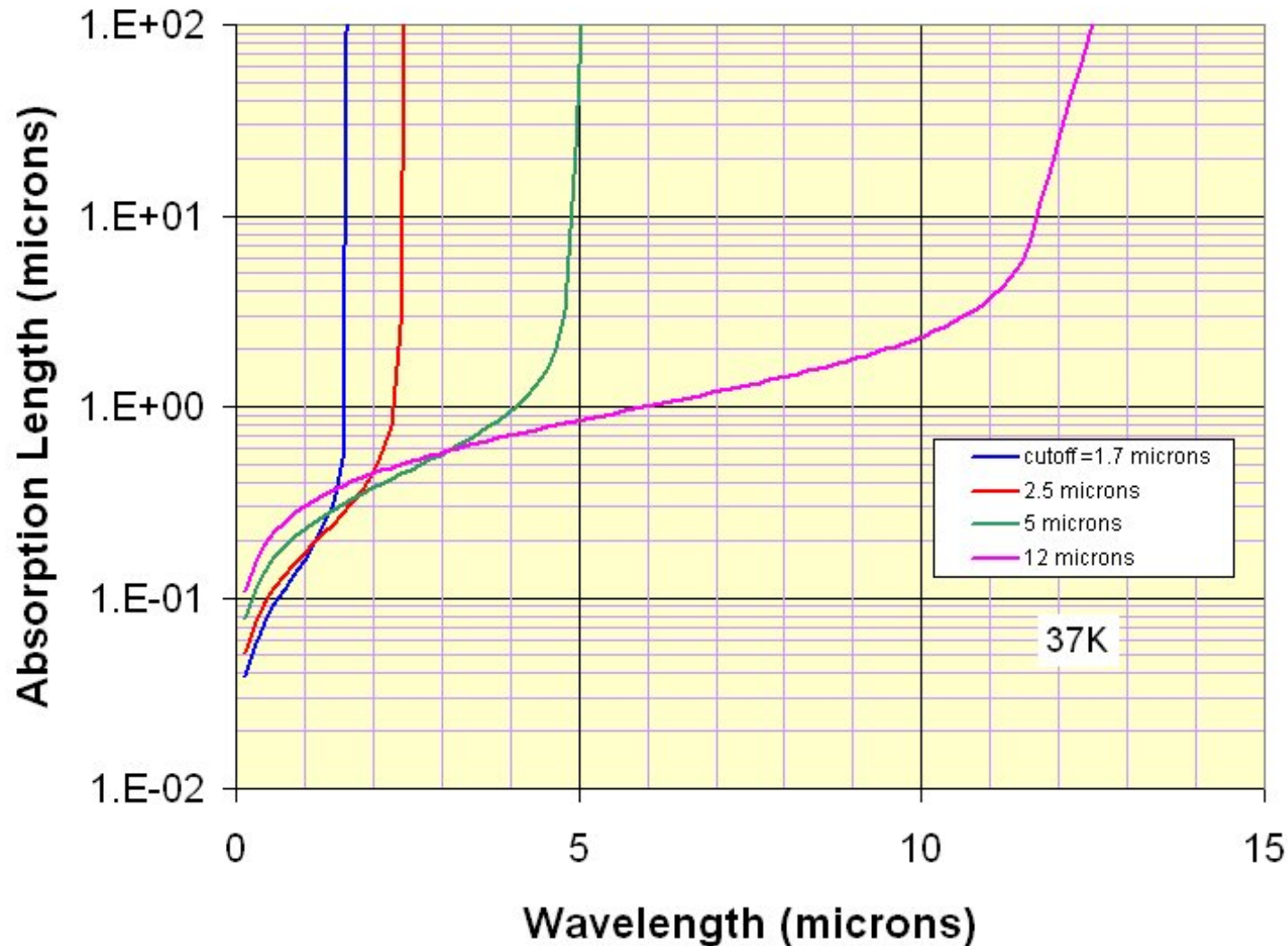
$$E_g = -0.302 + 1.93x - 0.81x^2 + 0.832x^3 + 5.35 \times 10^{-4} T(1 - 2x)$$

G. L. Hansen, J. L. Schmidt, T. N. Casselman, J. Appl. Phys. 53(10), 1982, p. 7099

Absorption Depth of HgCdTe

Rule of Thumb

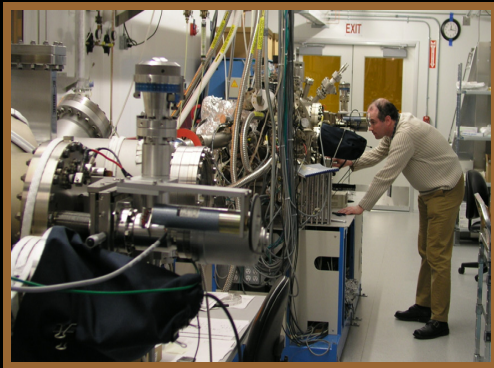
Thickness of HgCdTe layer needs to be about equal to the cutoff wavelength



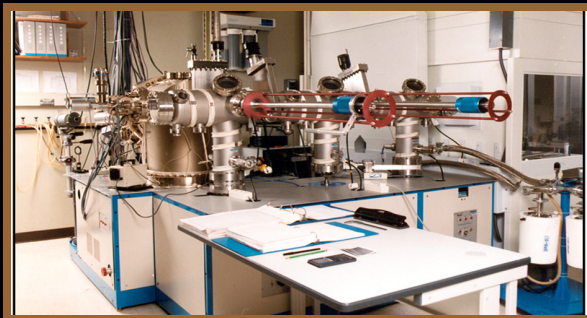
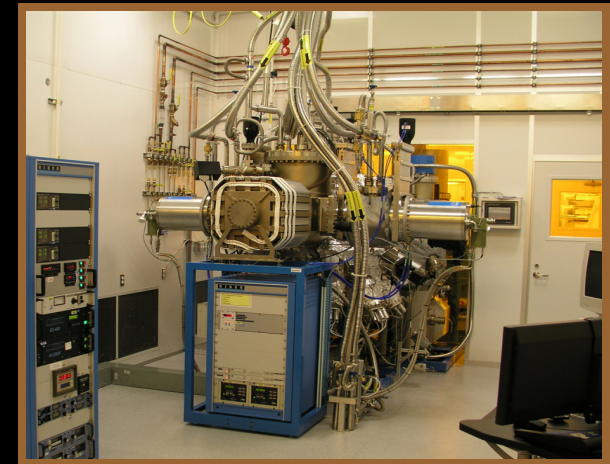
MBE growth of HgCdTe

1. Molecular Beam Epitaxy (MBE)

- Enables very accurate deposition \Rightarrow “bandgap engineering”
- Teledyne has 4 MBE machines for detector growth



RIBER 10-in MBE 49 System

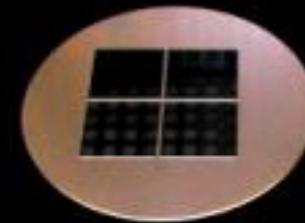


RIBER 3-in MBE Systems



3 inch diameter platen allows growth on one 6x6 cm substrate

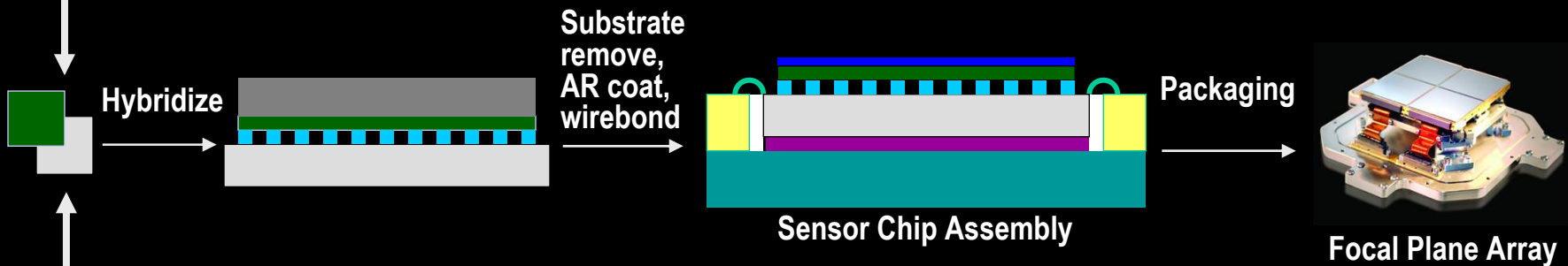
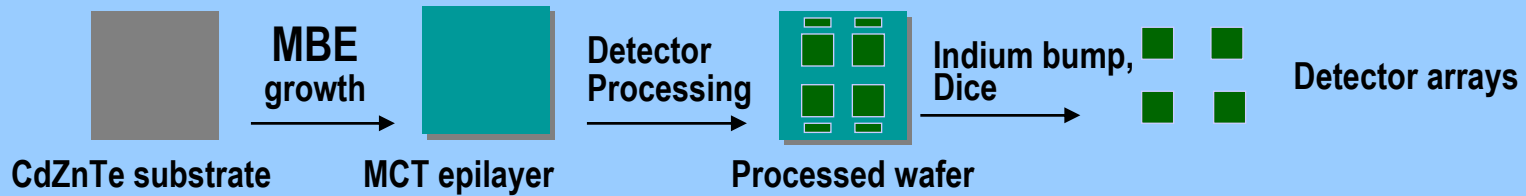
More than 7500 MCT wafers grown to date



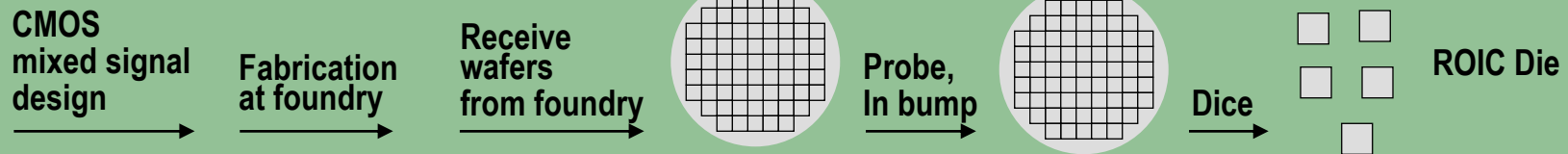
10 inch diameter platen allows simultaneous growth on four 6x6 cm substrates

HgCdTe IR FPA Manufacturing Process

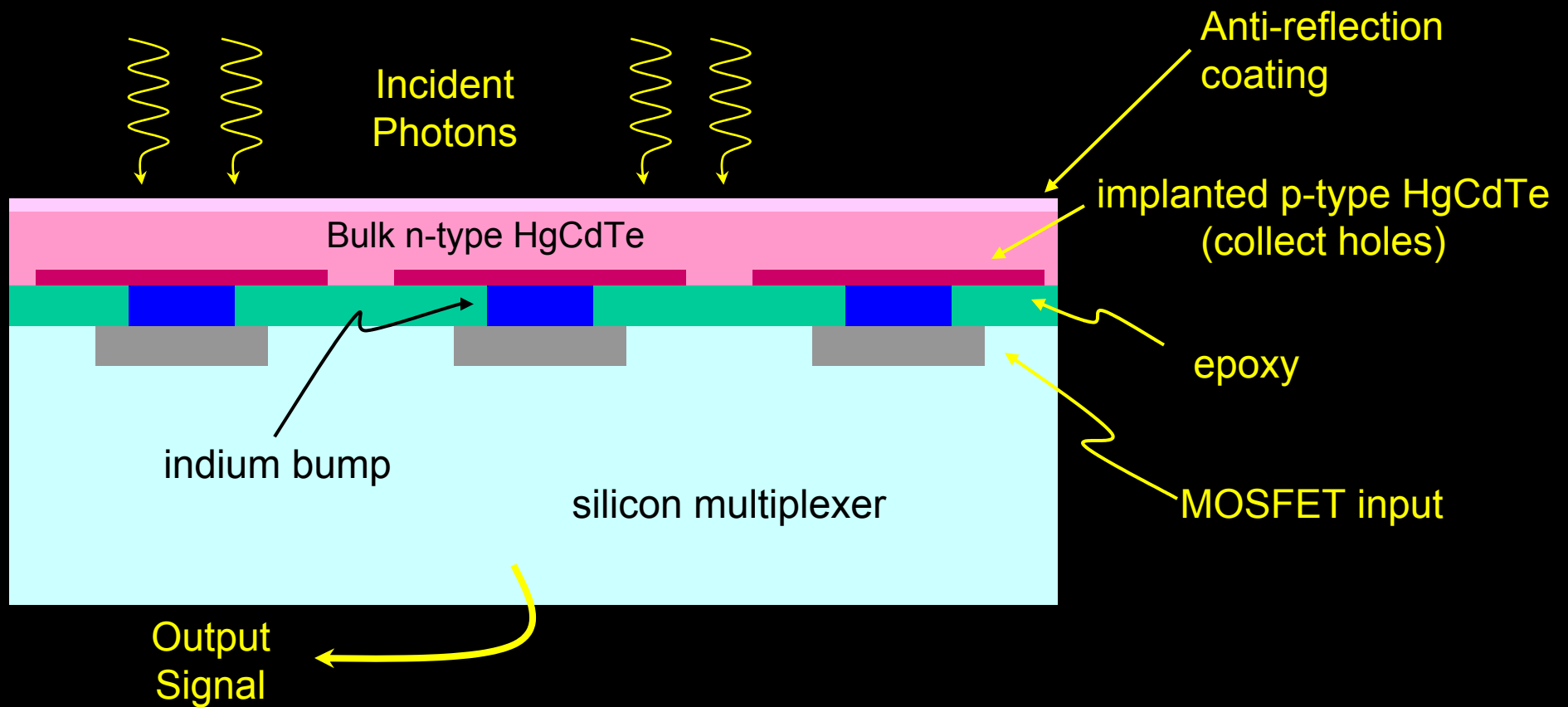
Detector Fabrication



Multiplexer Design and Fabrication

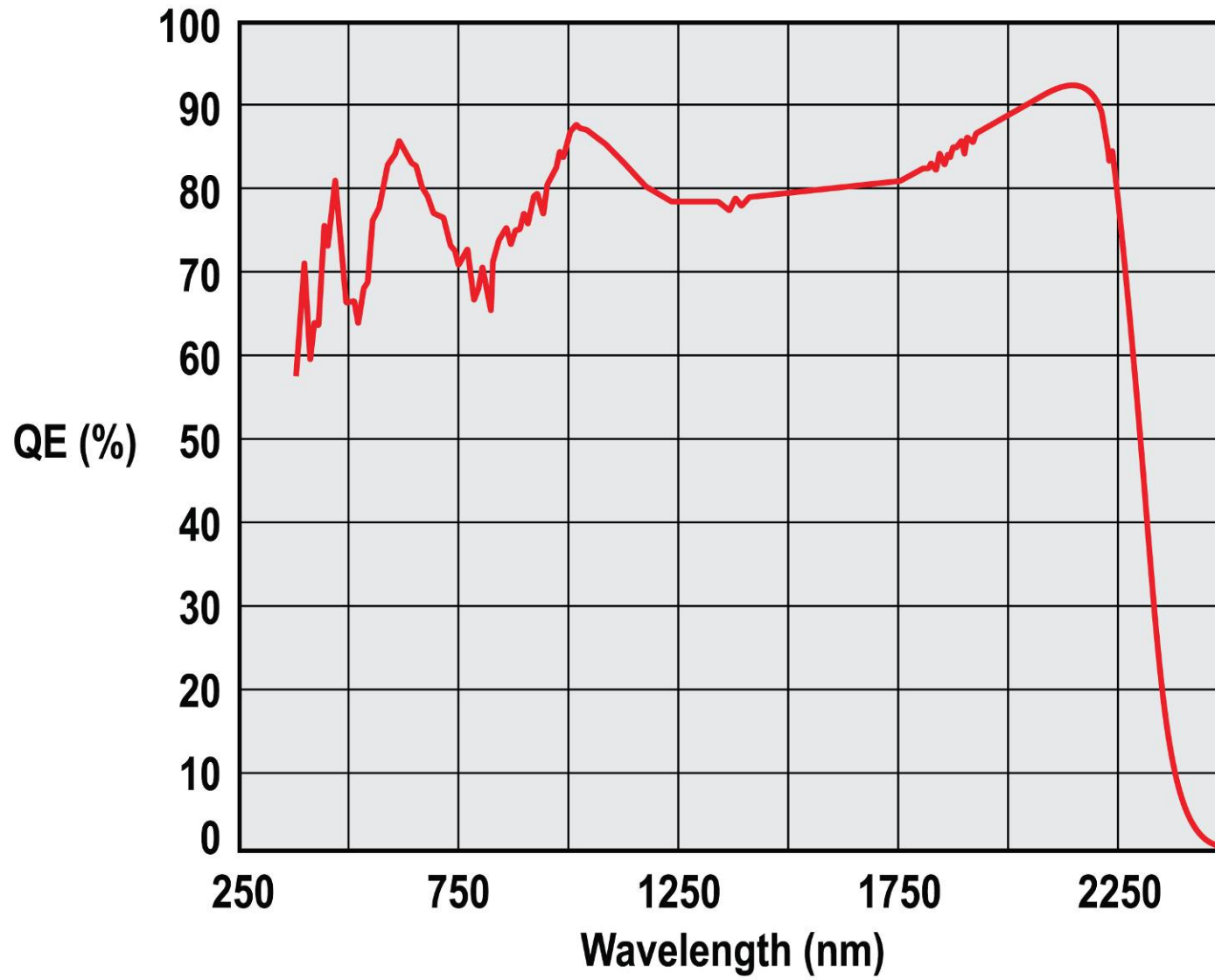


HgCdTe hybrid FPA cross-section (substrate removed)



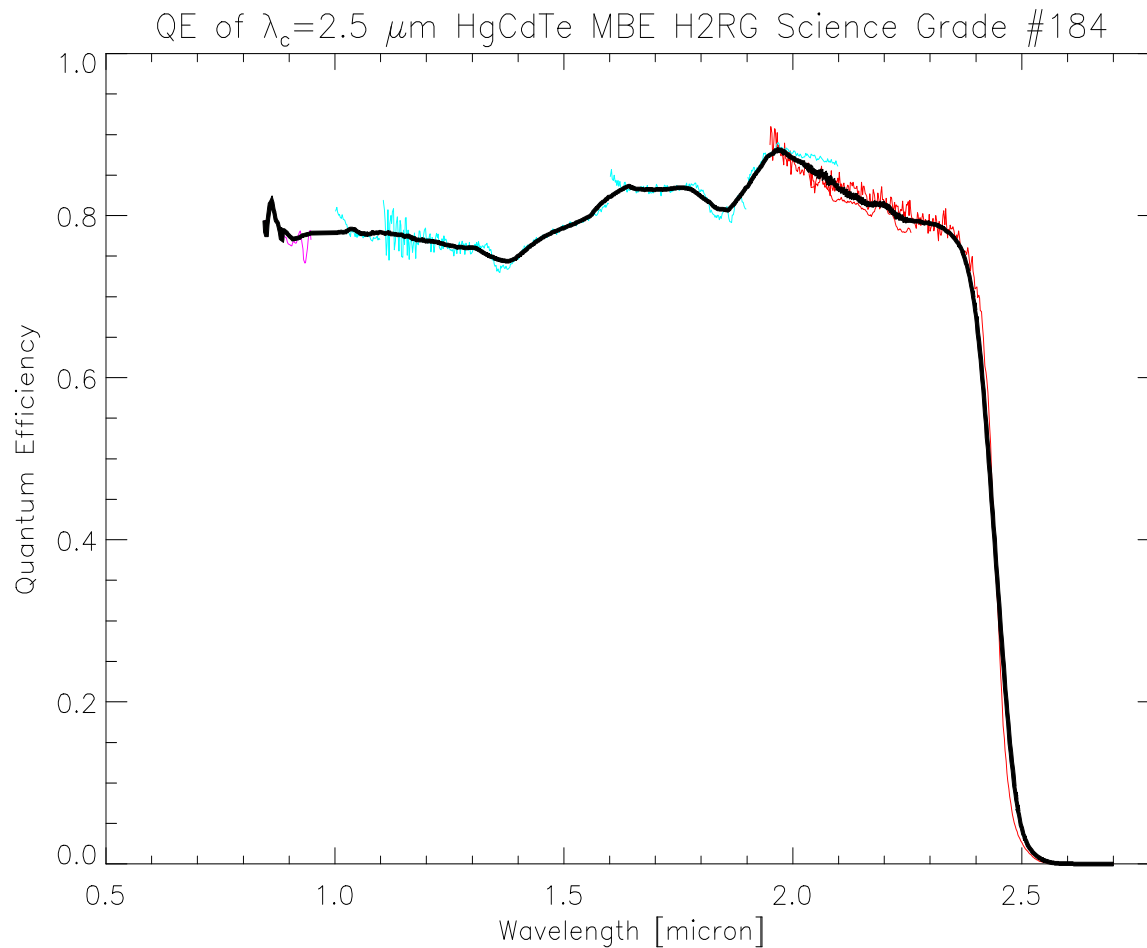
- Field in detector layer pushes charge to p-n junction
- Thin detector minimizes charge diffusion

Vis-SWIR Hyperspectral Imaging (Substrate Removed HgCdTe FPA)



Public Domain Information - OSR Public Release Authority (08-S-0965).

HgCdTe Quantum Efficiency Measured by the European Southern Observatory

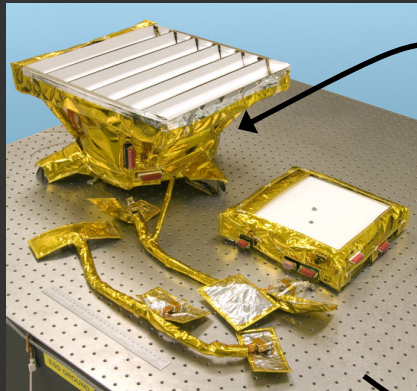


Data: Courtesy of ESO, KMOS project

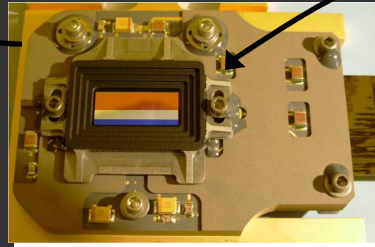
Moon Mineralogy Mapper Discovers Water on the Moon

Moon water findings are a game-changer

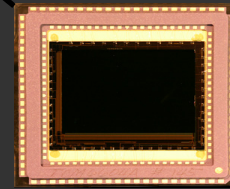
Discovery calls into question 40 years of assumptions about lunar surface



Instrument at JPL before shipment to India



Focal Plane Assembly



Sensor Chip Assembly

Teledyne Infrared FPA

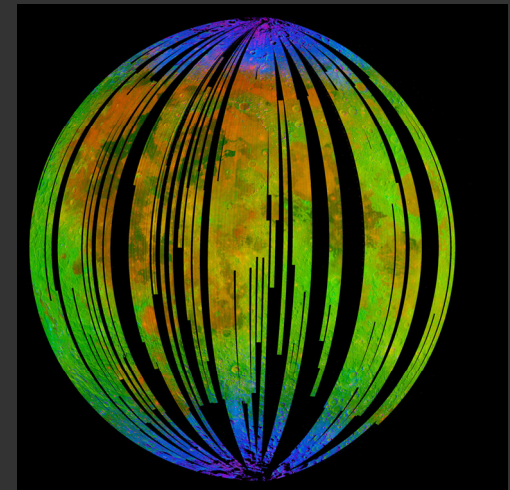
- 640 x 480 pixels (27 μm pitch)
- Substrate-removed HgCdTe (0.4 to 3.0 μm)
- 650,000 e- full well, <100 e- noise
- 100 Hz frame rate (integrate while read)
- < 70 mW power dissipation
- Package includes order sorting filter
- Total FPA mass: 58 grams

By Andrea Thompson

SPACE

updated 12:38 p.m. PT, Thurs., Sept. 24, 2009

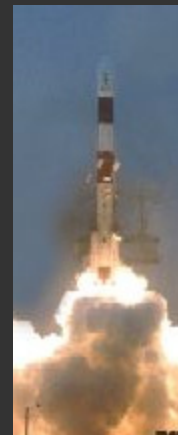
The discovery of widespread but small amounts of water on the surface of the moon, announced Wednesday, stands as one of the most surprising findings in planetary science.



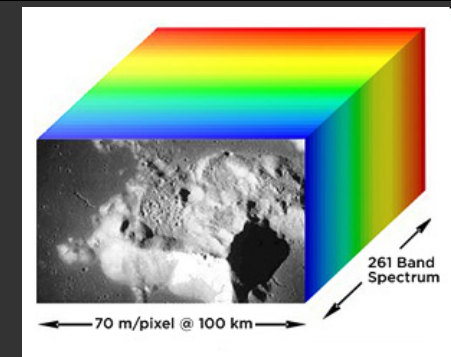
Completion of Chandrayaan-1 spacecraft integration
Moon Mineralogy Mapper is white square at end of arrow



Chandrayaan-1 in the
Polar Satellite Launch Vehicle

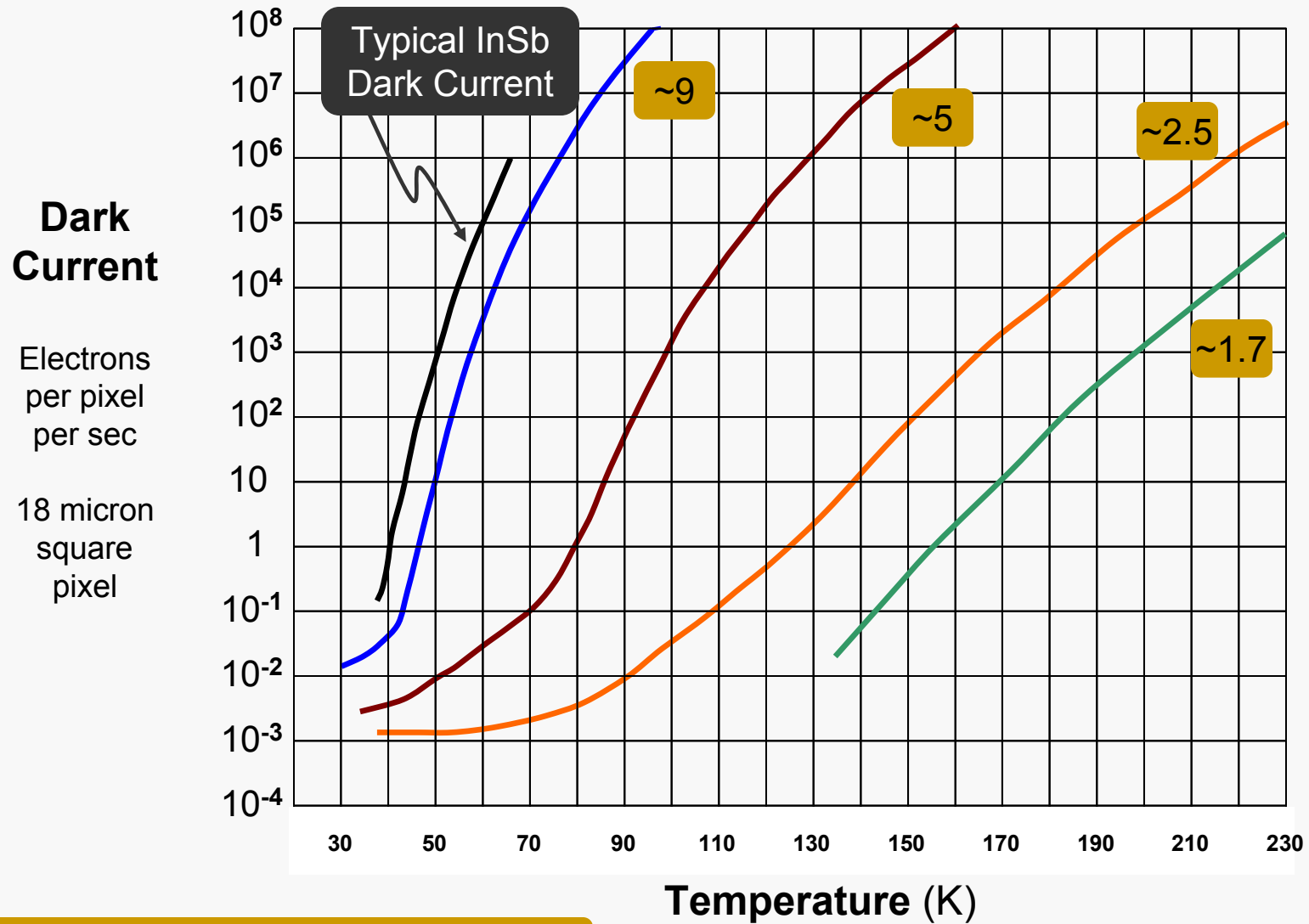


Launch from Satish
Dhawan Space Centre



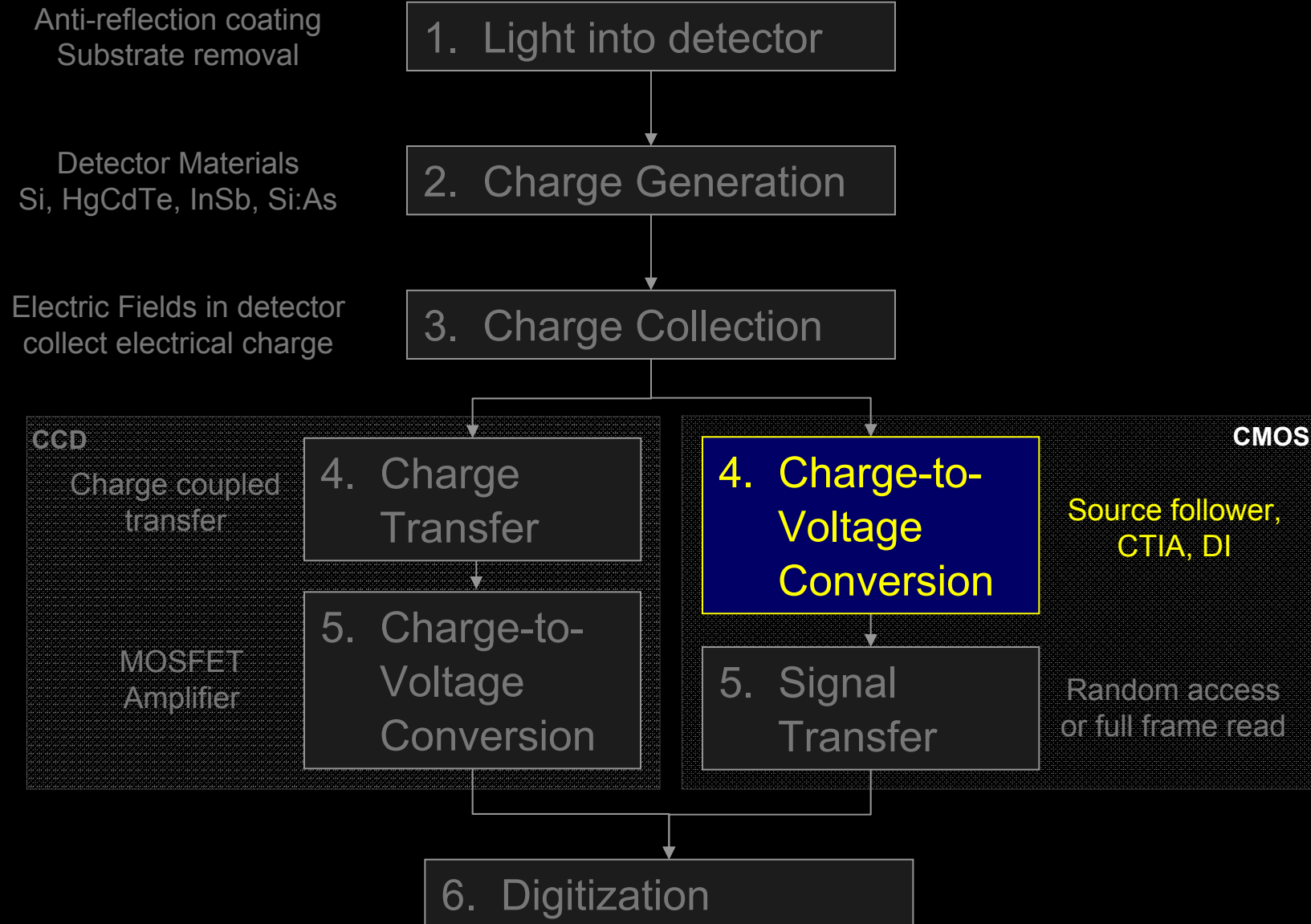
Moon Mineralogy Mapper resolves visible and infrared
to 10 nm spectral resolution, 70 m spatial resolution
100 km altitude lunar orbit

Dark Current of HgCdTe Detectors

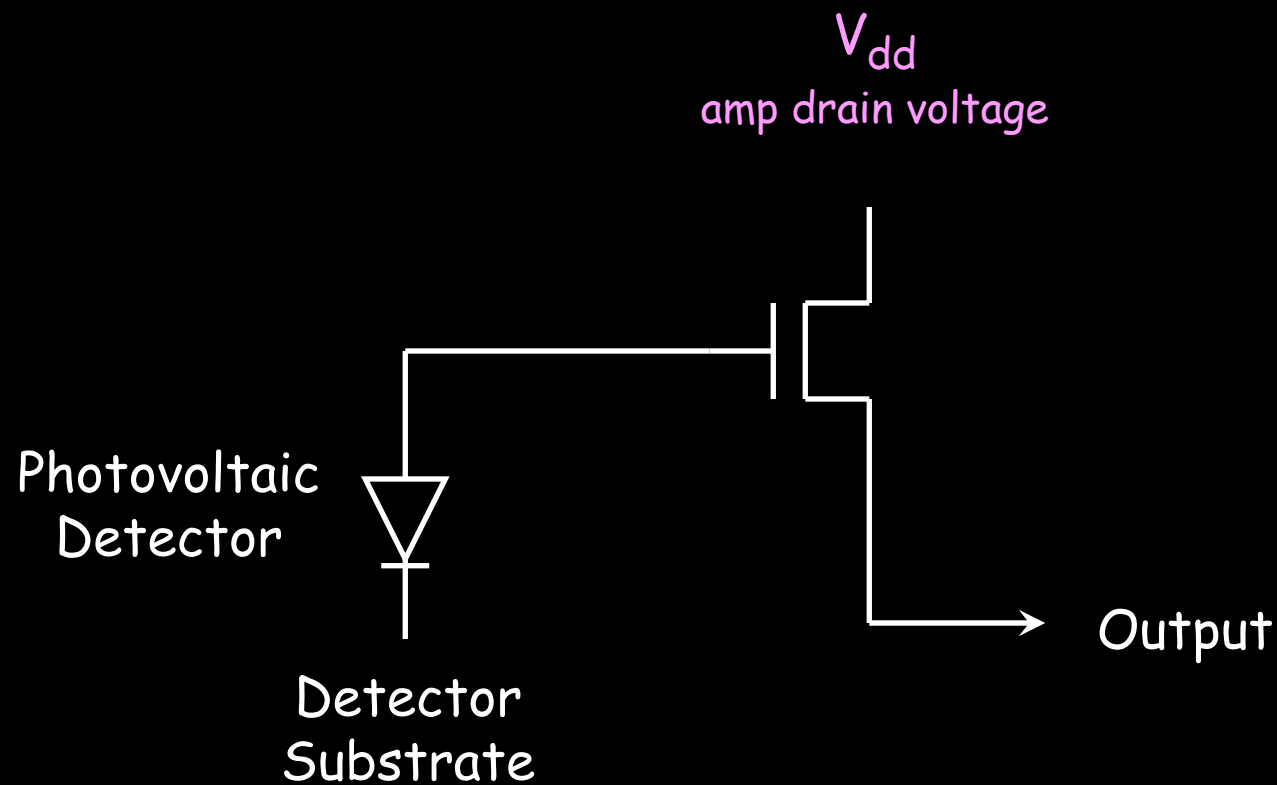


HgCdTe cutoff wavelength (microns)

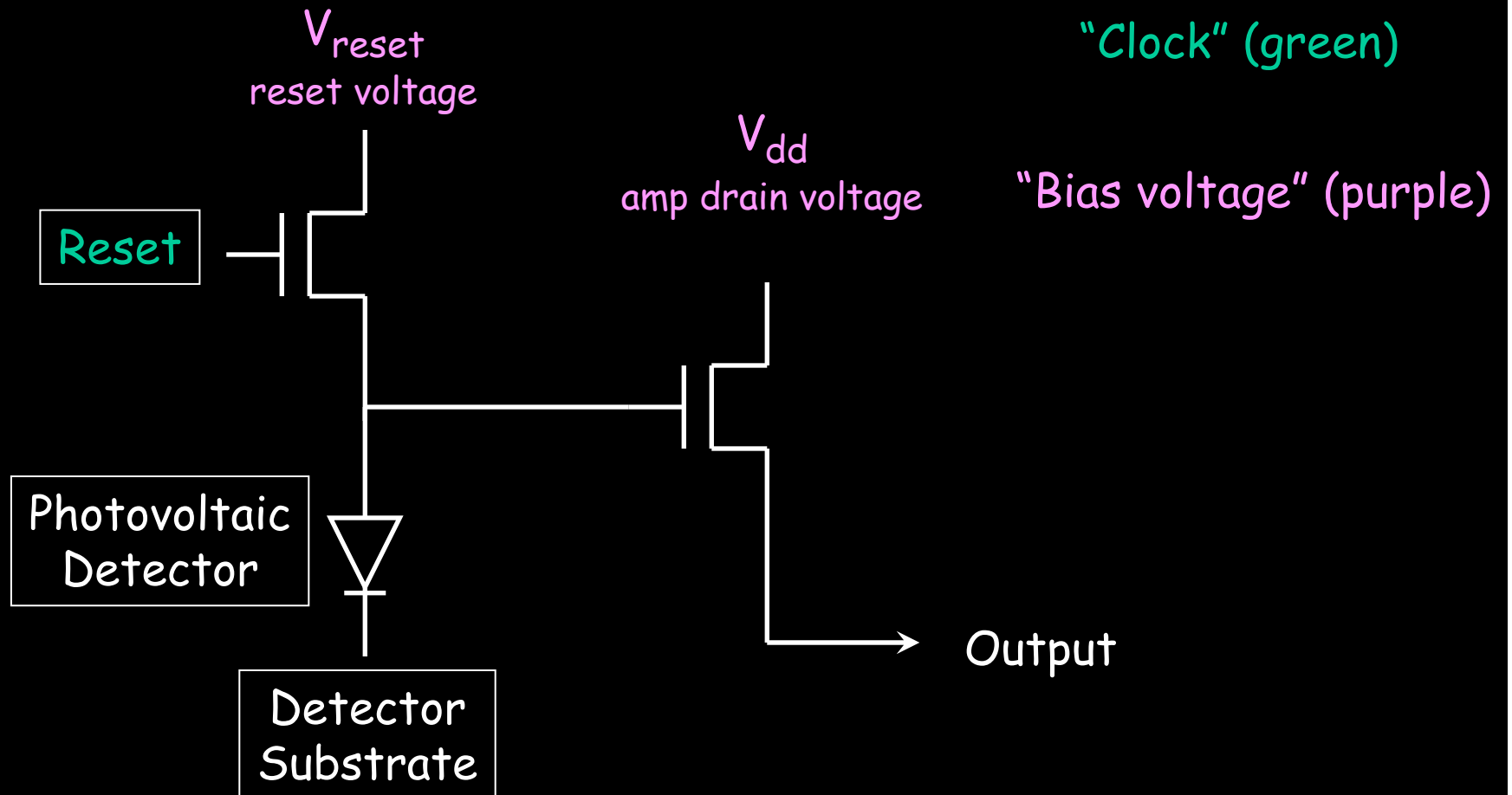
6 steps of optical / IR photon detection



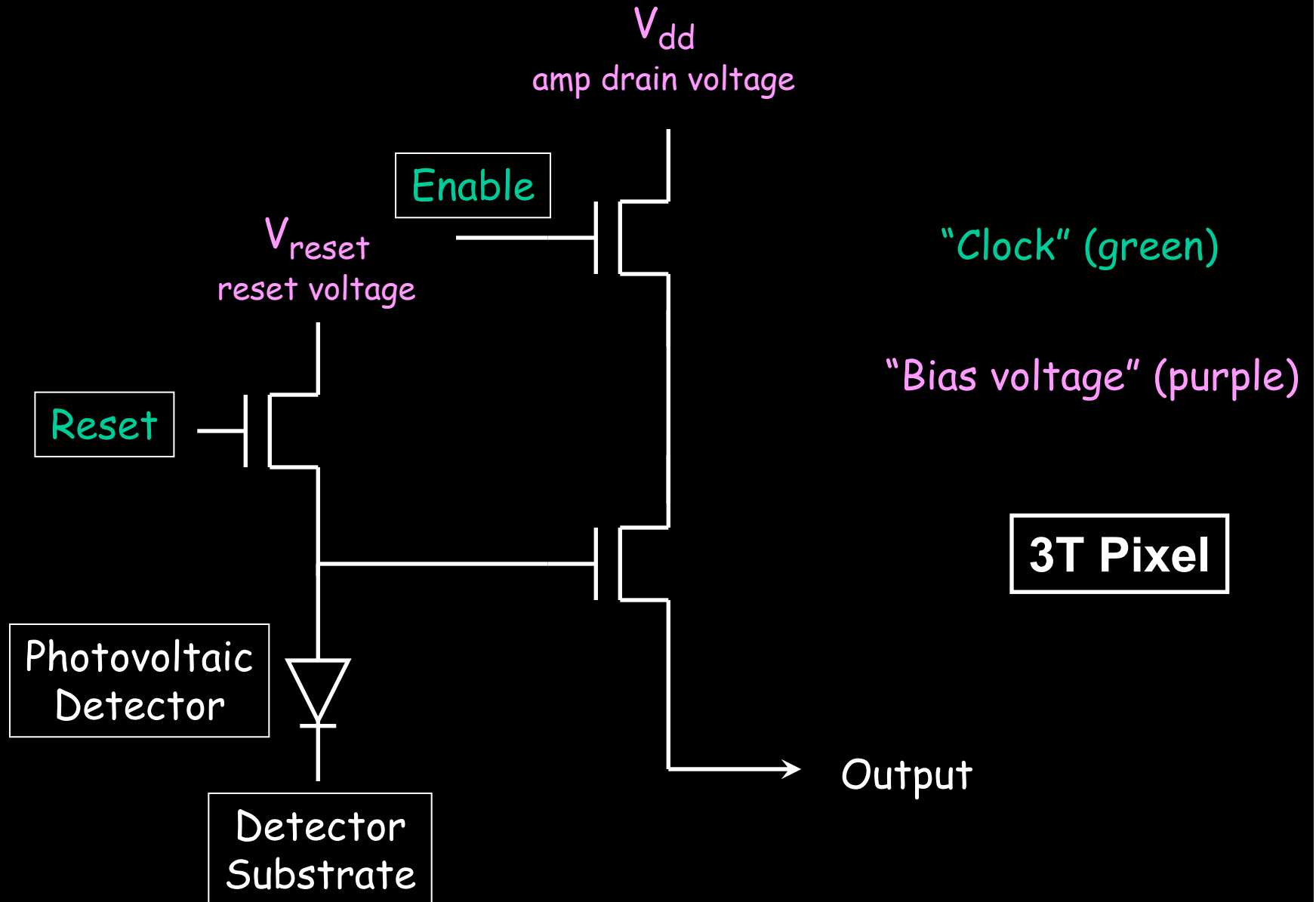
IR multiplexer pixel architecture



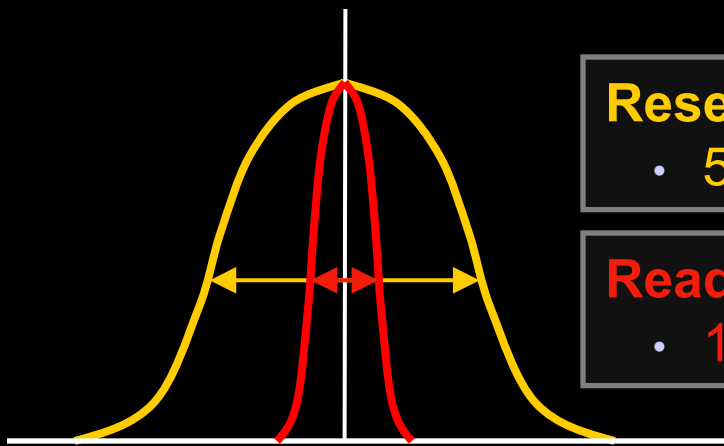
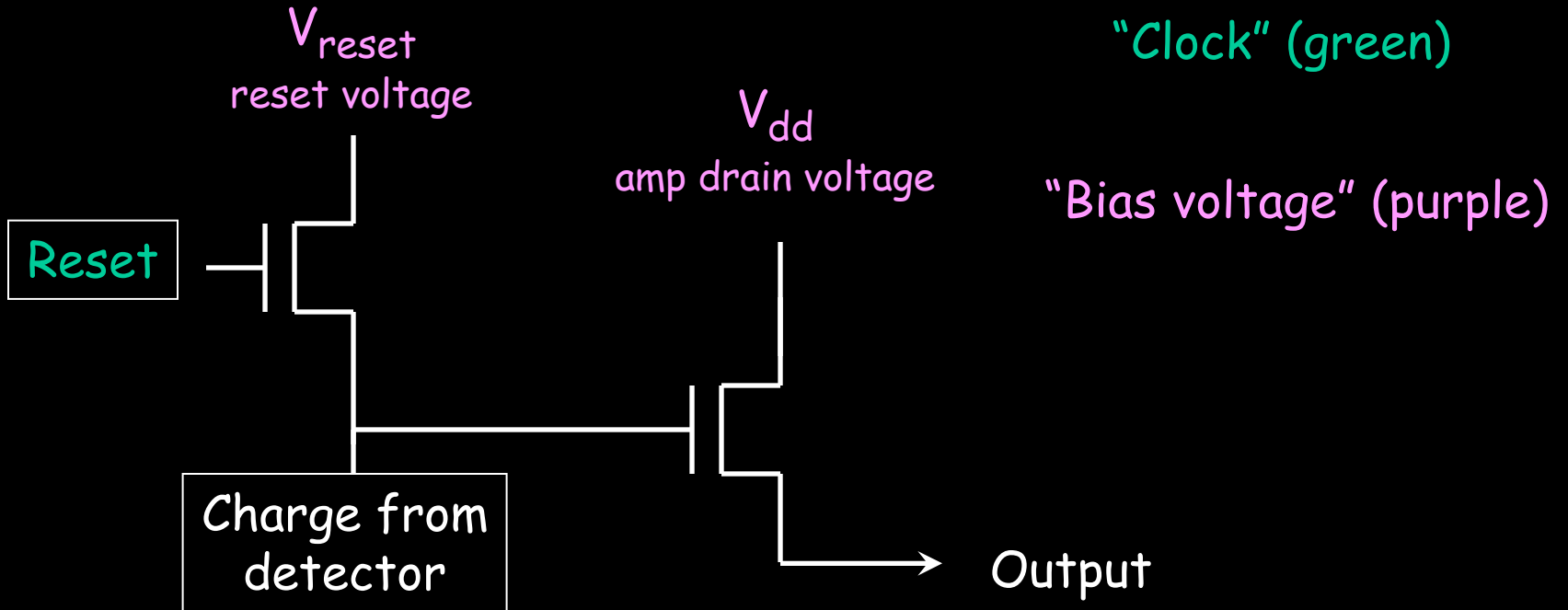
IR multiplexer pixel architecture



IR multiplexer pixel architecture



MOSFET Amplifier Noise



Reset Noise

- 50 to 100 e- rms

Read Noise

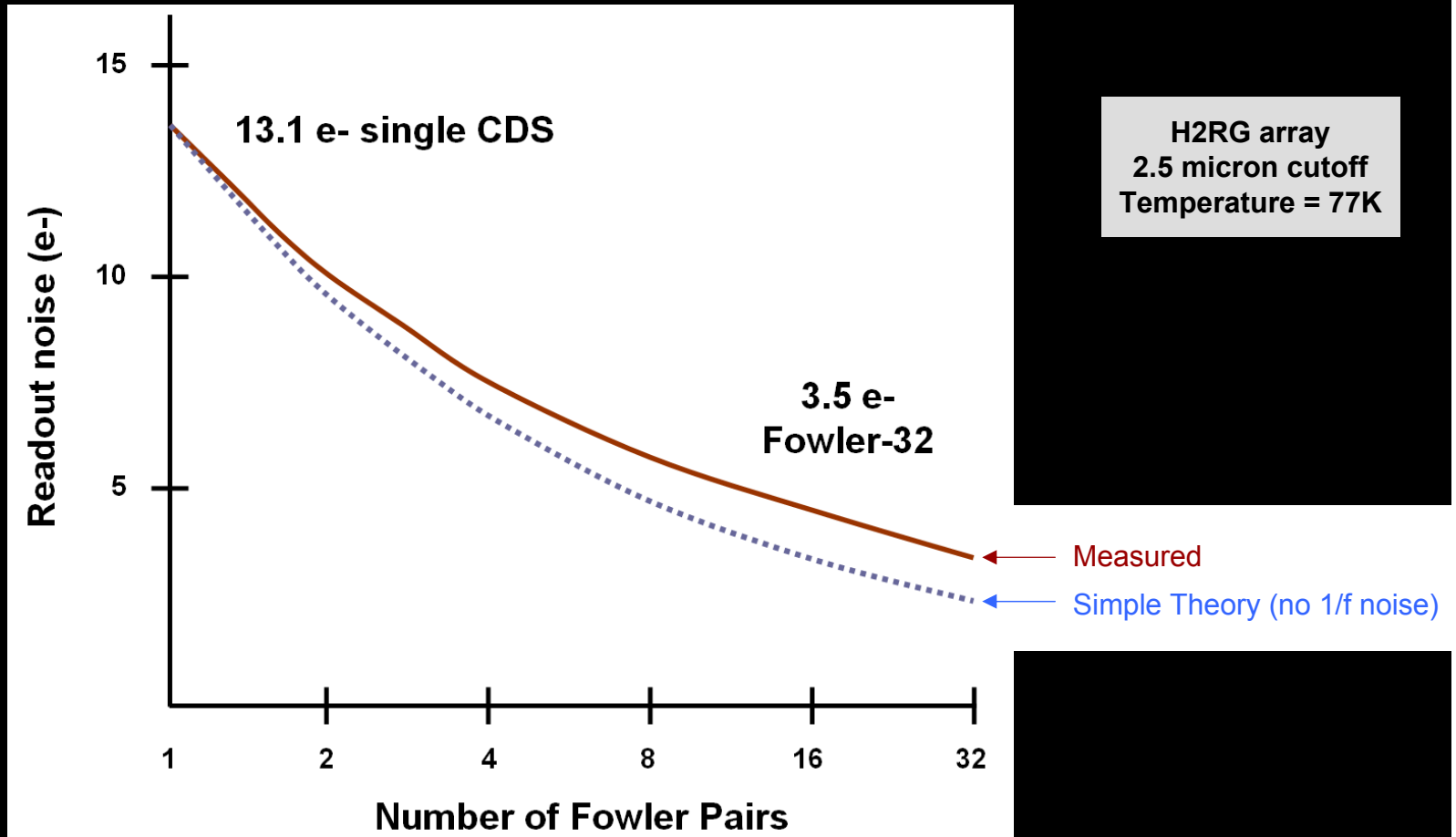
- 1.5 to 10 e- rms

Correlated Double Sample (CDS)

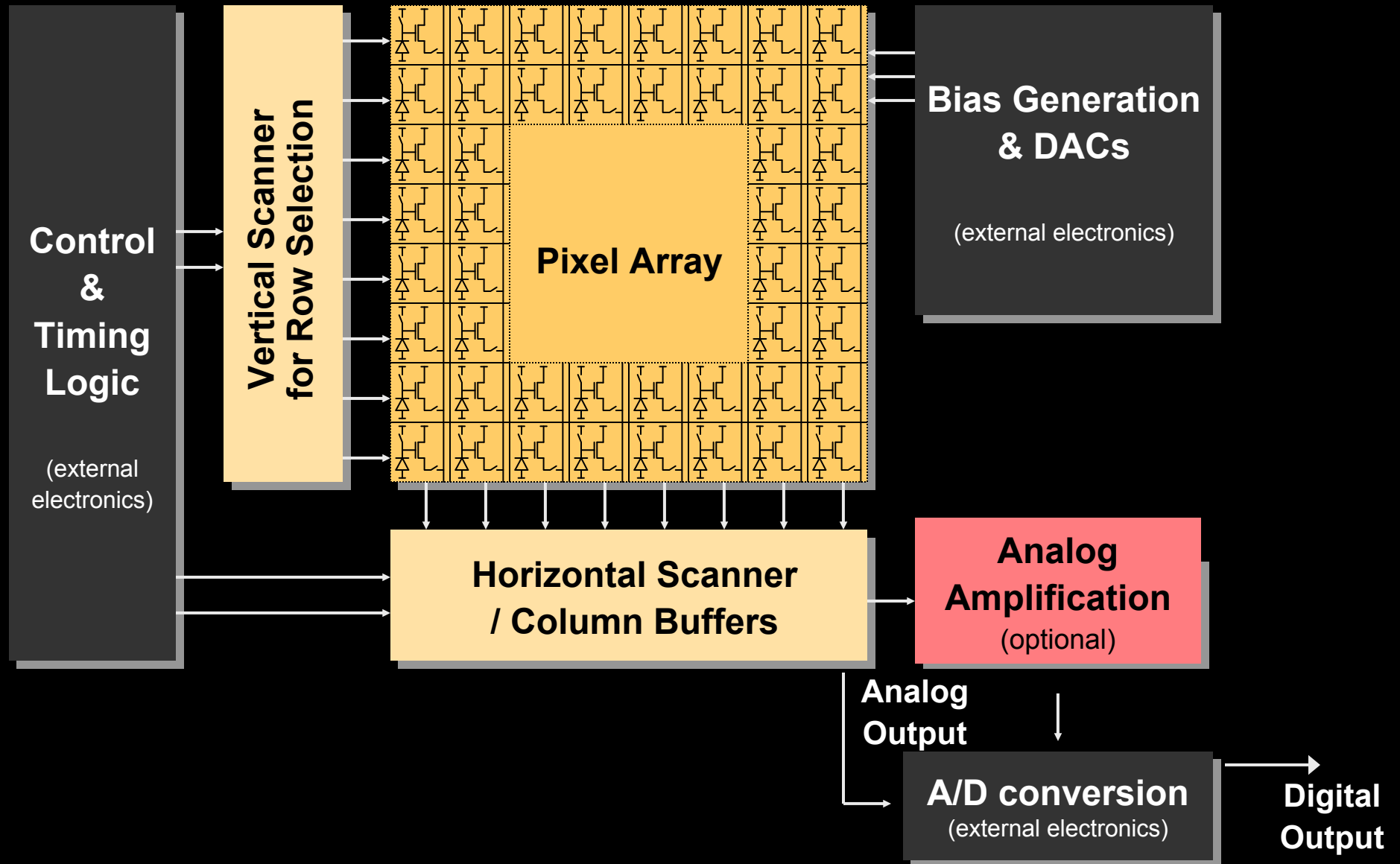
- Reset
- Read
- Put charge on gate
- Read

Example of Noise vs Number of Fowler Samples

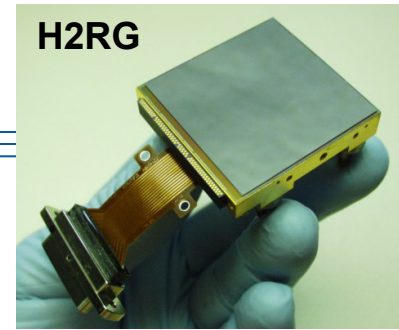
Non-destructive readout enables reduction of noise from multiple samples



Architecture of simplest analog CMOS sensor



HxRG Family of Hybrid Imaging Sensors



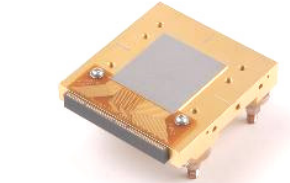
H: HAWAII: **H**gCdTe **A**stronomical **W**ide **A**rea **I**nfrared **I**mager
x: Number of 1024 (or 1K) pixel blocks in x and y-dimensions
R: **R**eference pixels
G: **G**uide window capability

- ➔ Substrate-removed HgCdTe for simultaneous visible & infrared observation
- ➔ Hybrid Visible Silicon Imager; Si-PIN (HyViSI)

Name	Format (# of Pixel)	Pixel Pitch (μm)	# of Outputs	NASA - TRL	Institutions, Observatories, and Programs Using HxRG Arrays
H1RG	1024×1024	18	1, 2, 16	9	Wide-field Infrared Survey Explorer (WISE) Orbiting Carbon Observatory (OCO) Development Programs in Astronomy & Earth Science
H2RG	2048×2048	18	1, 4, 32	6	James Webb Space Telescope (JWST) - NIRCam, NIRSpec, FGS Joint Dark Energy Mission (JDEM) Astronomy institutions and observatories: Calar Alto, Caltech, CFHT, ESO, ESTEC, Gemini, GSFC, IRTF, ISRO, IUCAA, JHU-APL, Keck, LBNL, LMU, MIT, MPIA, MPS, OCIW, Penn State, RIT, SALT, SAO, Subaru, TATA, U. Arizona, UCLA, UC Berkeley, U. Hawaii, U. Rochester, U. Toronto, U. Wisconsin Space surveillance applications
H4RG-10	4096×4096	10	1, 4, 16, 32, 64	6	Joint Milli-Arcsecond Pathfinder Survey (J-MAPS) Development Programs in Astronomy
H4RG-15	4096×4096	15	1, 4, 16, 32, 64	3	In Development, first on sky telescope test in 2011

HxRG Readout Integrated Circuit (ROIC) Architecture

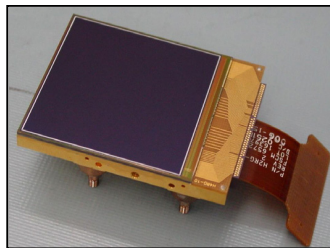
H1RG



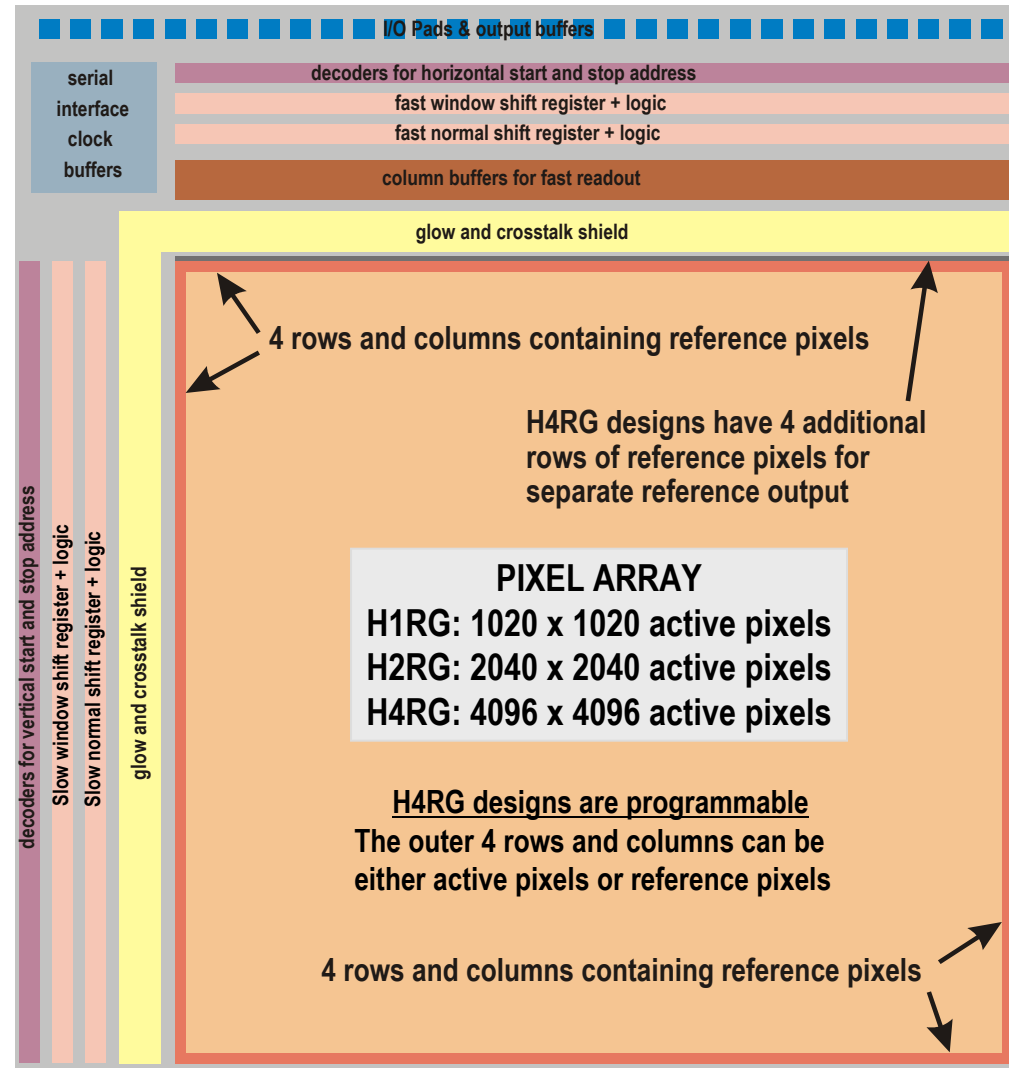
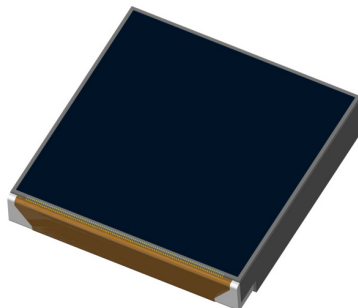
H2RG



H4RG-10

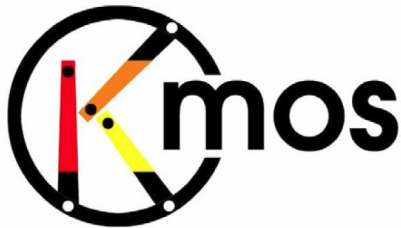
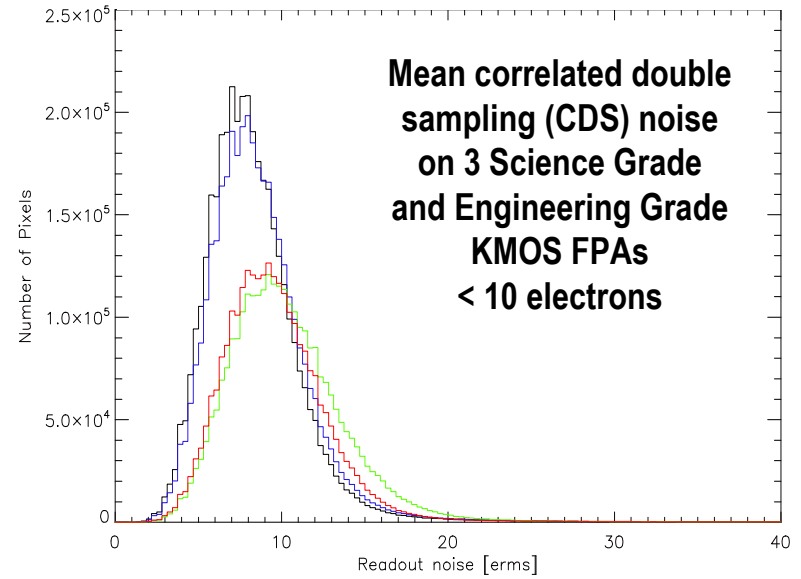
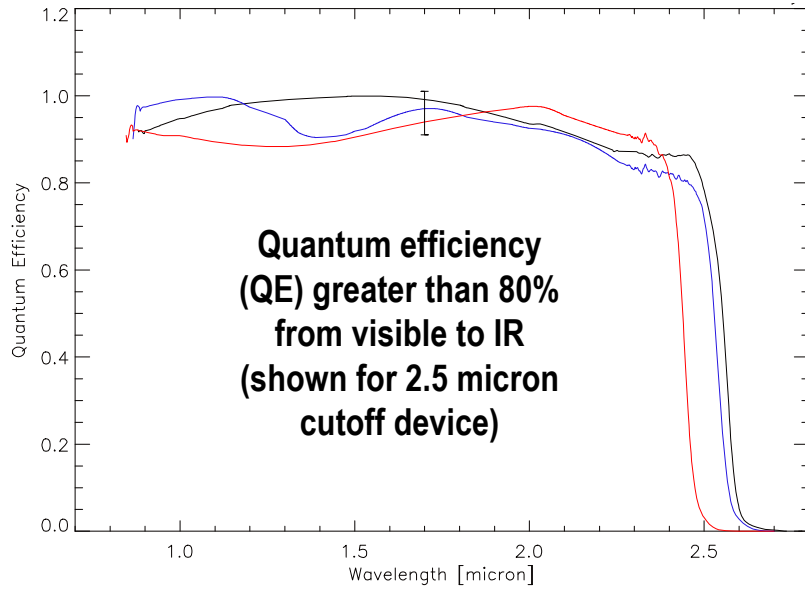


H4RG-15

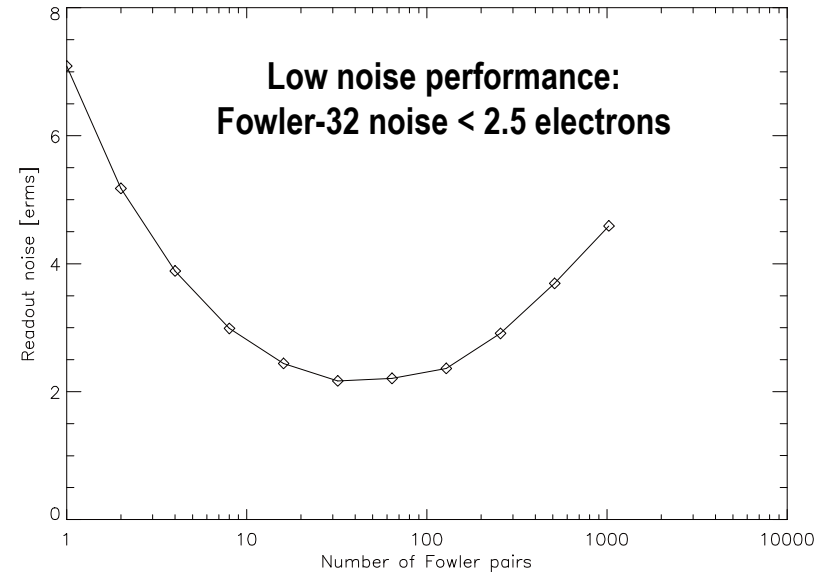


H4RG-15 adds programmable column deselect and serial register read-back

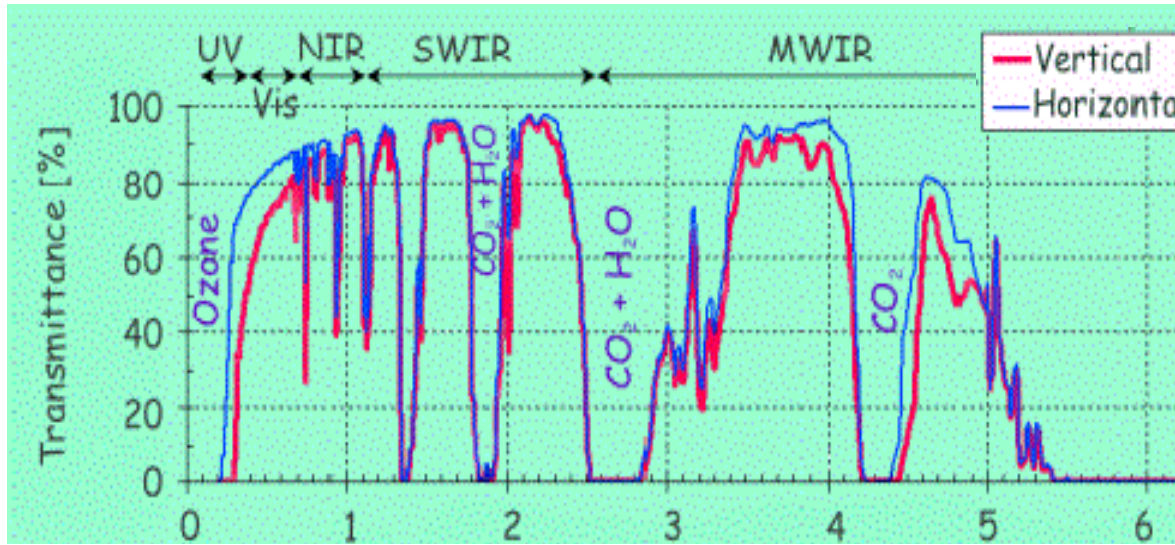
H2RG Performance Confirmed by ESO



Data: Courtesy of ESO, KMOS project



H2RG Standard Cutoff wavelengths

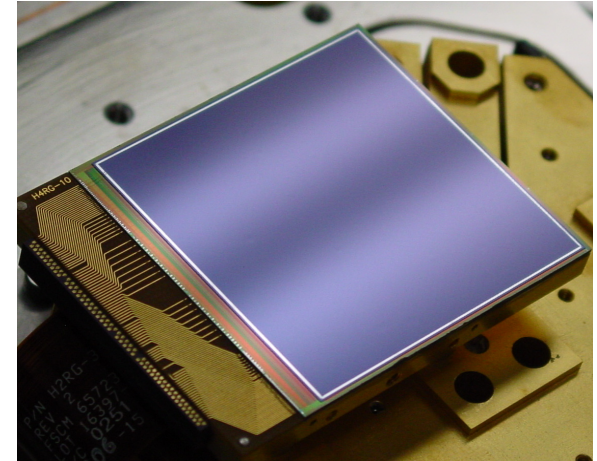


- The cutoff wavelength can be tuned to the scientific application
- To achieve economy of scale, Teledyne produces the H2RG with 3 cutoff wavelengths:
 - 1.75 microns
 - 2.5 microns
 - 5.3 microns

Large Visible Astronomy Focal Plane Array: H4RG-10

H4RG-10: 4096 x 4096, 10 μm Pixel Pitch FPA

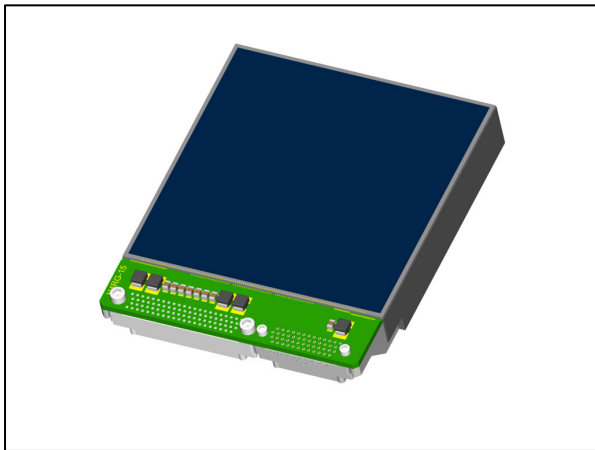
- H4RG-10 Hybrid Visible Silicon Imager (HyViSI™) focal plane array is baseline precision astrometry space mission Joint Milliarcsecond Pathfinder Survey (J-MAPS) by the US Naval Observatory (USNO)
 - ❑ First use of CMOS for astrometry in space
 - ❑ 2x2 H4RG-10 mosaic – 67 Megapixel Imager
- Focal planes delivered in 2008 and 2009 provide required performance at 193 K
- 2009 / 10 focus on operability improvement
 - ❑ Operability > 99.9%
- Flight arrays will be delivered to the U.S. Naval Research Laboratory (NRL) in 2011



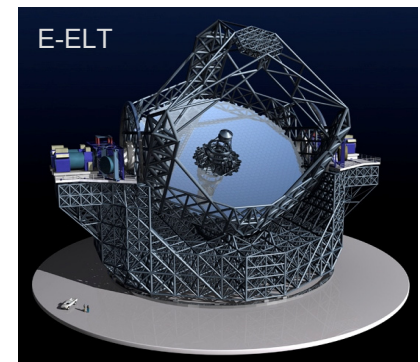
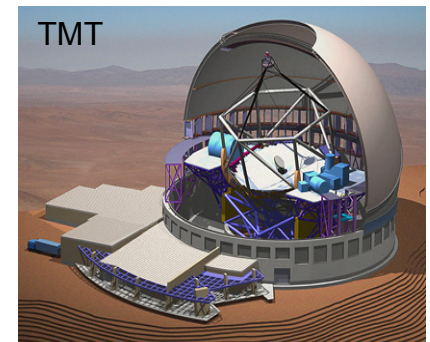
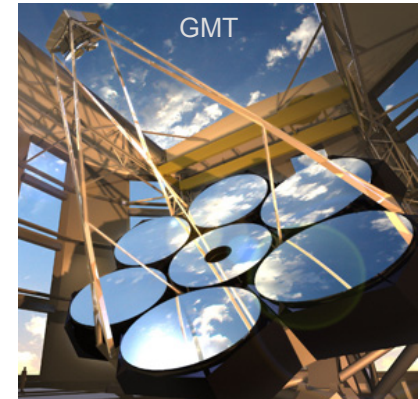
H4RG-10 HyViSI Prototype Focal Plane Array

Large Infrared Focal Plane Development: H4RG-15

- 4096×4096, 15 μm pixel pitch array
- Significantly reduce price / pixel and maintain established H2RG performance
- Four-side buttable (three-side close buttable) for large mosaics
- H4RG-15 adds:
 - Programmable column deselect and other advanced features for manufacturability
 - Serial register read back



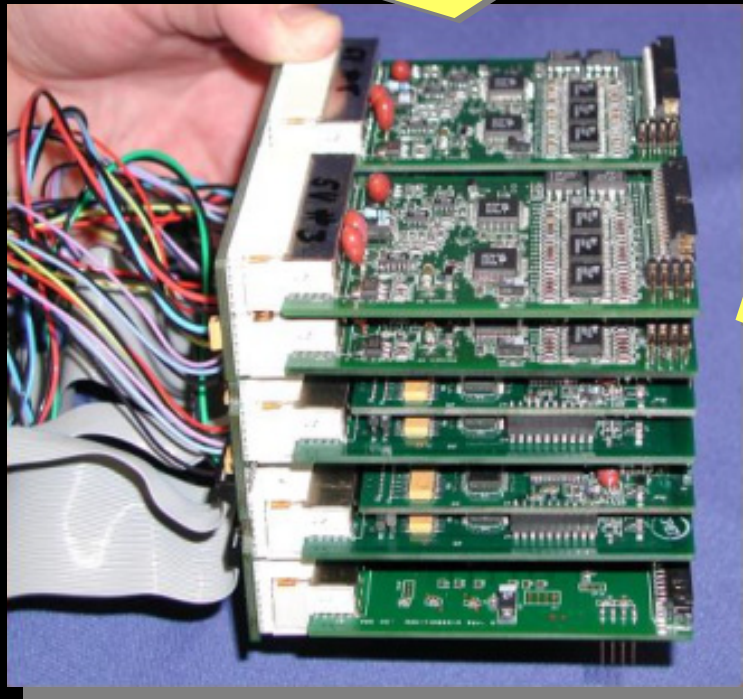
- \$6.2M grant received from the U.S. National Science Foundation (NSF)
- Project kicked off December 2009
- H4RG-15 readout circuit taped out 25 June 2010
- First prototype arrays are planned to ship to University of Hawaii in summer of 2011 for on-sky testing



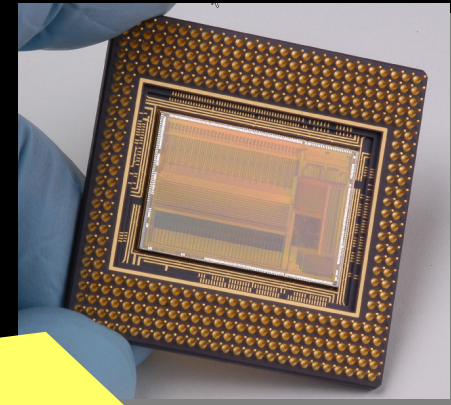
The SIDECAR ASIC

Complete Electronics on a Chip

Replace this



with this!

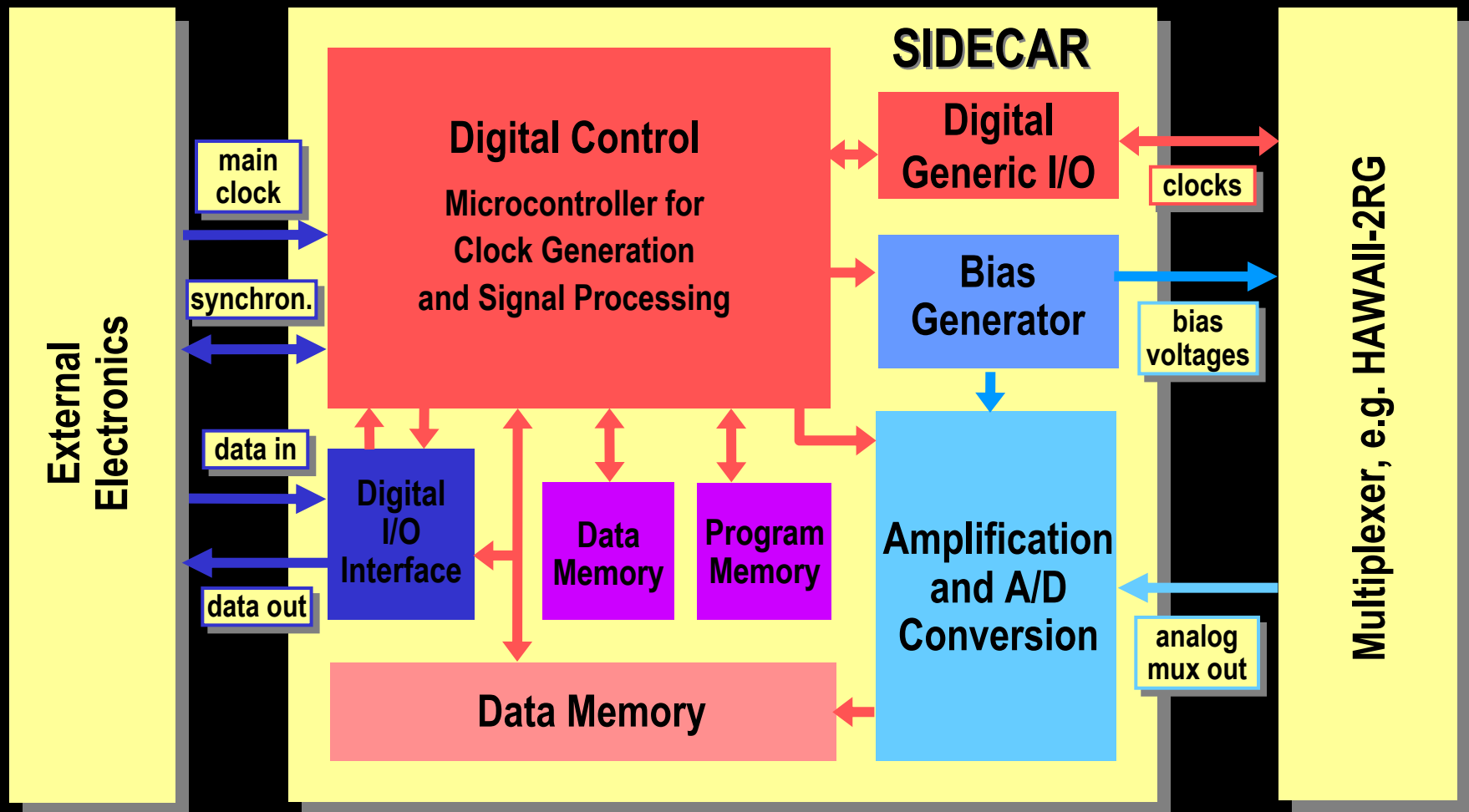


1% volume
1% power
less hassle

SIDECAR: **S**ystem for **I**mage **D**igitization, **E**nhancement, **C**ontrol **A**nd **R**etrieval

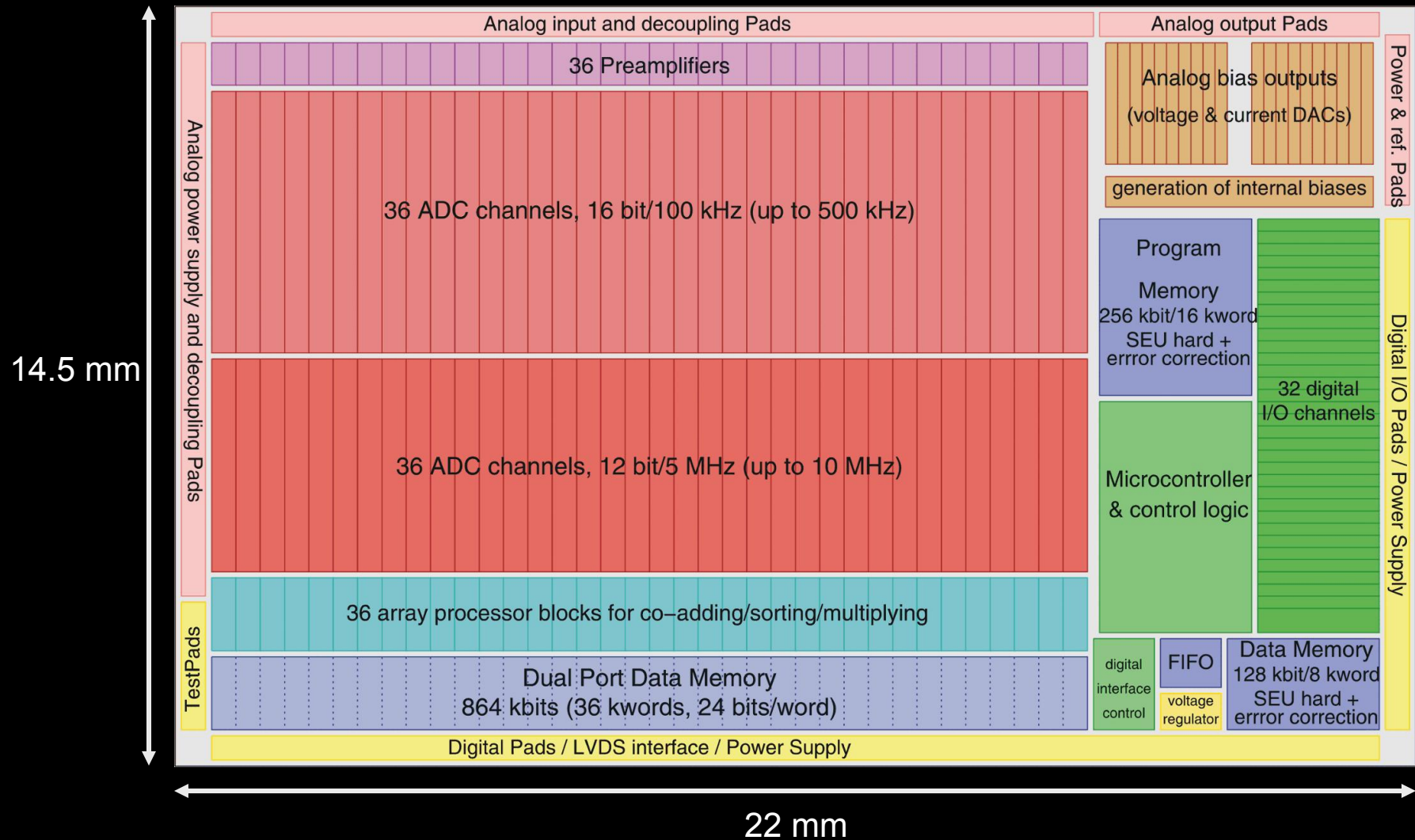
Teledyne Imaging Sensors

SIDECAR ASIC Functionality



Teledyne Imaging Sensors

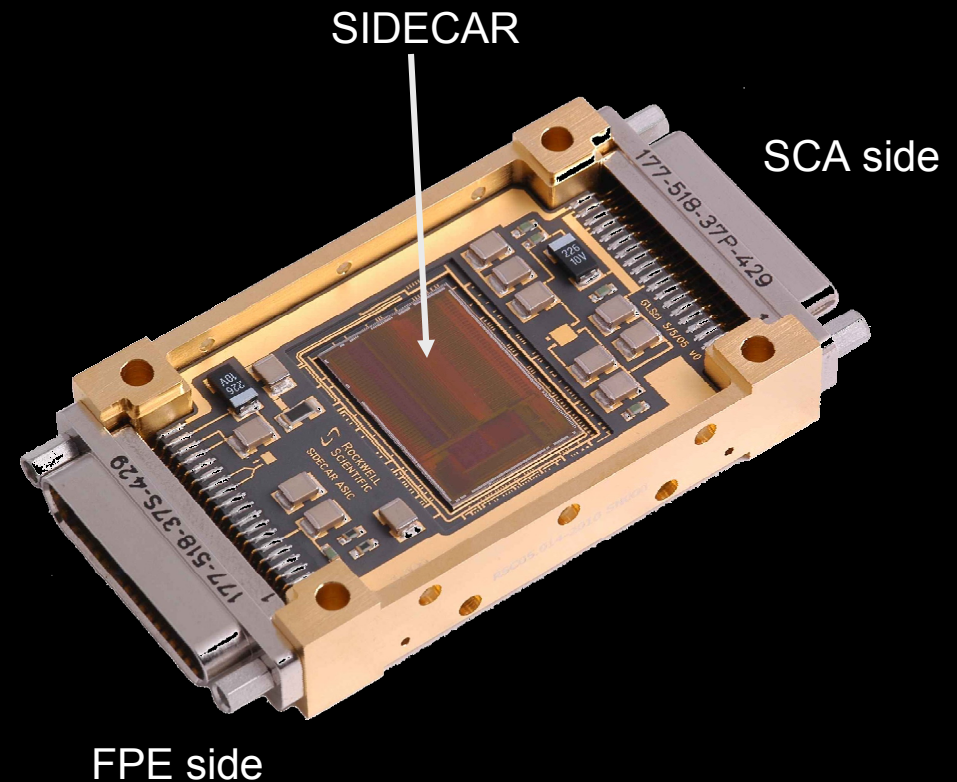
SIDECAR ASIC Floorplan



Teledyne Imaging Sensors

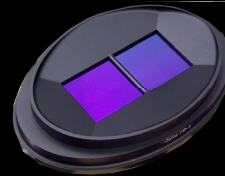
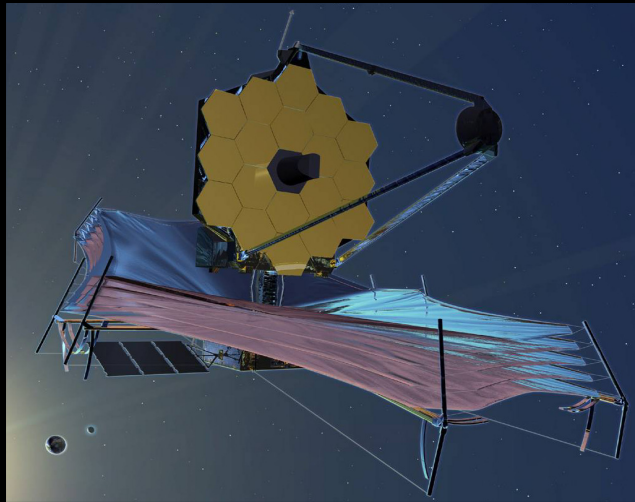
SIDECAR ASIC Flight Package for JWST

- Ceramic board with ASIC die and decoupling caps
- Invar box with top and bottom lid
- Two 37-pin MDM connectors
 - FPE-to-ASIC connection
 - ASIC-to-SCA connection
- Qualified to NASA Technology Readiness Level 6 (TRL-6)
- <15 mW power when reading out of four ports in parallel, with 16 bit digitization at 100 kHz per port.

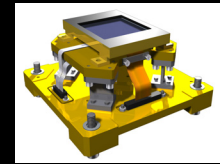
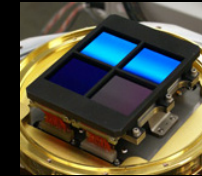
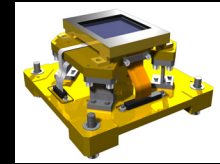
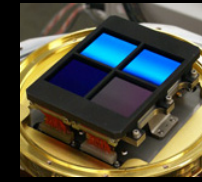


James Webb Space Telescope

15 H2RG 2K×2K infrared arrays on board (63 million pixels)



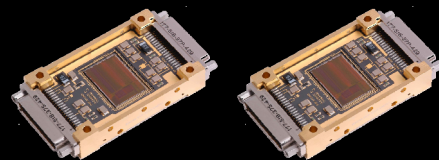
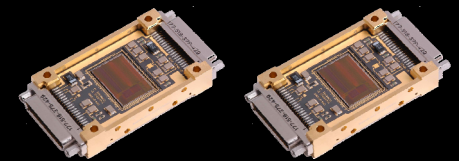
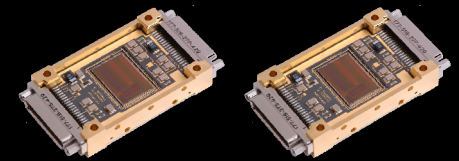
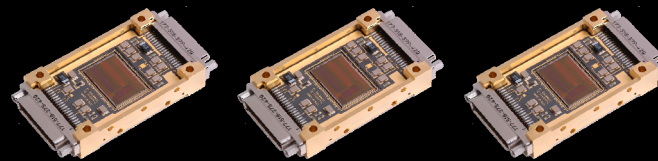
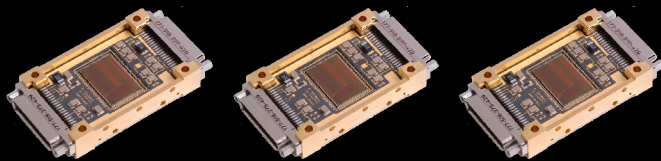
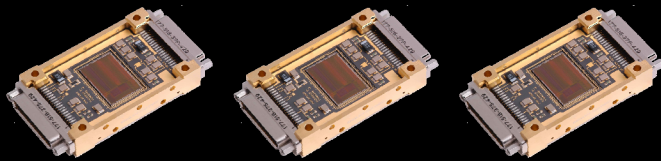
NIRSpec
(Near Infrared Spectrograph)
<6 e- noise for 1000 sec exposure



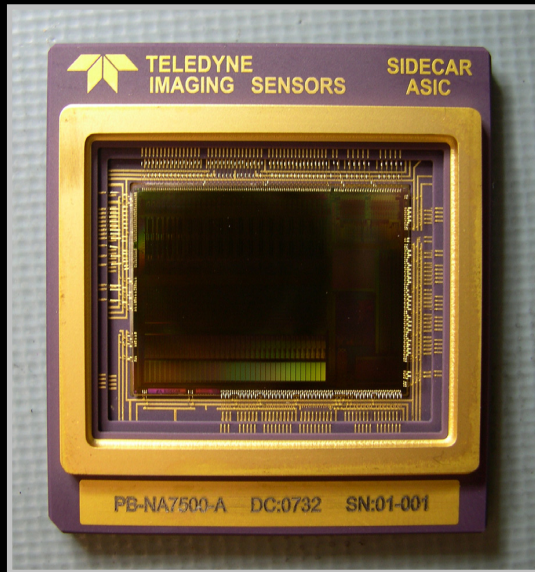
NIRCam
(Near Infrared Camera)



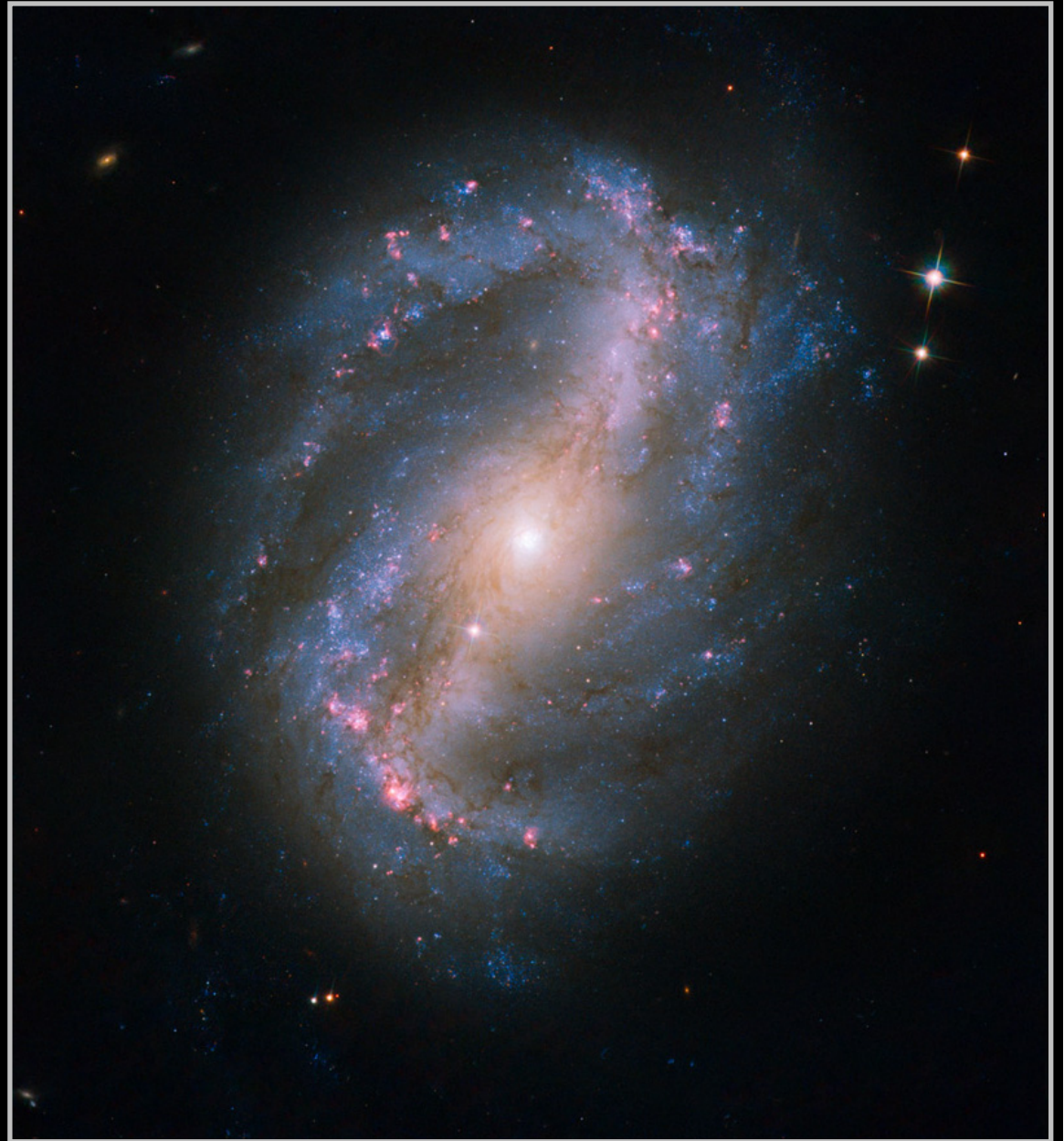
FGS
(Fine Guidance Sensors)



Hubble Servicing Mission 4



Repair of the
Advanced Camera for Surveys
(ACS)
Teledyne SIDE CAR ASIC



HxRG – SIDECAR ASIC Package Development

One modular approach for all applications:

- Silicon Carbide (SiC) carrier for visible and substrate removed IR focal planes
- Rigid-flex cable with wirebond pads and with passives for flight or ground-based application

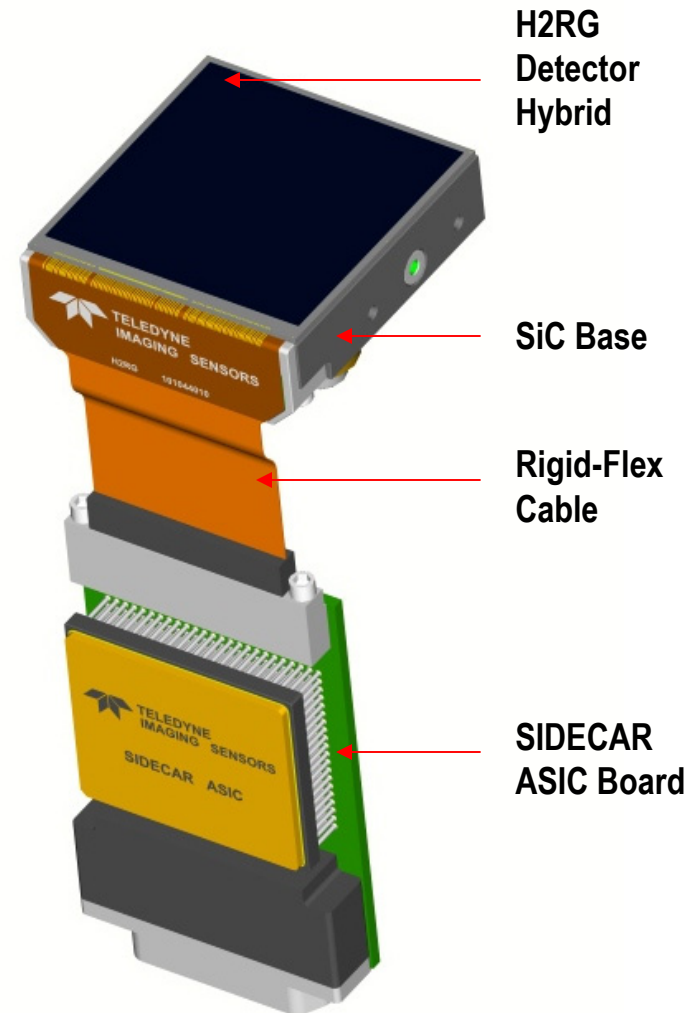
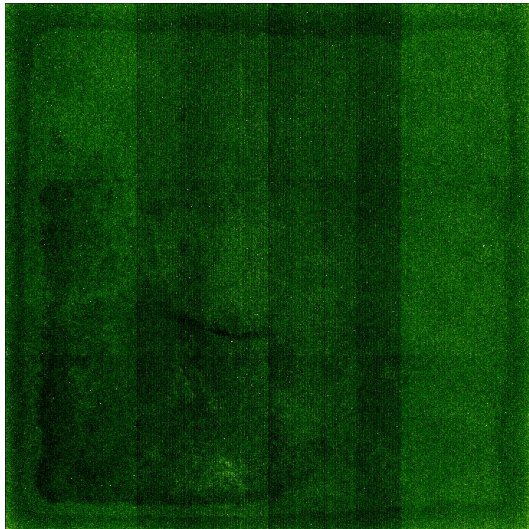


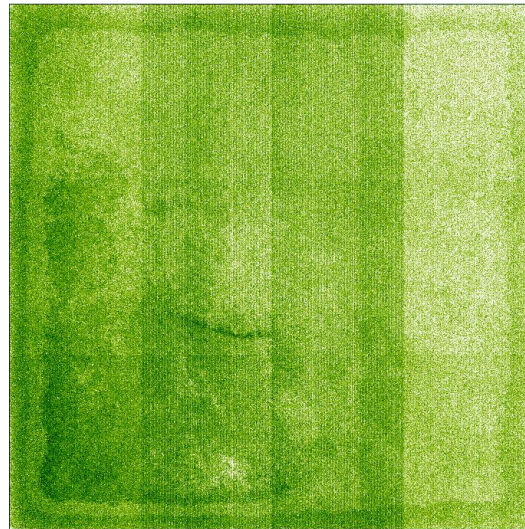
Image Data of H2RG + HgCdTe Detector

Chart 83

- Typical 2.5 μm cutoff detector
- Images taken under weak flat field illumination (non-uniform)
- All images shown at the same scaling factor



Raw frame
(1st read after reset)



Raw frame
(2nd read after reset)



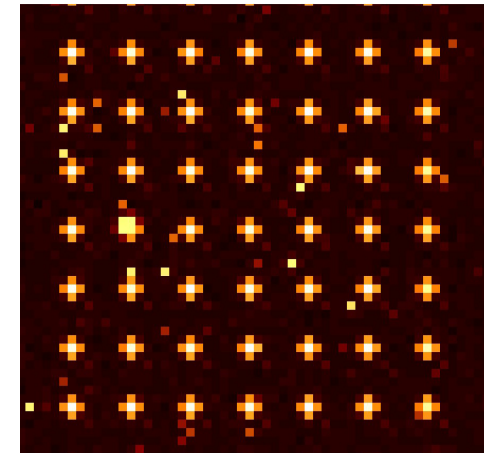
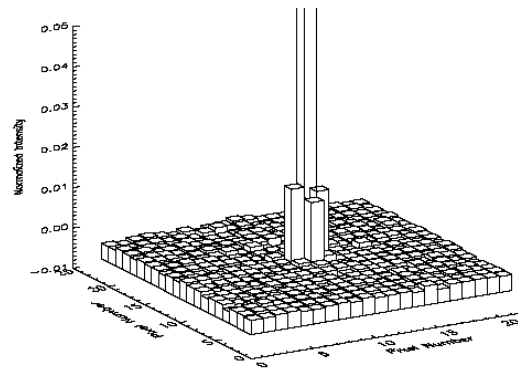
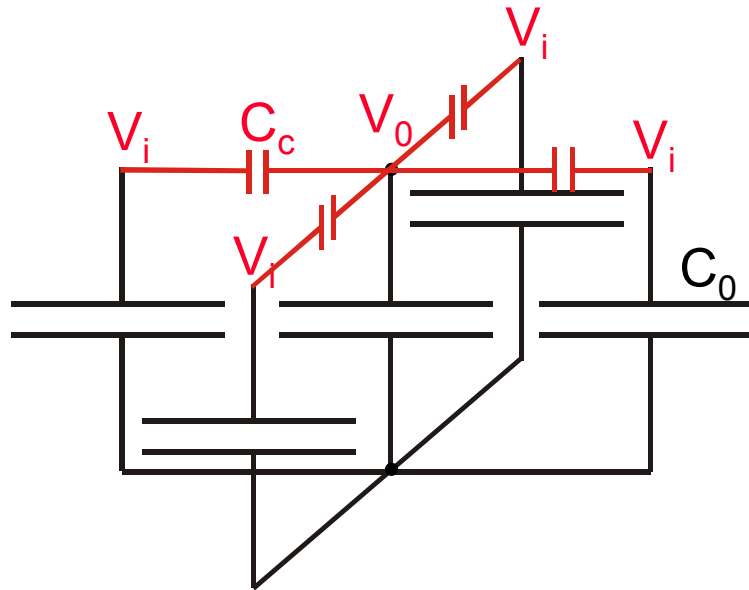
Correlated Double Sample
(2nd – 1st read)
Removes all offset artifacts

Non-Ideal Sensor Attributes

**Inter-Pixel Capacitance
Persistence (latent image)**

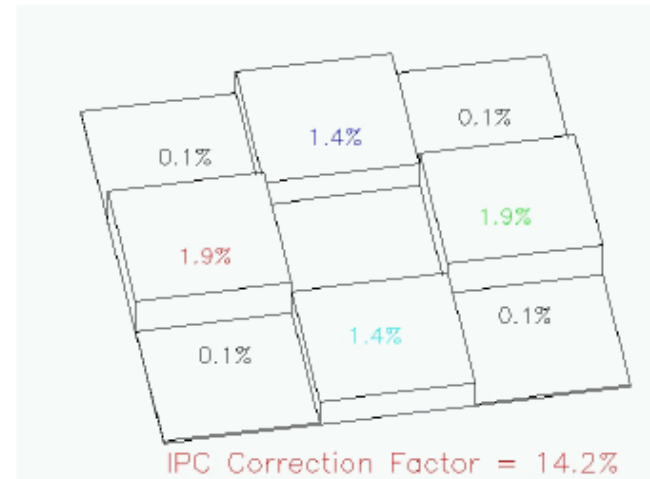
Interpixel Capacitance (IPC)

Chart 85



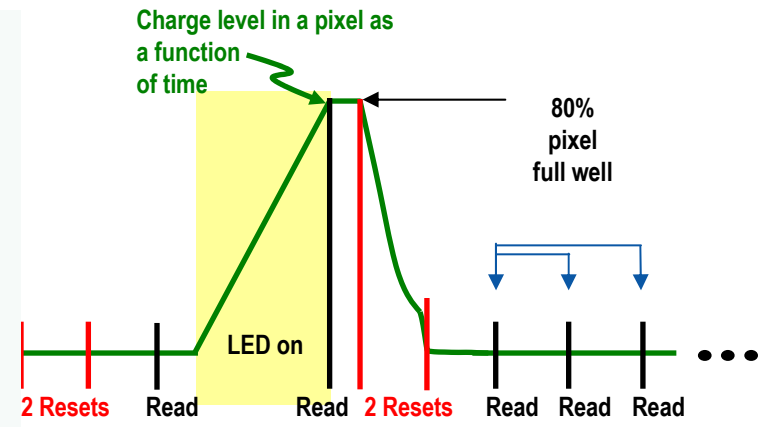
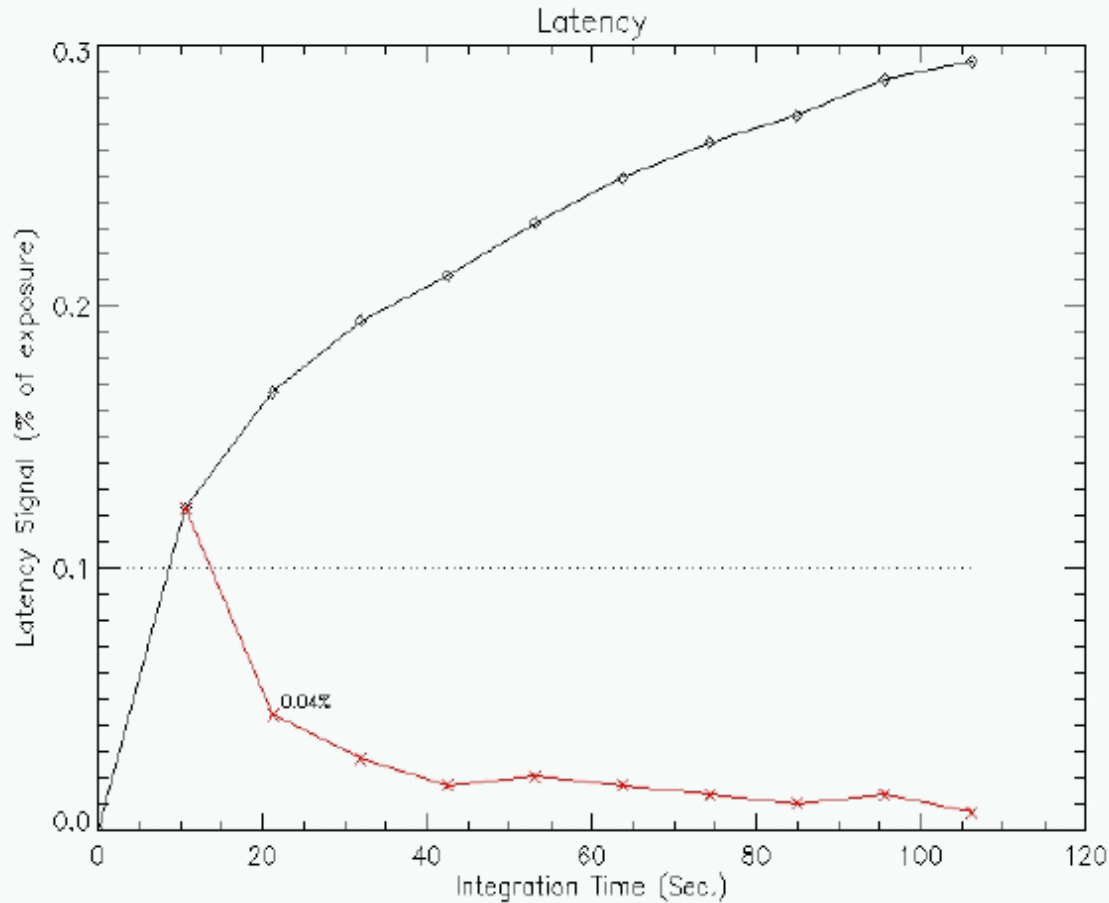
Single Pixel Resets

- C_0 node capacity of pixel
- Coupling capacitance C_c ($x = C_c/C_0$)
- Apparent capacitance for shot noise: $C=C_0(5x+1)/(x+1)$
- $V_0+4V_i = V$
- Photometry conserved
- For uniform illumination no signal charge stored on C_c
- C_c reduces noise, but also sharpness and contrast



Residual Image (CDS Latency)

Chart 86



The latent image is the CDS signal measured on the second frame (i.e., the difference of the first latent frame from the second latent frame) after performing 2 resets following the removal of the illumination source. Integration time for each post-exposure frame is equal to the integration time used to provide the ~80% full well signal frame.

Cumulative and differential signal as percent of illumination signal vs. time is shown.

Example Test Measurements

Interconnect

Operable Pixels

Quantum Efficiency

Single Correlated Double Sample (CDS) Readout Noise

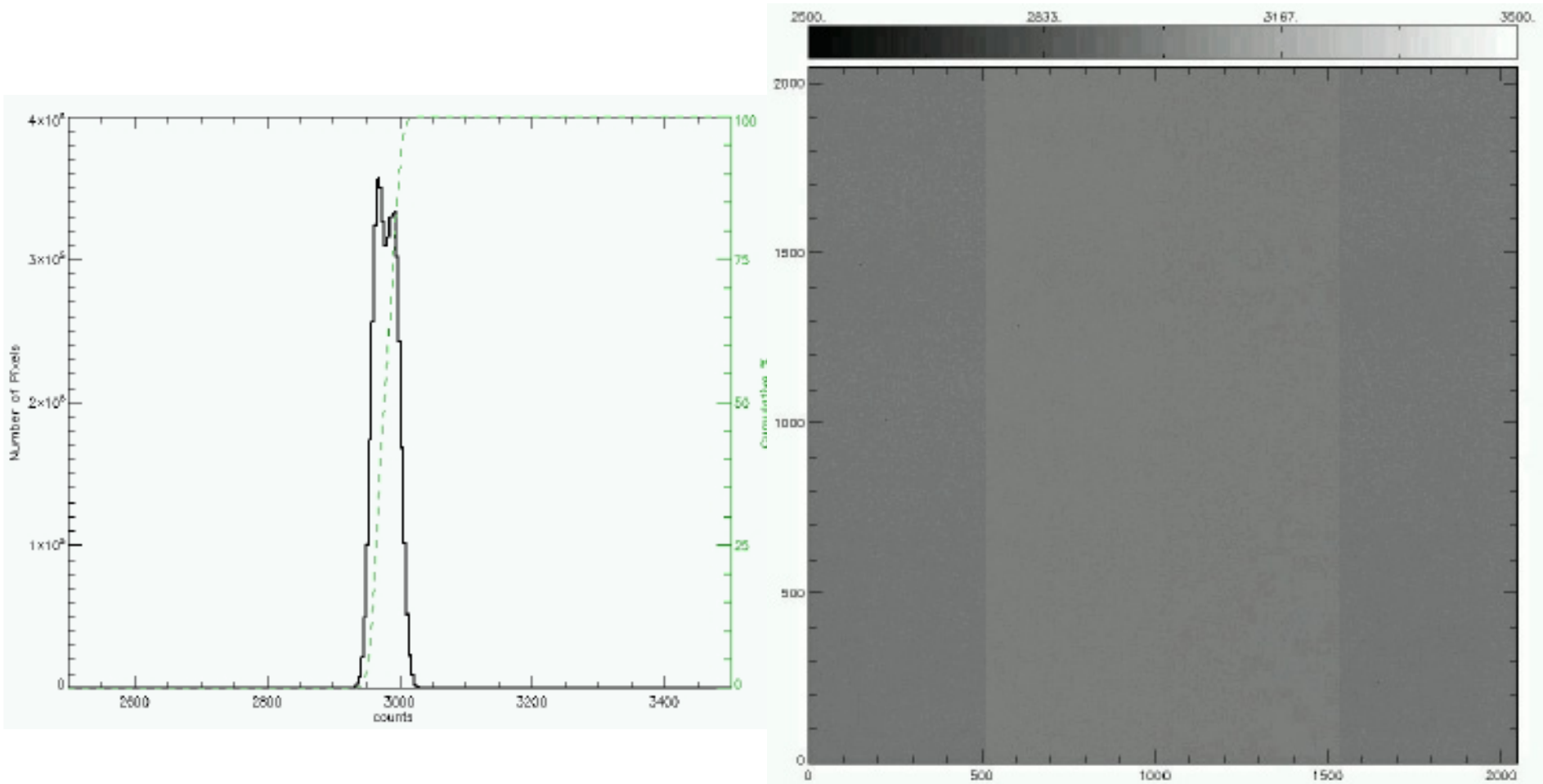
Readout Noise after multiple sampling

Dark current

Well depth

Interconnect at Room Temperature – nearly perfect

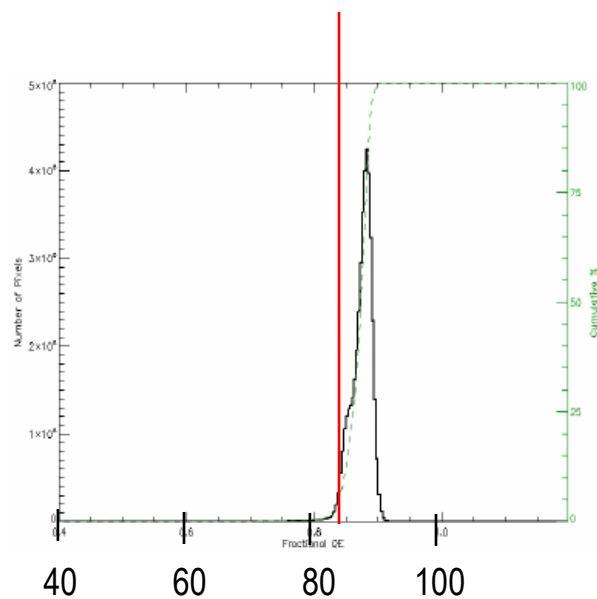
Chart 88



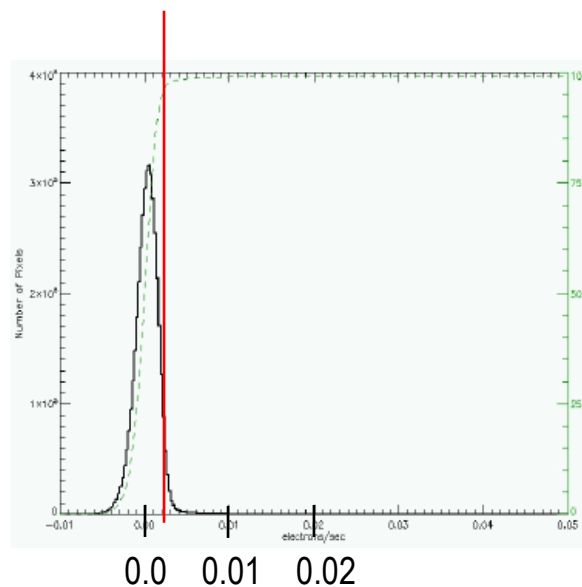
Operable Pixels

Chart 89

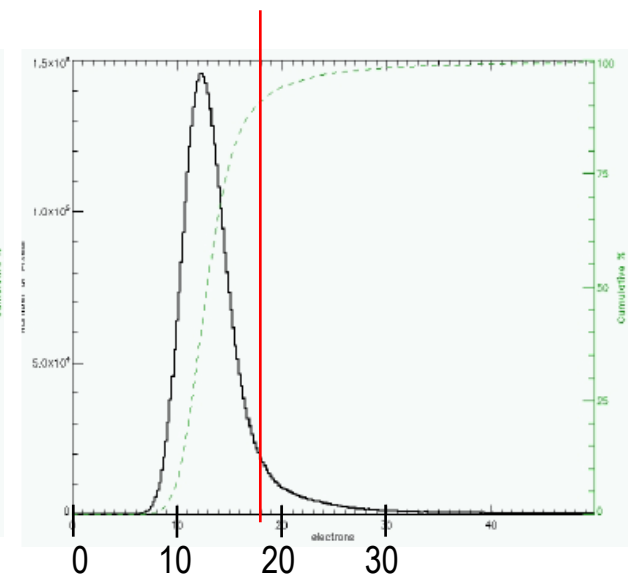
- To be operable, a pixel must pass all 3 criteria: quantum efficiency, dark current and single CDS readout noise
- Difference between the mean value and 90% operability level:
 - 3-4% for quantum efficiency
 - ~ 0.01 e-/pix/sec for dark current
 - 4-5 e- for readout noise



Quantum Efficiency (%)



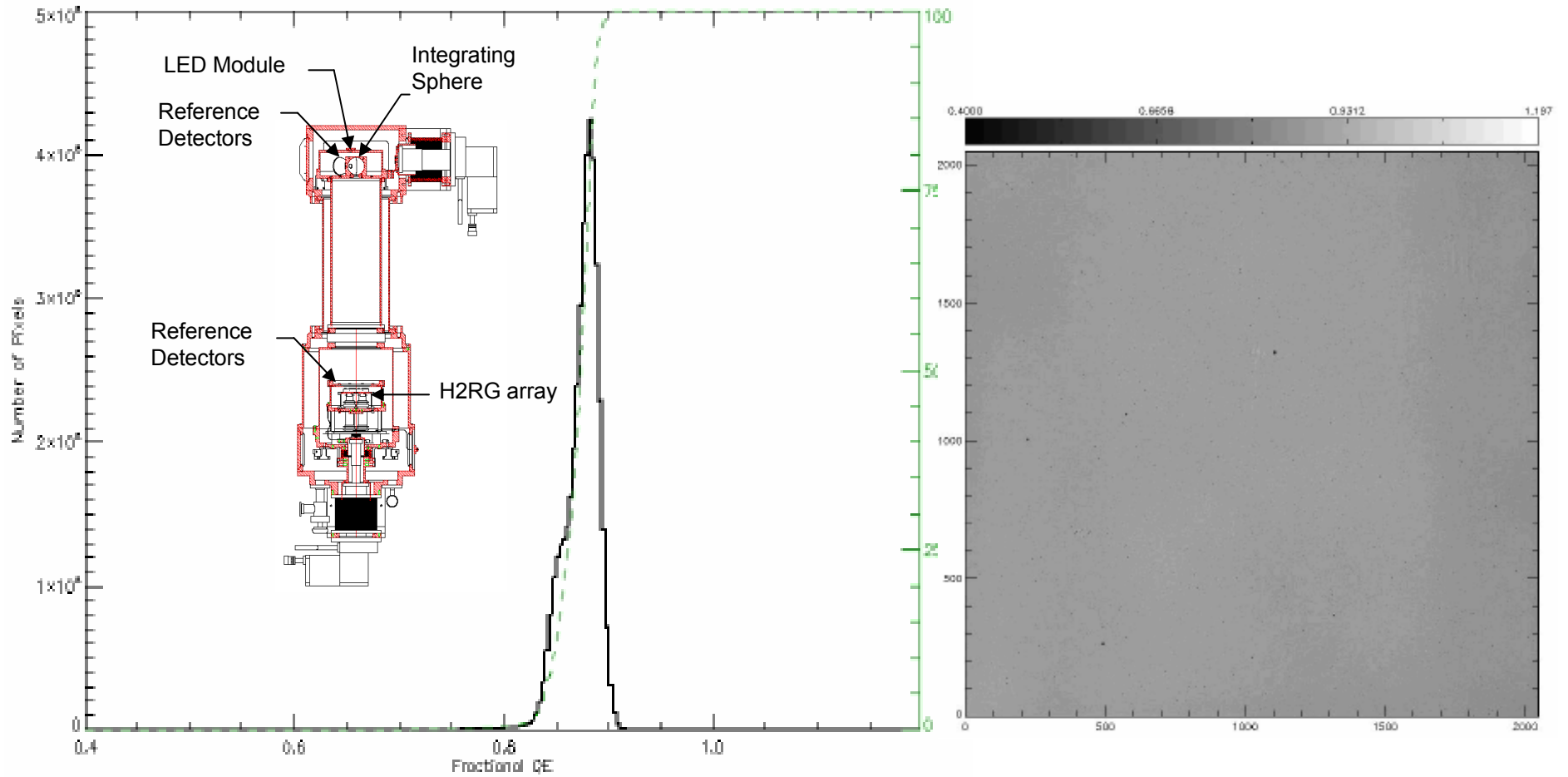
Dark Current (e-/pix/sec)



Readout Noise (e-)

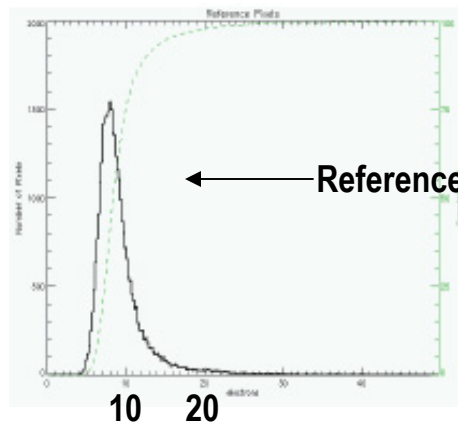
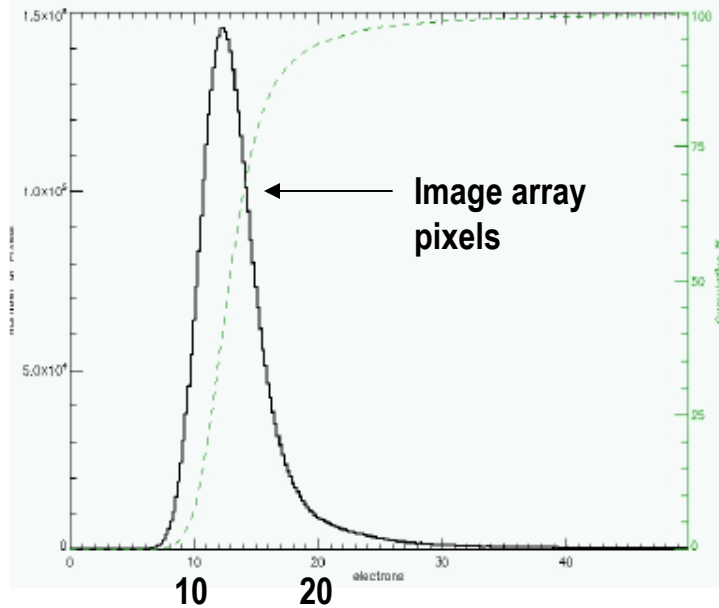
Quantum Efficiency

Chart 90



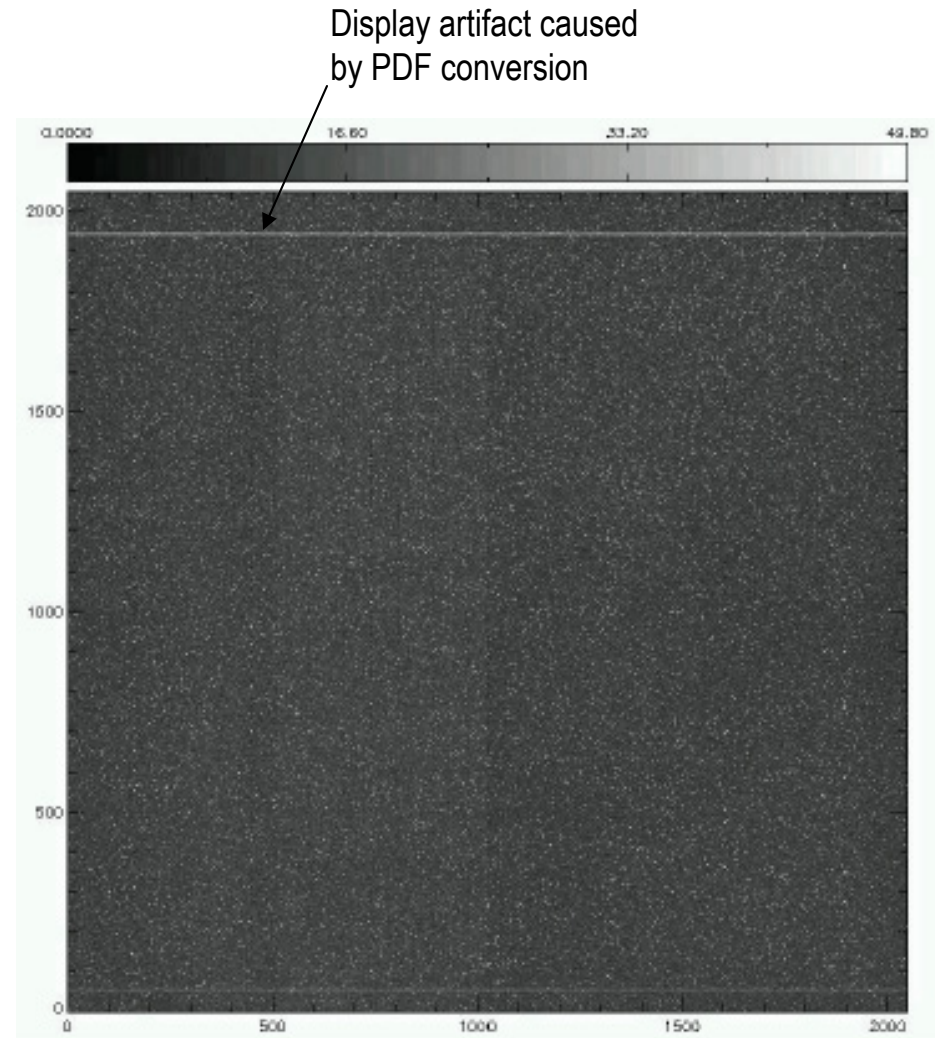
Single Correlated Double Sample (CDS) Read Noise

CDS from two subsequent frames, i.e. 10.6 sec.



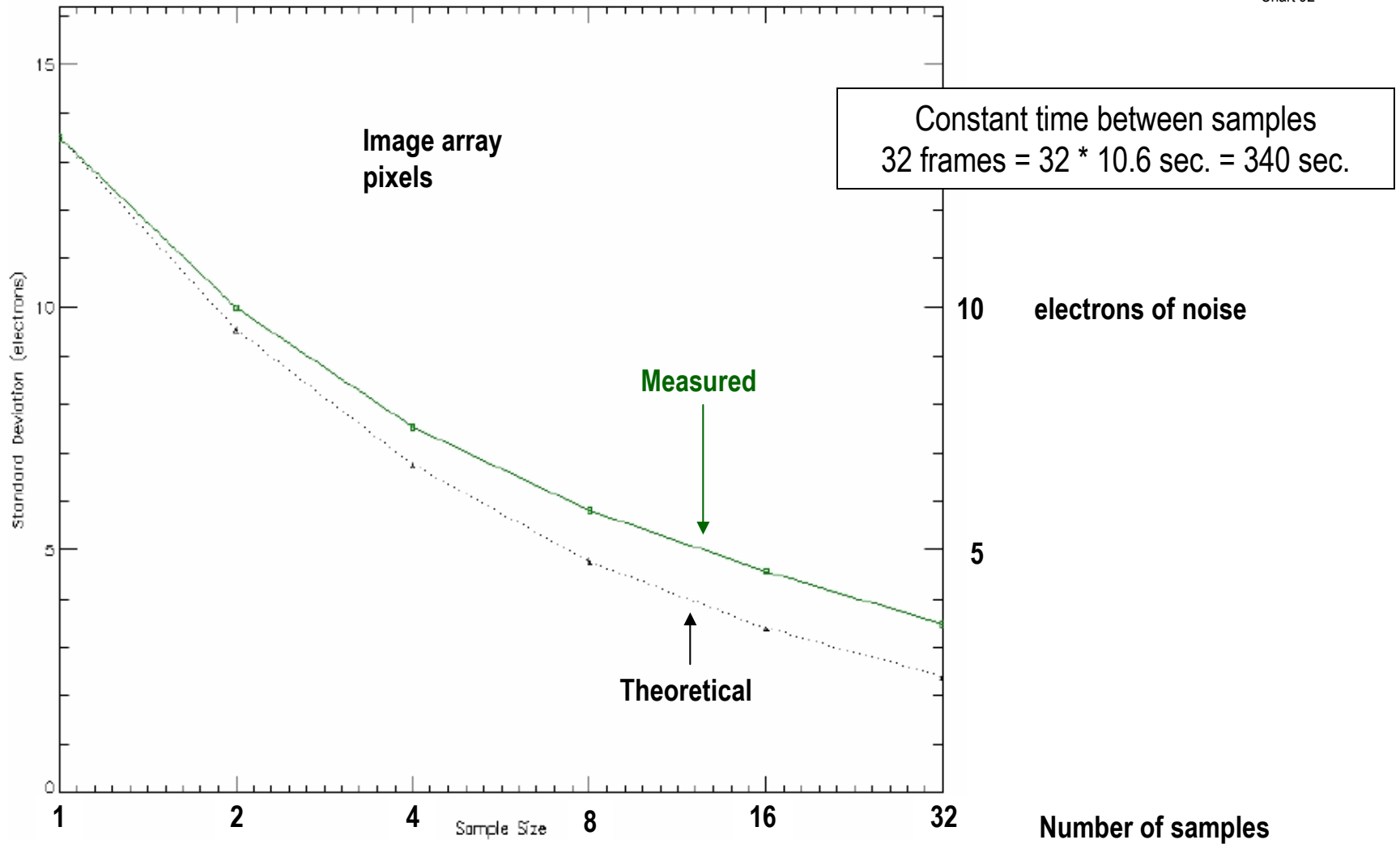
electrons
noise

Chart 91

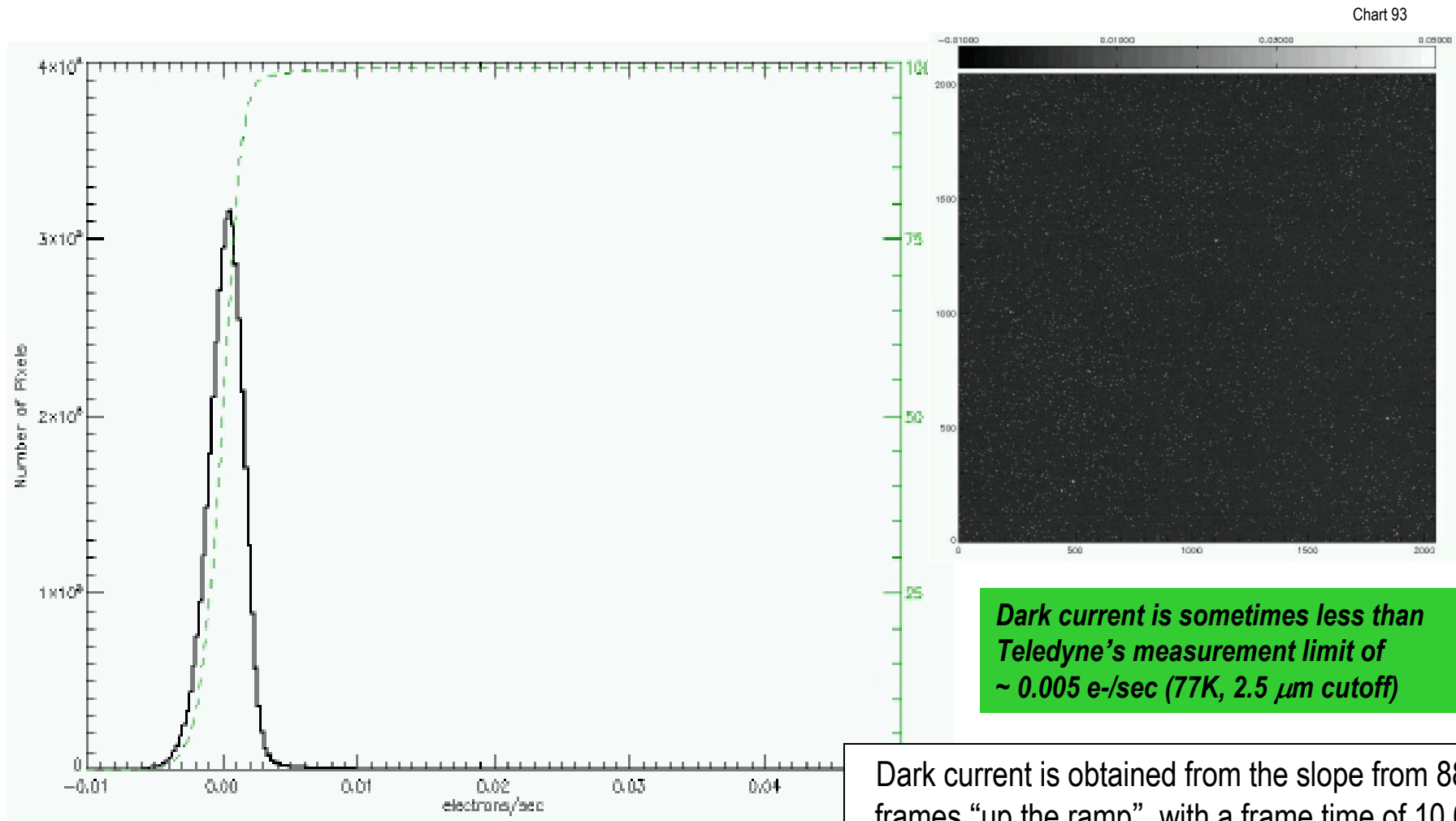


Readout Noise after multiple sampling

Chart 92



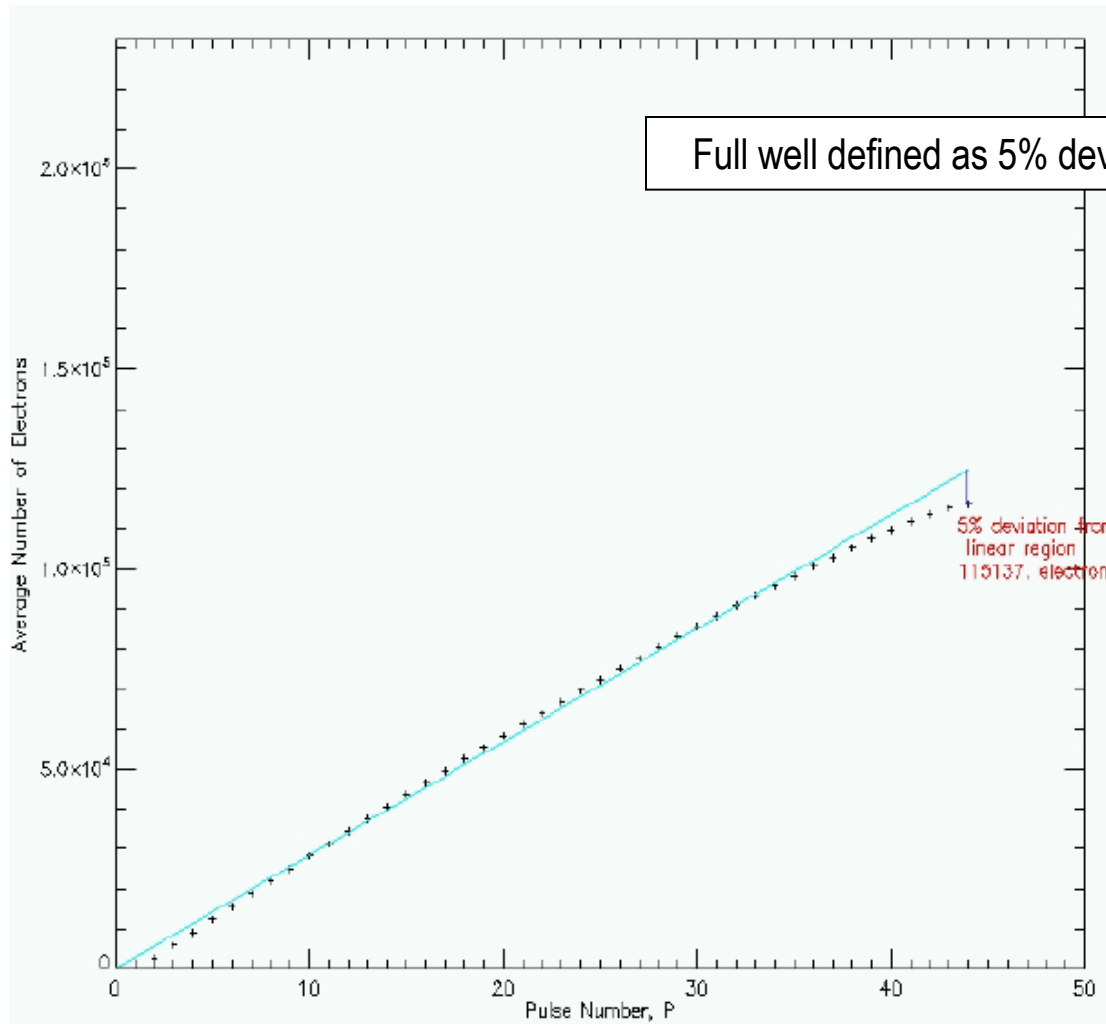
Dark Current



Dark current is obtained from the slope from 88 frames "up the ramp", with a frame time of 10.6 seconds, averaged over 50 ramps

Well Depth

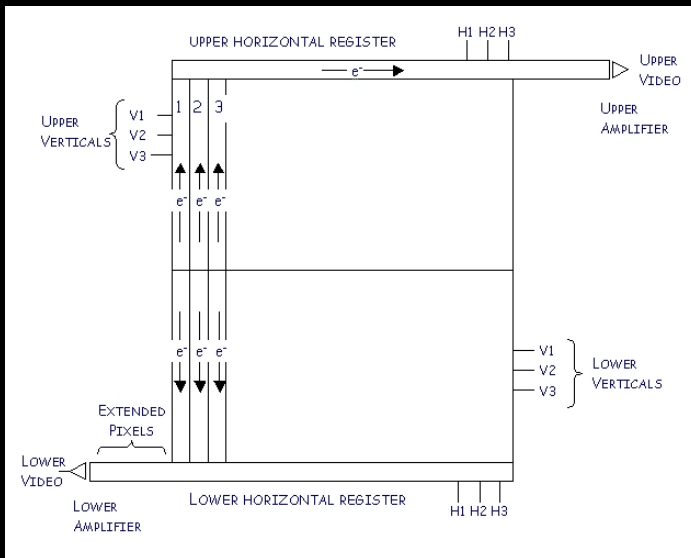
Chart 94



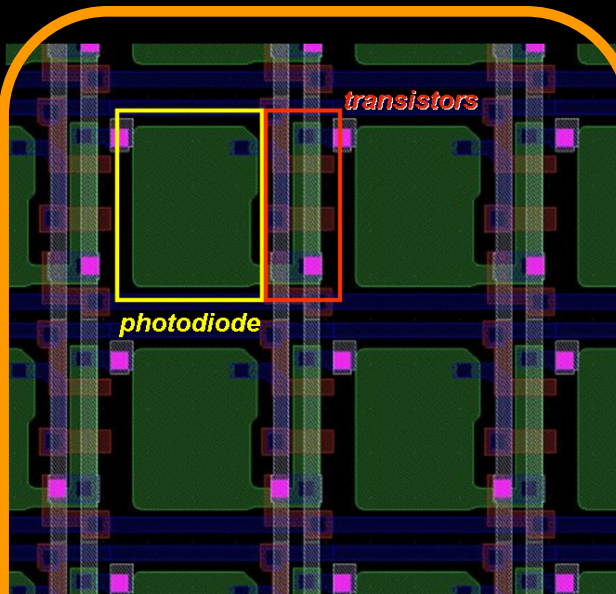
**In this example
Full Well: 115,000 e-**

Other things to consider with IR arrays

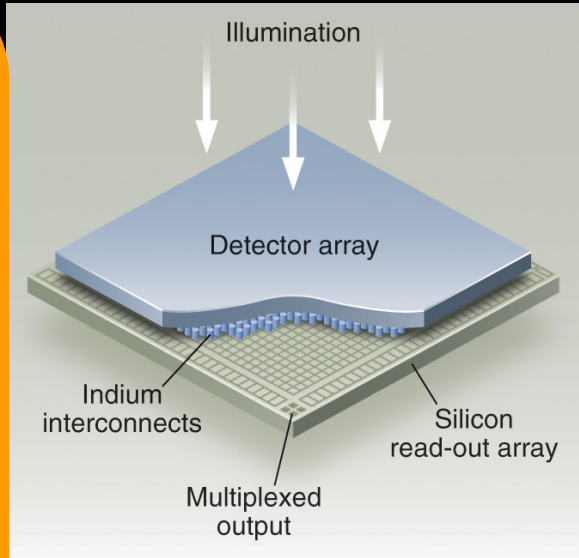
- Source follower (MOSFET) is simplest type of charge-to-voltage converter
- Capacitive Trans-Impedance Amplifier (CTIA), akin to an operational amplifier, has several good properties:
 - VERY linear
 - No inter-pixel capacitance (IPC)
 - Can have very large full well capacity (1–10 million electrons)
- 1.75 micron cutoff H2RG HgCdTe arrays get higher readout noise than 2.5 micron cutoff.
 - 2.5 micron: 12-14 e- single CDS (best is <10 e-)
 - 1.75 micron: 20-25 e- single CDS
- For H2RG, gap between individual sensor chip assemblies (SCAs) is 3 mm on 3-sides, 6 mm on bond pad side



CCD



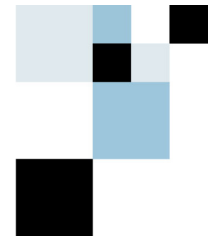
Monolithic CMOS



Hybrid CMOS

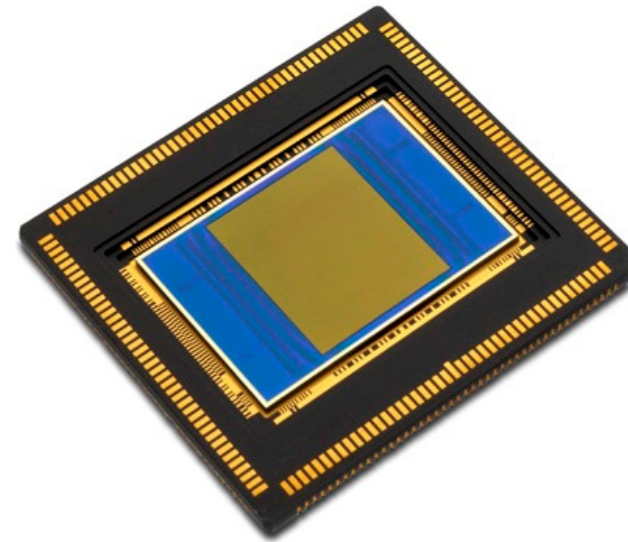
HgCdTe
Visible through IR

Silicon - Visible through near IR



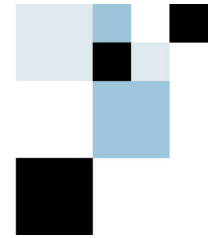
CIS2051 5.5M Pixel Image Sensor

- 6.5 μm^2 5T pixel architecture
- 2560(H) x 2160(V) imaging array
- Dual gain 11-bit output channels
- 100 fps in rolling shutter readout
- 50 fps in global shutter readout
- Read noise < 2e- rms at 30 fps
- Dynamic range > 83 dB (15000:1)
- QE > 55% at 600 nm
- Dark current at 20°C 3 pA/cm²

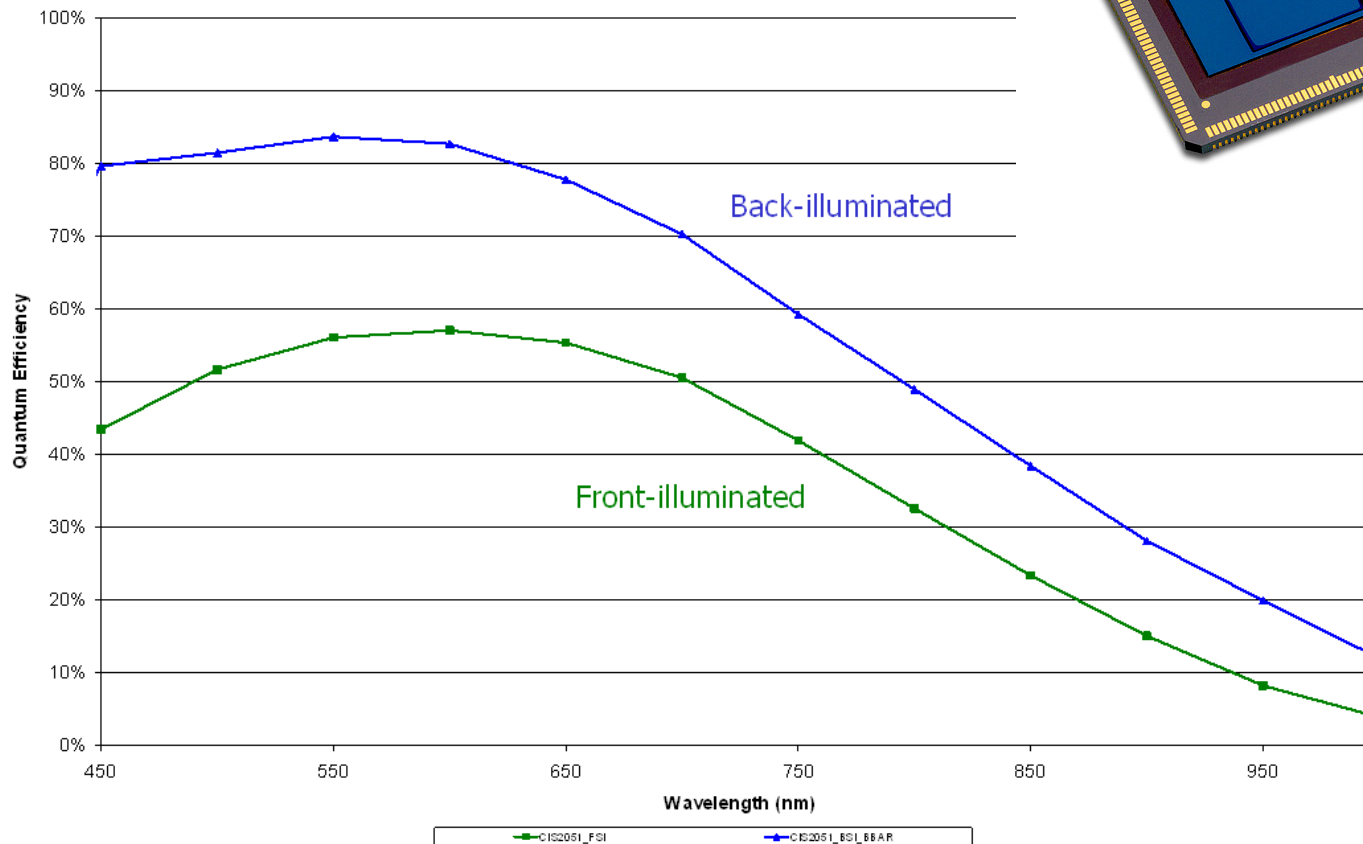
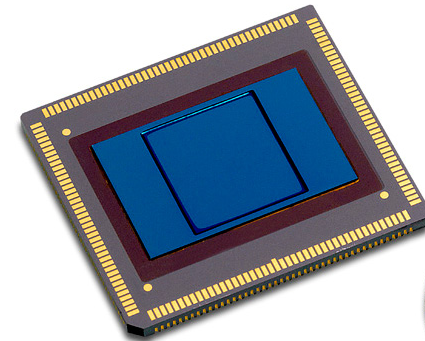


Back-Illuminated CIS2051

Fairchild Imaging

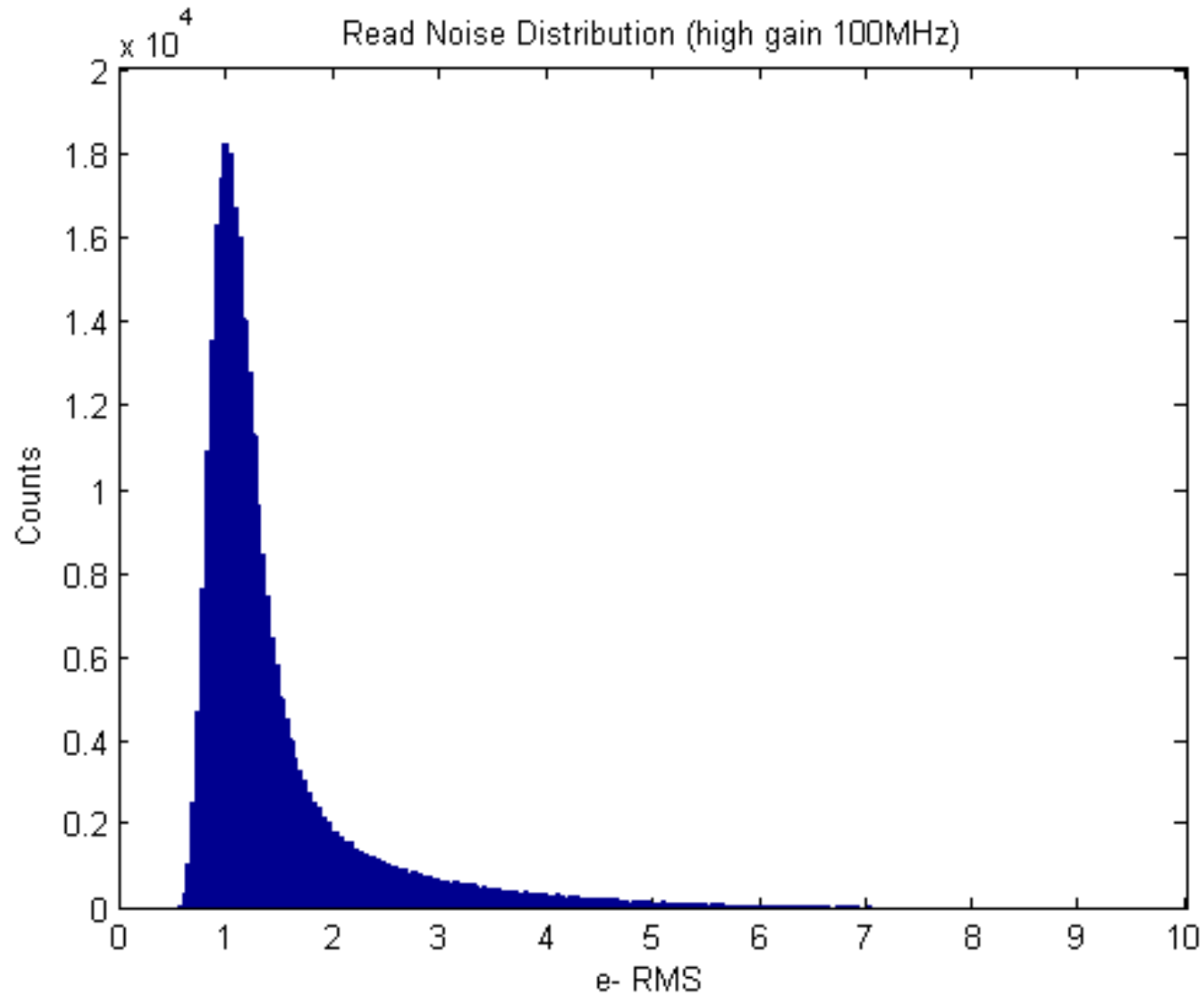
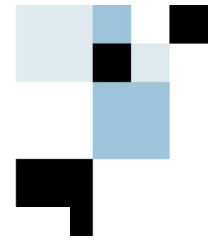


- Imaging area thinned to epi thickness (5 μm)
- QE > 83% at 550 nm
- Dark current at 20°C < 8 pA/cm²
- Read noise < 2e⁻ at 100 MHz



CIS2051 Read Noise Distribution (High gain 100MHz)

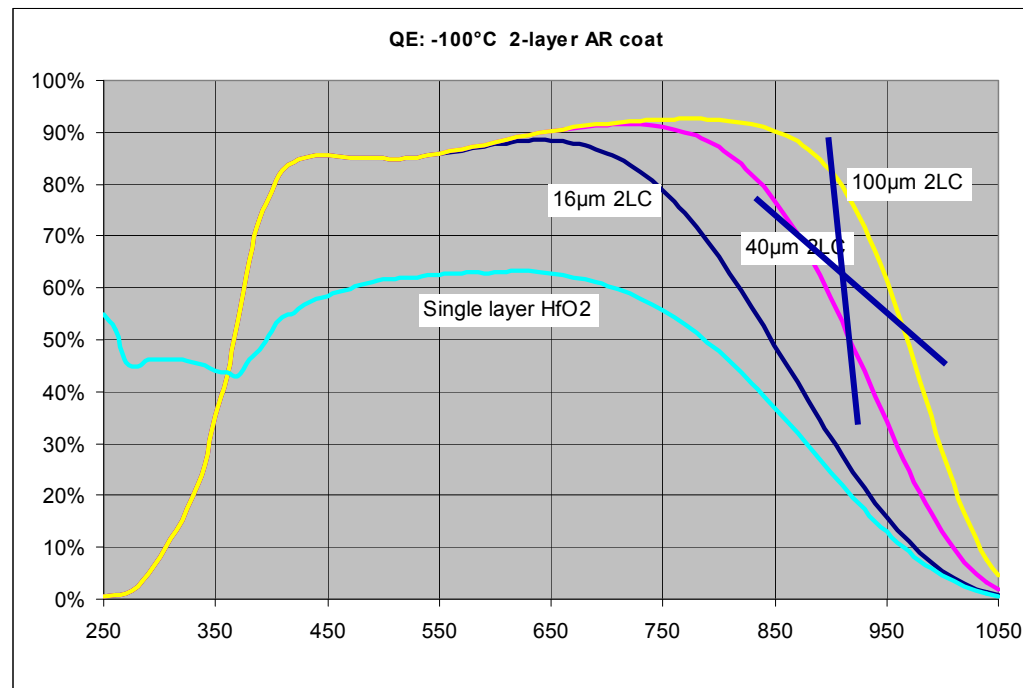
Fairchild
Imaging



CMOS Backthinning

e2v

CMOS Wafers have been thinned from Tower, UMC and IBM. All behave much as expected. The only issue has been the epi starting thickness QE obtained in the red has not yet matched that available from CCDs. We're working with thicker, higher resistivity epi to improve red response

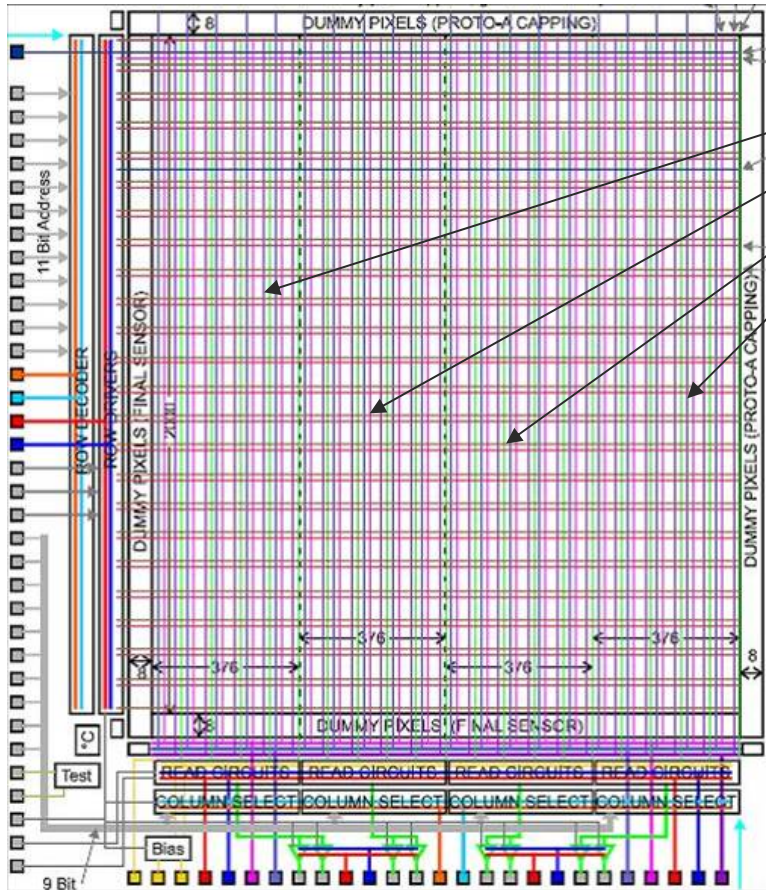


We have space qualified front illuminated CMOS sensors. The next step is to space qualify a backthinned CMOS sensor

- Part funded development : Phase 1
- The development sensor is $\frac{1}{4}$ of the final 12 MPixel device
- Development sensor includes both 3T and 4T pixels (7 μ m pitch).
- Schematic layout is shown on the following slide
- Each 3 MPixel segment has 4 analogue outputs
 - (Analogue preferred by some customers: more flexible)
- **Timescale**
 - Tape-out was in March 2010
 - Frontside illuminated Silicon available July 2010
 - Backside illuminated silicon characterisation completed in Oct 2010

Large area Science imager

e2v



1500 x 2000 pixels.
Different areas have 3T and 4T pixels, with optimisation for low noise or high signal handling,

We expect, for example:
90ke- FWC with 45e- read noise
Or
70ke- FWC with 10e- read noise
Or
15ke- FWC with 5e- read noise

In the PHASE 2 development, this scales up to a full size device

Large area Science imager



Phase 2

The 12MPixel device will be a composite of four 3 MPixel devices

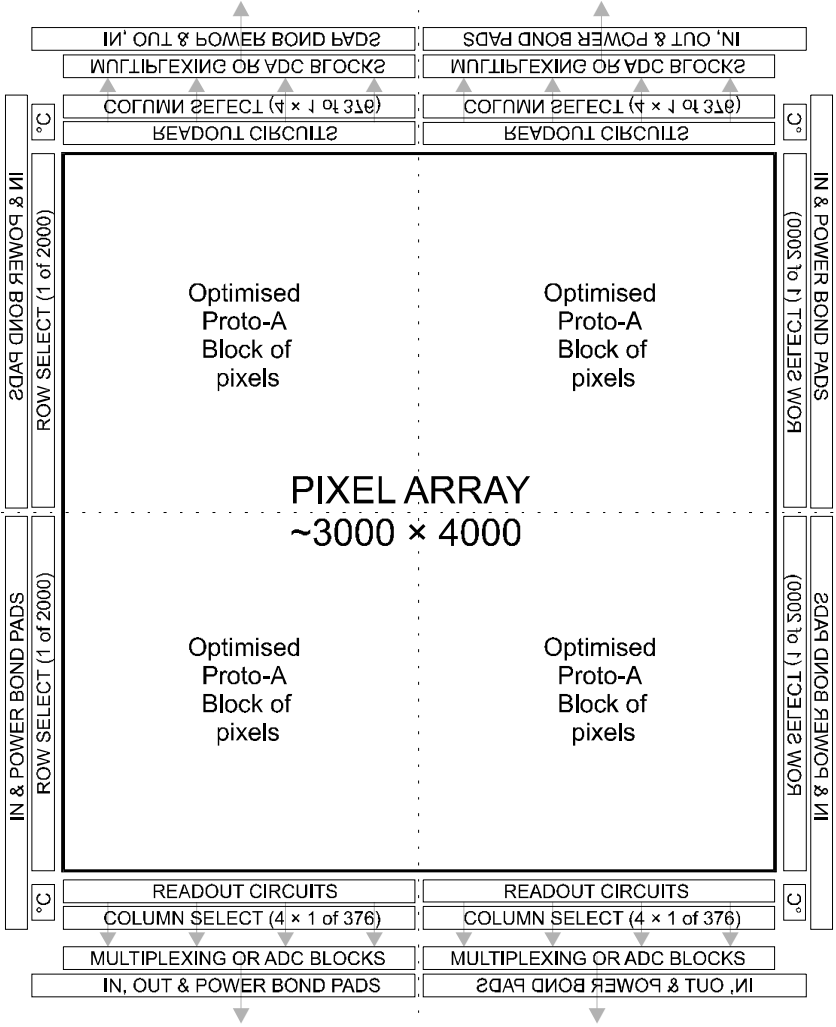
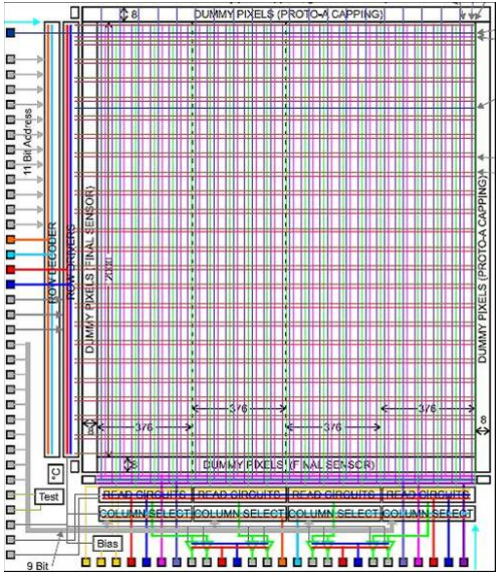
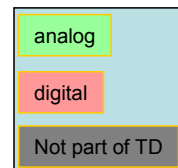
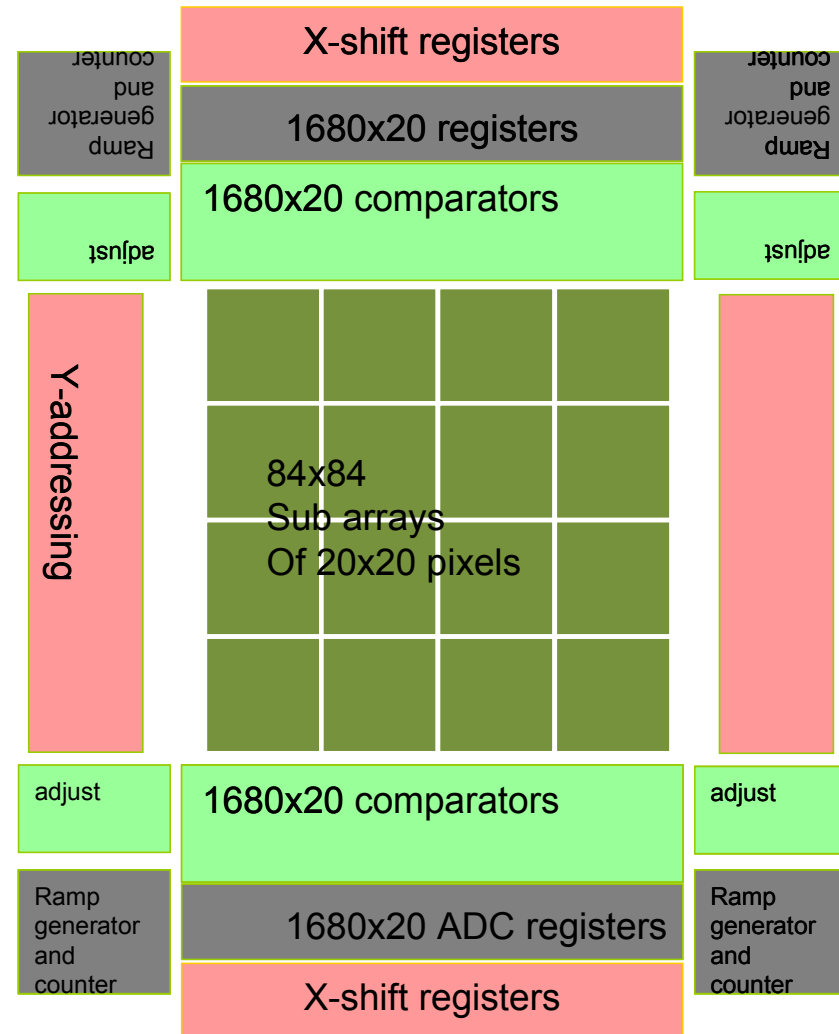


Image Sensors for Planetary Exploration

3 Mega-pixel Wavefront Sensor for the E-ELT

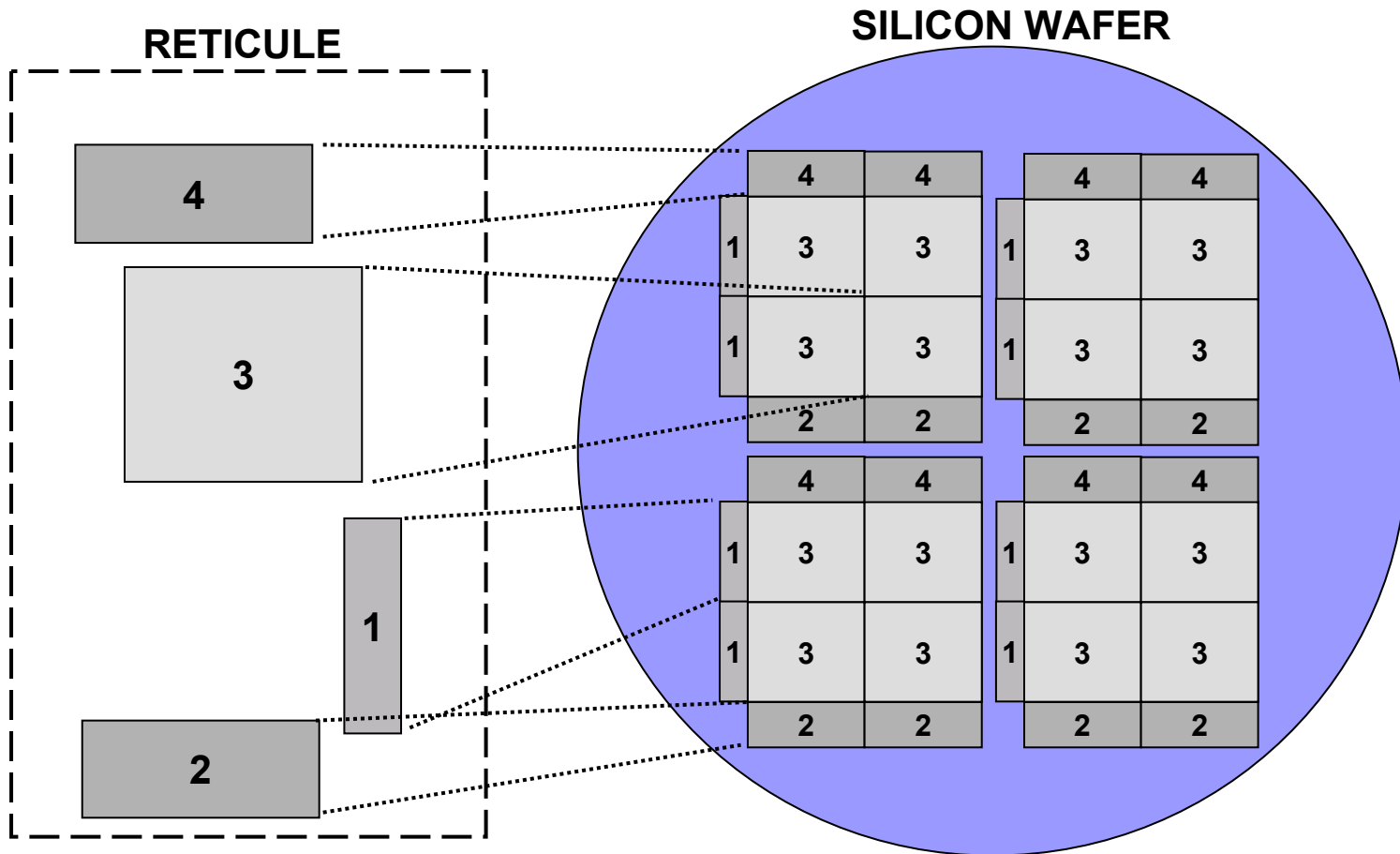
e2v

- 1680×1680 pixels
- 24 μm square pixels
- Up to 1000 frames/sec (fps)
- <3e- total noise at 700 fps
- Fully digital sensor
- 40 (9-bit) ADCs per column (a total of 68,000 ADCs)



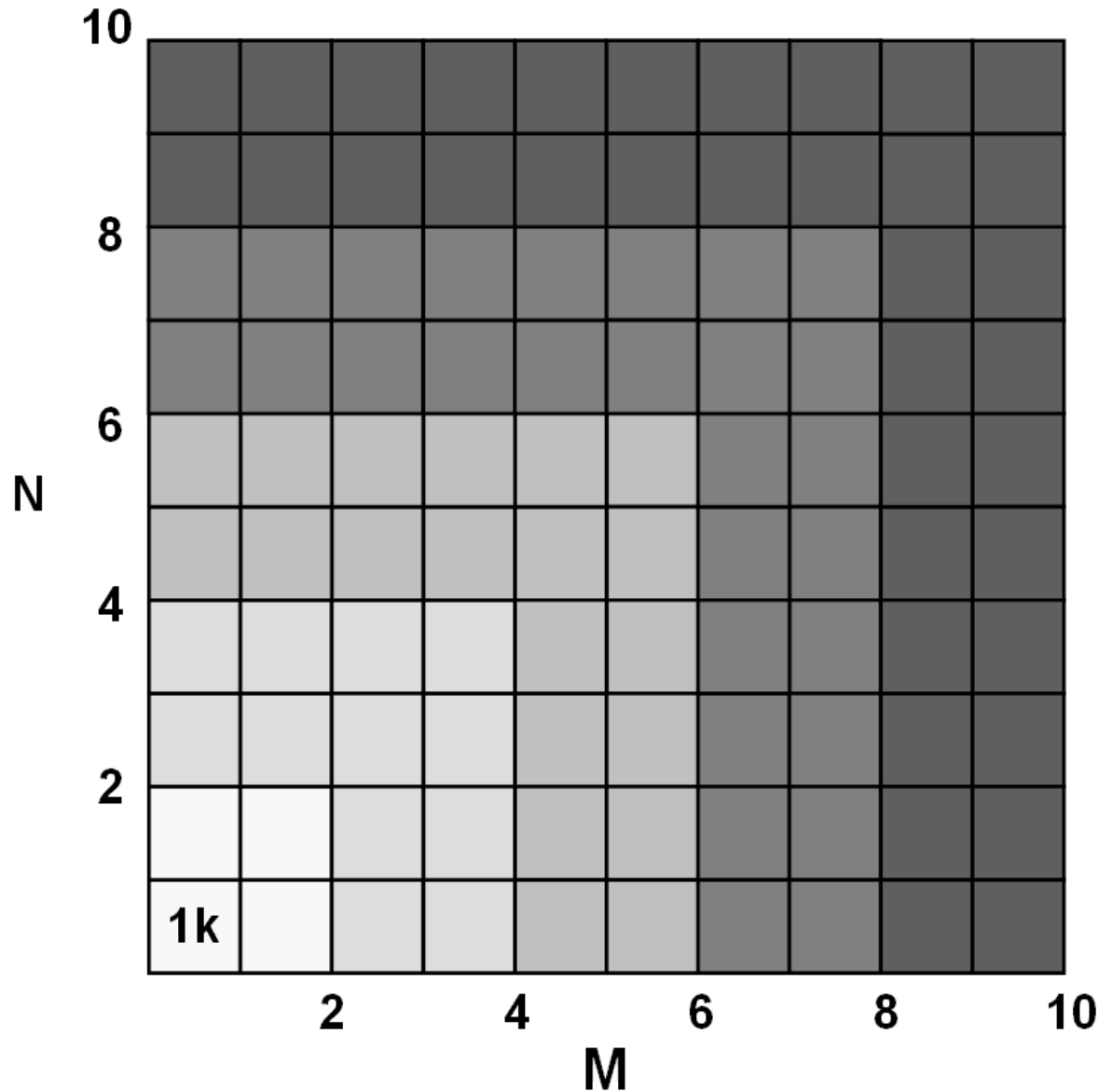


CMOS STITCHING





Mk (H) x Nk (V) x 10um IMAGERS



**10k x 10k x 10µm
COLOSSAL MINIMAL
IMAGER CURRENTLY
BEING DESIGNED.**

Thank you for your attention



Teledyne

Enabling humankind to understand the Universe and our place in it